

Permit ID: 5-4154-00002/01743

Renewal Number: 1

Modification Number: 3 07/01/2011

Facility Identification Data

Name: MOMENTIVE PERFORMANCE MATERIALS

Address: 260 HUDSON RIVER RD

WATERFORD, NY 12188

Owner/Firm

Name: MPM SILICONES LLC Address: 260 HUDSON RIVER RD WATERFORD, NY 12188, USA

Owner Classification: Corporation/Partnership

Permit Contacts

Division of Environmental Permits: Name: W RICHARD SPEIDEL Address: NYSDEC 232 GOLF COURSE RD WARRENSBURG, NY 12885

Phone:5186231281

Division of Air Resources: Name: STEPHEN J BARLOW Address: NYSDEC

232 GOLF COURSE RD WARRENSBURG, NY 12885

Phone:5186231212

Air Permitting Contact: Name: RUTH YEOMANS

Address: MOMENTIVE PERFORMANCE MATERIALS

260 HUDSON RIVER RD WATERFORD, NY 12188

Phone:5182335075

Permit Description Introduction

The Title V operating air permit is intended to be a document containing only enforceable terms and conditions as well as any additional information, such as the identification of emission units, emission points, emission sources and processes, that makes the terms meaningful. 40 CFR Part 70.7(a)(5) requires that each Title V permit have an accompanying "...statement that sets forth the legal and factual basis for the draft permit conditions". The purpose for this permit review report is to satisfy the above requirement by providing pertinent details regarding the permit/application data and permit conditions in a more easily understandable format. This report will also include background narrative and explanations of regulatory decisions made by the reviewer. It should be emphasized that this permit review report, while based on information contained in the permit, is a separate document and is not itself an enforceable term and condition of the permit.

Summary Description of Proposed Project

This is an administrative modification to restructure the permit in order to condense it. There are no actual changes to existing permitted conditions.



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Attainment Status

MOMENTIVE PERFORMANCE MATERIALS is located in the town of WATERFORD in the county of SARATOGA.

The attainment status for this location is provided below. (Areas classified as attainment are those that meet all ambient air quality standards for a designated criteria air pollutant.)

Criteria Pollutant

Attainment Status

Particulate Matter (PM)	ATTAINMENT
Particulate Matter< 10µ in diameter (PM10)	ATTAINMENT
Sulfur Dioxide (SO2)	ATTAINMENT
Ozone*	MARGINAL NON-ATTAINMENT
Oxides of Nitrogen (NOx)**	ATTAINMENT
Carbon Monoxide (CO)	ATTAINMENT

- * Ozone is regulated in terms of the emissions of volatile organic compounds (VOC) and/or oxides of nitrogen (NOx) which are ozone precursors.
- ** NOx has a separate ambient air quality standard in addition to being an ozone precursor.

Facility Description:

Momentive Performance Materials operates a silicone production facility (sic 2821) located in Saratoga County, New York, in the town of Waterford. The plant is approximately 12 miles north of Albany. The site produces silicone products and other materials including resins, fluids, dispersions, emulsions, heat curing elastomers, room temperature vulcanizing (rtv) elastomers and fumed silica. The site has continuous and batch chemicals processes, compounding, finishing and packaging operations, and steam generation capability.

Major emissions include: Carbon Monoxide (CO), Sulfur Dioxide (SO2), Volatile Organic Compounds (VOCs), Hazardous Air Pollutants (HAPs), Oxides of Nitrogen (NOx), Particulate Mater (PM) and Particulate Mater less than 10 microns (PM-10).

Emission unit listing and a brief description:

C-27018: This unit consists of the following production areas: Methyl Chloride, Gaseous Dihydrolysis (GDH), Liquid Dihydrolysis (LDH), Siloxane Oil, the Area 38 tank farm, the B30 Polykettle systems, and the B24A MQ Resin system. The unit also includes the following control devices and their associated equipment: the MCS Vent Incinerator, MCS Vent Scrubber, the Fixed Box (#2) Hazardous Waste Incinerator, and the Rotary Kiln Hazardous Waste Incinerator. Sources in this unit include storage tanks, distillation columns, process vessels, Synthetic Organic Chemical Manufacturing Industry (SOCMI) distillation columns, SOCMI reactors, and SOCMI wastewater. Applicable regulations for unit C-27018 include: the Hazardous Organic NESHAP (HON) under 40 CFR 63 Subparts F, G, and H, the Hazardous Waste Incinerator MACT under 40 CFR 63 Subpart EEE, the Miscellaneous Organic NESHAP under 40 CFR Subpart FFFF, New Source Performance Standards (NSPS) for SOCMI distillation columns (40 CFR 60 Subpart NNN), SOCMI reactors (40 CFR 60 Subpart RRR), and volatile organic liquid (VOL) storage tanks (40 CFR 60 Subpart Kb), Volatile Organic Compound Reasonably Available Control Technology (VOC RACT) under 6 NYCRR Subpart 212, sulfur fuel limitations under 6 NYCRR Subpart 225, VOC



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RACT for storage tanks under 6 NYCRR Subpart 229, and State Air Toxics under 6 NYCRR Subpart 212.

C-27035: Emission unit C-27035 is comprised of several aboveground storage tanks that are used to store acids. All of the tanks are located in the HCL Tank Farm. All but one of the tanks vents to a packed tower water scrubber (EP27035). One tank vents to an eductor (EP27039) which is piped to the chemical process sewer. The emission unit also contains three locations within the tank farm, which allow for scrapping of acid to the chemical process sewer. The applicable regulations are the State Air Toxics under 6 NYCRR Subpart 212, the Miscellaneous Organic NESHAP under 40 CFR Subpart FFFF, and New Source Performance Standards (NSPS) for volatile organic liquid (VOL) storage tanks under 40 CFR 60 Subpart Kb.

C-61007: Emission unit C-61007 includes the Silicon Grinding and Fines Passivation area. In the area, Silicon Grinding area, silicon metal is ground, screened, and transferred to silos. In the Fines Passivation area, mixers are used to mix fines to neutralize and harden the material. Processes include mixers, dust collectors, and an unloading station. Applicable regulations for this unit include emissions limitations for capping under Prevention of Significant Deterioration (40 CFR Subpart 52), the Miscellaneous Organic NESHAP under 40 CFR Subpart FFFF, and particulate emissions limitations under 6 NYCRR 212.

C-62008: Emission unit C-62008 includes all equipment associated with the methylchlorosilane (MCS) reactor systems (MCS II system, MCS III system and MCS IV system) that are not associated with the control devices in unit C-27018. Sources include process vessels, feed hoppers, and hot oil furnaces. Applicable regulations for this unit include emissions limitations for capping under Prevention of Significant Deterioration (40 CFR Subpart 52) and Non-Attainment New Source Review under 6 NYCRR 231-2, the Miscellaneous Organic NESHAP under 40 CFR Subpart FFFF, and particulate limitations under 6 NYCRR 212.

C-62014: This unit consists of sources in the Trichlorosilanes (TCS) and Fumed Silica production areas. The TCS area currently consists of exempt sources. The Fumed Silica area consists of a scrubber and various solids handling equipment. Applicable regulations include State Air Toxics under 6 NYCRR Subpart 212 and the Hydrochloric Acid Production MACT under NNNNN.

EGNRTR: This unit consists of emergency generator sources. They are subject to the Reciprocating Industrial Combustion Engine MACT of 40 CFR 63 Subpart ZZZZ.

F-INISH: This unit consists of intermediate and final production of silicone products and materials, including resins, fluids, dispersions, emulsions, heat curing elastomers, room temperature vulcanizing (rtv) elastomers, sealants, and treated fumed silica. Also includes various maintenance shops and individual maintenance sources (such as degreasers). Process sources include storage vessels, batch reactors, process tanks, mixers, feed hoppers, filter presses, drumming operations, liquid add stations, process strippers, unloading stations, packaging operations, maintenance degreasers, and all of the associated control equipment. Applicable regulations include the following: emissions limitations for capping under Prevention of Significant Deterioration (40 CFR Subpart 52) and Non-Attainment New Source Review under 6 NYCRR 231-2, New Source Performance Standards (NSPS) for volatile organic liquid (VOL) storage tanks under 40 CFR 60 Subpart Kb, Volatile Organic Compound Reasonably Available Control Technology (VOC RACT) under 6 NYCRR Subpart 212, State Air Toxics under 6 NYCRR Subpart 212, VOC RACT for Storage Tanks Under 6 NYCRR 229, the Miscellaneous Organic NESHAP under 40 CFR Subpart FFFF, and VOC RACT for Part Cleaners under 6 NYCRR 226.

H-OFURN: This unit consists of the plant; s hot oil furnaces not associated with MCS. These furnaces are subject to $6\ NYCRR\ 227$ and the Industrial Boiler MACT .



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T-13004: Unit 13004 consists of various pilot plant processes located in Building 13. Sources include process vessels, filters, and local extraction discharges. The applicable regulations include State Air Toxics under 6 NYCRR Subpart 212.

T-14009: This unit consists of equipment in the facility's Pilot Plant, located in Buildings 14, 15 and 16. The Pilot Plant makes developmental/experimental products for evaluation, and scaled-down batches of problem production grades to develop process adjustments. Scaled down batches of commercial products are also made here. Processes are small-volume sources including process vessels, strippers, distillation columns, mixers, and reactors. The applicable regulations include State Air Toxics under 6 NYCRR Subpart 212.

U-28002: Emission Unit U28002 consists of Boilers 13 and 18 and a #2 Fuel Oil storage tank. Applicable regulations include emissions limitations for capping under Prevention of Significant Deterioration (40 CFR Subpart 52) and Non-Attainment New Source Review under 6 NYCRR 231-2, New Source Performance Standards (NSPS) for volatile organic liquid (VOL) storage tanks under 40 CFR 60 Subpart Kb, NSPS regulations for industrial boilers under 40 CFR 60 Subpart Db, NOx RACT under 6 NYCRR 227-2, particulate limitations under 6 NYCRR 227-1, NOx Budget regulations under 6 NYCRR 227-3, 204 and 243, the Industrial Boiler MACT, and fuel limitations for sulfur under 6 NYCRR 225.

U-28003: Emission Unit U28003 consists of boilers 14, 15, 16, and 17. Applicable regulations include Prevention of Significant Deterioration (40 CFR Subpart 52) and Non-Attainment New Source Review under 6 NYCRR 231-2, NOx RACT under 6 NYCRR 227-2, particulate limitations under 6 NYCRR 227-1, the Industrial Boiler MACT, and fuel limitations for sulfur under 6 NYCRR 225.

W-97004: This emission unit is the wastewater treatment process system of the waste handling area. The wastewater treatment plant is a physical/chemical treatment system consisting of pH neutralization, oil and grease separation, clarification, and air stripping operations. The applicable regulations are New Source Performance Standards (NSPS) for Volatile Organic Liquid (VOL) storage tanks under 40 CFR 60 Subpart Kb, State Air Toxics under 6 NYCRR Subpart 212, the Miscellaneous Organic NESHAP under 40 CFR Subpart FFFF, and Volatile Organic Compound Reasonably Available Control Technology (VOC RACT) under 6 NYCRR Subpart 212.

E-LISTS: This emission unit exists simply to provide a means of condensing the permit. Processes in this EU list all affected sources for a specific citation in its monitoring description. This Process is then listed as the only affected source in the actual monitoring condition for the citation. This lists the affected sources in a much more condensed fashion than making a separate line for each source and should elliminate 300 pages from the permit.

Permit Structure and Description of Operations

The Title V permit for MOMENTIVE PERFORMANCE MATERIALS

is structured in terms of the following hierarchy: facility, emission unit, emission point, emission source and process. A facility is defined as all emission sources located at one or more adjacent or contiguous properties owned or operated by the same person or persons under common control. The facility is subdivided into one or more emission units (EU). Emission units are defined as any part or activity of a stationary facility that emits or has the potential to emit any federal or state regulated air pollutant. An emission unit is represented as a grouping of processes (defined as any activity involving one or more emission sources (ES) that emits or has the potential to emit any federal or state regulated air pollutant). An emission source is defined as any apparatus, contrivance or machine capable of causing emissions of any air contaminant to the outdoor atmosphere, including any appurtenant exhaust system or air cleaning device. [NOTE: Indirect sources of air contamination as defined in 6 NYCRR Part 203 (i.e. parking lots) are excluded from this definition]. The applicant is required to identify the principal piece of equipment



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(i.e., emission source) that directly results in or controls the emission of federal or state regulated air pollutants from an activity (i.e., process). Emission sources are categorized by the following types:

combustion - devices which burn fuel to generate heat, steam or power

incinerator - devices which burn waste material for disposal

control - emission control devices

process - any device or contrivance which may emit air contaminants

that is not included in the above categories.

MOMENTIVE PERFORMANCE MATERIALS is defined by the following emission unit(s):

Emission unit C61007 - Silicon grinding area and fines passivation area. In the silicon grinding area, silicon metal is ground, screened, and transferred to silos. In the fines passivation area, mixers are used to mix fines to neutralize and harden the material.

Emission unit C61007 is associated with the following emission points (EP): 61001, 61002, 61003, 61005, 61006, 61007, 61008, 61009, 61010, 61805

Process: 711 is located at Building 61 - Old Silicon grinding plant - unloads Silicon metal from rail cars to buffer silo. Silicon is fed from buffer silo to ball mill. Ball mill grinds Silicon and discharges ground powder to screener. Finished product is placed in silos; oversize material is recycled from screener to mill.

Process: GCC is located at Building 61 - Fines passivation. Fines are mixed with Lignin and water to neutralize and harden the material. Associated equipment is a bag dump station.

Emission unit C62008 - Chemops - MCSII, MCSIII and MCSIV operations. All equipment associated with the MCSII, MCSIII and MCSIV production operations, with the exception of the MCS vent scrubbers and MCS vent incinerator.

Emission unit C62008 is associated with the following emission points (EP): 55005, 55006, 57004, 62009, 62012, 65001, 65002

Process: 419 MCS Hot oil furnaces with limits on #2 fuel oil.

Process: MCW is located at Building 62 - MCS-Tanks - Working Loss - This process consisits of Working Losses from tanks in the MCS production operation.

Emission unit C62014 - This unit consists of sources in the trichlorosilanes (TCS) and fumed silica production areas.

Emission unit C62014 is associated with the following emission points (EP): 68001, 68002, 68003, 68004

Process: 407 Fumed Silica scrubber. This process consists of a scrubber which removes Chlorine, Hydrogen Chloride, and Particulates.

Emission unit ELISTS - This EU consists of lists of Processes, Emission Points & Emission Sources referenced in other EU Compliance Monitoring Activities



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Process: L01 is located at 1st floor, Building All - List of Processes subject to 40 CFR 63 Subpart SS [63.983(a, b, c & d), 63.990(a & b), 63.996, 63.996(d), 63.998(a)(2), 63.998(b & c), 63.998(c)(1 & 2) & 63.998(d)(1)]

EU-C27018: Proc - 033, 035, 078, 080, 085, 090, 093, 119 & 143

EU-C27035: Proc - 056

EU-FINISH: Proc - 069, 081 & 169

Process: L02 is located at 1st floor, Building All - List of Processes subject to 40 CFR 63 Subpart SS [63.988(a), 63.988(b)]

EU-C27018: Proc - 033, 035, 076, 080, 090, 093, 119 & 143

Process: L03 is located at 1st floor, Building All - List of Processes subject to 40 CFR 63 Subpart UU [63.1019, 63.1022, 63.1023(a, b & c), 63.1023(e), 63.1024(a, c, d, e & f), 63.1025(b, c & d), 63.1025(e)(1, 2 & 3), 63.1026, 63.1026(b)(4), 63.1026(e), 63.1027(b), 63.1027(e)(1 & 2), 63.1028, 63.1029, 63.1030, 63.1031(f), 63.1032, 63.1033, 63.1035, 63.1036, 63.1038(b & c) & 63.1039(a & b)]:

EU-C27018: Proc - (001-003), (005-013), (022-027), (031-033), (035-037), 039, 040, (042-049), 051, 054, 055, 061, 064, (066-068), (071-073), 078, 080, (082-090), (093-097), (099-103), 105, 106, 108, 109, (112-117), (119-125), (127-135), 137, 139, (141-143), 146, (148-154), 156, 158, (160-164), (166-168), 172 & (183-189).

EU-C27035: Process - 056.

EU-FINISH: Processes - (014-020), 029, 053, (057-060), 063, 065, 069, 076, 077, 081, 092, 136, 155, 157, 159, 165, 169, 173 & (175-182).

Process: L04 is located at Building All - List of Emission Points subject to Part 212.10(c)(4)(i):

EU-FINISH: EPs - 24946, 32038, 32040, 32042, 32044, 32049, 32050, 71013, 76006 & 85008.

EU-C27018: EPs - 31037, 62007, 76001, 23002, 24947, 31036.

Process: L05 is located at 1st floor, Building All - List of Emission Points subject to Part 212.10(c)(4)(iii):

EU-C27018: EPs - 24105, 24806, 62005 & 62011.

EU-W97004: EPs - 97004, 97005, 97011, 97012, 97017, 97020 & 97021.

EU-FINISH: EPs - 32040, 32042, 32044, 32049 & 32050.

Process: L06 is located at 1st floor, Building All - List of Emission Points subject to Part 212.4(c) & Part 212.6(a):

EU-FINISH: EPs - 32006, 32007, 32008, 32009, 32016, 32017, 33002, 33003, 33004, 42012 & 85002.

EU-C27018: EPs - 14006, 24120, 24132, 31003, 31022, 31030, 32038, 37707, 37934, 55001, 57001, 57002, 57003, 61801, 62005, 62007, 62008, 62011, 76004, 76005, 78005, 97001, 97002 & 97003.



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EU-C61007: EPs - 61001, 61002, 61003, 61005, 61006, 61007, 61008, 61009, 61010 & 61805.

EU-C62014: EPs - 68001, 68002, 68003 & 68004.

EU-W97004: EP - 95002.

Process: L07 is located at 1st floor, Building All - List of Emission Points & Processes subject to Part 227-1.3(a):

EU-HOFURN

EU-U28002: Proc - 408 & 409.

EU-U28003: Proc - 412, 413, 414, 415, 416 & 417.

EU-C62008: EPs - 55005, 57004, 65001.

Process: L08 is located at 1st floor, Building All - List of Emission Points, Processes & Emission Sources subject to Part 229.5(d):

EU-C27018: (Proc 090 / ES SSTVT, 6204A, 62T12, 62T56, 62T59, 62TBA & T506D), (Proc 013 / ESs 76ACW & 76SBS), (Proc 401 / ES 62T56) & (EP 37925).

EU-FINISH: (Proc 053 / ES 76PTA), (Proc 175 / ES 85CT1, 85CT2, 85CT3, 85ST7 & 85BST), (Proc 182 / ES 85FPT), (Proc 735 / ES 76VS1, 76VS2 & 76VS3), (Proc 736 / ES 76VS1, 76VS2 & 76VS3) & (EPs 24141 & 37924).

EU-W97004: EPs 97041 & 97042.

Emission unit FINISH - Finishing - intermediate and final production of silicone products and materials including resins, fluids, dispersions, emulsions, heat curing elastomers, room temperature vulcanizing (rtv) elastomers, sealants, and treated fumed silica. Also includes various maintenance shops and individual maintenance sources (such as degreasers).

Emission unit FINISH is associated with the following emission points (EP): 21101, 23100, 24136, 24141, 24413, 24946, 24947, 27102, 28009, 29102, 30001, 30002, 32006, 32007, 32008, 32009, 32016, 32017, 32026, 32027, 32028, 32040, 32042, 32044, 32046, 32049, 32050, 33002, 33003, 33004, 33017, 33019, 33020, 33024, 33025, 33026, 33901, 33902, 33903, 33904, 33905, 33906, 37001, 37016, 37032, 37047, 37049, 37050, 37054, 37059, 37701, 37924, 37948, 37960, 41001, 41002, 41003, 42001, 42002, 42003, 42005, 42012, 42013, 42019, 42020, 61602, 61603, 71010, 71013, 76006, 76007, 76716, 78021, 78022, 78023, 78024, 85002, 85003, 85004, 85006, 85007, 85008, 85013, 85020, 85021, 85022, 85023, 85024, 85029, 85032, 85036, 85037, 85038, 85039, 85040, 85041, 85042, 85045, 85046, 85054, 85058, 85059, 85066, 85067, 85903, 85904, 97023

Process: 014 is located at Building 41 - This process represents FOM 014, which is a miscellaneous

Process: 014 is located at Building 41 - This process represents FOM 014, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)



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Process: 015 is located at Building 41 - This process represents FOM 015, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 016 is located at Building 41 - This process represents FOM 016, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 017 is located at Building 41 - Equiment for Family of Material #017, which is a miscellaneous organix manufacutring unit (MCPU) that is regulated under 40 CFR Part 63, SubPart FFFF.

Process: 018 is located at Building 41 - This process represents FOM 018, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 019 is located at Building 41 - This process represents FOM 019, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 020 is located at Building 41 - This process represents FOM 020, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 029 is located at Building 85 - This process represents FOM 029, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 053 is located at Building 76 - This process represents FOM 053, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 057 is located at Building 42 - This process represents FOM 057, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 058 is located at Building 42 - This process represents FOM 058, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 059 is located at Building 42 - This process represents FOM 059, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 060 is located at Building 30 - This process represents FOM 060, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)
Building 30/42

Process: 063 is located at Building 30 - This process represents FOM 063, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)



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Buildings 30/42

Process: 065 is located at Building 30 - This process represents FOM 065, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing) Buildings 30/42

Process: 069 is located at Building 76 - This process represents FOM 069, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 076 is located at Building 30 - This process represents FOM 076, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 077 is located at Building 30 - This process represents FOM 077, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 081 is located at Building 37 - This process represents FOM 081, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 092 is located at Building 71 - This process represents FOM 092, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing)

Process: 136 is located at Building 30 - Equipment for Family of material #136 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 155 is located at Building 78 - Equipment for Family of Material #155 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 157 is located at Building 32 - Equipment for Family of Material #157 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR 63 Subpart FFFF.

Process: 159 is located at Building 42 - Equipment for Family of Material #159 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 165 is located at Building 41 - Equipment for Family of Material #165 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 169 is located at Building 76 - Equipment for Family of Material #169 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 173 is located at Building 78 - Equipment for Family of Material #173 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 175 is located at Building 85 - Equipment for Family of Material #175 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.



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Process: 176 is located at Building 30 - Equipment for Family of Material #176 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 177 is located at Building 30 - Equipment for Family of Material #177 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 178 is located at Building 30 - Equipment for Family of Material #178 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 179 is located at Building 30 - Equipment for Family of Material #179 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 180 is located at Building 78 - Equipment for Family of Material #180 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 181 is located at Building 78 - Equipment for Family of Material #181 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 182 is located at Building 85 - Equipment for Family of Material #182 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 207 This process represents the management of Group 1 wastewater in individual drain systems. The Group 1 wastewater streams are generated by the miscellaneous organic chemical manufacturing units (MCPUs) in C-27018 that are regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing).

Process: 218 01 - catalyst vapors emitted by material in purge drums waste drums screening operations drum weigh 02 - caco3 &/or tio2 is fed continuously from gravity feeders 898-424-0067 to inlet hopper on 03 - "packaged" piped vacuum cleaning system (898-451-003) for housekeeping in processing areas of 04 - vent from the beringer oven

Process: 219 Untreated filler is conveyed via a moving air stream to this silo displaced air from the silo is filtered and vented to atmosphere

Process: 712 South resins. During the vacuum process, emissions from a body kettle condenser pass through a receiver to a vacuum eductor and vent to the RKI.

Process: 713 East resins. During the vacuum process, emissions from a body kettle condenser pass through a receiver to a vacuum eductor and vent to the RKI.

Process: 714 Doughmixer area - doughmixers #5,6,7,8, and 9 vent to a condenser and a receiver vent. The doughmixers are batch mixers used in the production of various products.

Process: 716 Doughmixer area - doughmixers #3,5,6,7,8, and 9 vent to a hood. The doughmixers are batch mixers used in the production of various products.

Process: 717 Treater filler kettle - treater filler kettle is used to treat raw filler with HMDZ. HMDZ vapors are discharged to receiver and ultimately to a packed tower scrubber. Tank wagon emissions also vented to scrubber.



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Process: 718 1500 Phenyl reactor (Diol and Tetramer). A batch system used to manufacture phenyl diol and Pheny Tetramer.

Process: 720 Treater Filler Kettles The Methyl Tetramer (D4) recovery system consists of a vapor condensing tower, a D4 circulating tank, a knock out pot, and a light-ends weigh tank. D4 vapor and Nitrogen are released from treated filler kettles and transferred to the recovery system.

Process: 721 Treater Filler Kettles Treater filler kettles are used to treat raw fillers with Methyl Tetramer. Methyl Tetramer vapors are discharged to a condenser/receiver system.

Process: 728 1M Fluorosilicone reactor. A 1000 gallon batch system used to manufacture Fluorosilicone Polysiloxane. The process consists of two steps: production of 88536 followed by hydrolysis. Major equipment includes a reactor, weigh tank, and two receivers.

Process: 729 Transfer truck unloading. Tank wagon loading/unloading station.

Process: 734 4000 PUFA. This process consists of a 1-Hexene process tank.

Process: 735 East and West Systems - Standing losses from atmospheric storage tanks. The tanks are used to store Acetyl Chloride waste, Silane blend, and propyltriacetoxysilane (PTAS).

Process: 736 East and West Systems - Working losses from atmospheric storage tanks. The tanks are used to store Acetyl Chloride waste, Silane blend, and propyltriacetoxysilane (PTAS).

Process: 738 Working losses from the four pigment tanks are used to store liquid pigment dispersions. The vessels vent to the atmosphere when the vessels are charged from the drums the vessels vent to a common conservation vent header.

Process: 739 Standing storage losses from four pigment tanks are used to store liquid pigment dispersions. The vessels vent to the atmosphere when the vessels are charged from the drums. The vessels vent to a common conservation vent header.

Process: 740 WP2, WP3 Tanks - This process represents working losses from volatile organic liquid storage tanks used in the WP-2 and WP-3 operations. Tanks are under pressure or have a Nitrogen blanket.

Process: BMD Molding Compound Area Solids handling operations, including dust collectors for grinding operations and exhaust hoods, blending and extruding, and bag slitting. Associated equipment includes mixers, extruders, grinders, and blenders.

Process: DEG Maintenance shops - Cold cleaning solvent degreasing units that use a petroleum distillate solvent.

Process: FFR Eductor system. Insignificant emissions from the Phenyl Tetramer eductor system.

Process: TKC Transfer and Blending. Working losses from Tank 538. The tank is under a Nitrogen pad/dapad system.

Process: TKD Transfer and Blending. Working losses from Isopropanol storage tank.

Process: TKE Transfer and Blending. Standing storage losses from Isopropanol storage tank.



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Process: WPF is located at Building 30 - Fugitive emissions WP1, & WP4.

Emission unit HOFURN - This unit consists of additional hot oil furnaces not already included in another emission unit.

Emission unit HOFURN is associated with the following emission points (EP): 21012, 35027, 62016, 85063

Process: 418 This process includes the operation of hot oil furnaces.

Process: 426 is located at Building 35 - This process includes the operation of hot oil furnaces replace the existing 21HOF and 35HOF upon reconfiguration of the existing 12.5 mmBTU/hr natural gas burners with 15 mmBTU/hr natural gas burners. These furnaces are in building 21 and 35.

Emission unit T13004 - Vapors and particulates are vented to the atmosphere outside of building 13 at different emissions points. These include process, filter, and local extraction discharges.

Emission unit T13004 is associated with the following emission points (EP): 13004, 13006

Process: 742 Process development. Emissions from siloxanes passing from the compounder to the LIM after-condenser at location 4A.

Process: 743 Process development. Volatiles stripped from the LIM during compounding and cooling pass through the shared LIM after-condenser at location 4C.

Emission unit U28002 - Emission Unit U28002 consists of Boilers 13 and 18 and a #2 Fuel Oil storage tank.

Emission unit U28002 is associated with the following emission points (EP):

28002, 28006, 28020

Process: 408 Boiler 13 - Natural gas combustion.

Process: 409 Boiler 13 - Number 6 fuel oil combustion.

Process: 410 Boiler 18 - natural gas combustion.

Process: 411 is located at Building 28 - #2 fuel oil combustion for boiler #18

Emission unit U28003 - Emission Unit U28003 consists of boilers 14, 15, 16, and 17.

Emission unit U28003 is associated with the following emission points (EP):

28003, 28004, 28005

Process: 412 Boilers 15 - number 6 fuel oil combustion.



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Process: 413 is located at Building 28 - Boiler 15 - Natural gas combustion.

Process: 414 is located at Building 28 - Boiler 14 - Number 6 fuel oil combustion.

Process: 415 is located at Building 28 - Boiler 14 - Natural gas combustion.

Process: 416 is located at Building 28 - Boiler 17 - Natural gas combustion.

Process: 417 is located at Building 28 - Boiler 16 - Natural gas combustion.

Emission unit W97004 - This Emission Unit is the wastewater treatment process system of the waste handling area. The wastewater treatment plant is a physical/chemical treatment system consisting of pH neutralization, oil and grease separation, clarification, and air stripping operations.

Emission unit W97004 is associated with the following emission points (EP): 95002, 97004, 97005, 97008, 97011, 97012, 97017, 97020, 97021, 97041, 97042, 97043, 97047, 97048, 97049

Process: 744 Underground storage tanks receiving acidic aqueous polar and non-polar solvent containing wastewater via sewer pipe.

Process: 745 Waste Water Treatment Plant - 5,000 gallon neutralization tank which receives non-aqueous phase material and neutralizes it with KOH.

Process: 747 Waste Water Treatment Plant - 2.2 million gallon open top tanks used to provide equalization and mixing of wastewater prior to introduction to the bio reactors.

Emission unit C27018 - Chemical operations and sources requiring incineration control under MON MACT. The MCS Vent incinerator, MCS vent scrubber, Fixed Box incinerator no. 2, and the rotary kiln incinerator are included in this unit.

Emission unit C27018 is associated with the following emission points (EP): 14006, 21005, 21011, 22001, 23002, 23005, 24103, 24105, 24113, 24120, 24121, 24132, 24133, 24134, 24135, 24137, 24139, 24140, 24207, 24208, 24305, 24307, 24308, 24309, 24310, 24311, 24312, 24409, 24423, 24702, 24704, 24801, 24806, 24906, 24907, 24916, 24922, 24924, 24925, 24935, 24937, 24938, 24939, 24940, 24941, 24944, 24945, 24949, 24950, 27018, 27022, 27023, 27024, 30801, 30802, 30803, 30804, 30805, 30806, 30807, 30808, 30901, 30902, 30904, 30910, 30911, 30912, 30913, 30914, 30915, 30916, 30917, 30918, 30921, 30922, 30933, 30935, 30945, 30946, 31002, 31003, 31019, 31022, 31030, 31031, 31032, 31034, 31036, 31037, 31040, 31041, 31045, 32035, 32036, 32038, 34001, 34002, 35006, 35007, 35009, 35010, 35011, 35012, 35017, 35018, 35028, 35031, 35032, 35033, 35034, 35035, 35036, 35037, 35038, 35039, 35040, 35041, 35042, 35043, 35044, 35045, 35046, 35047, 35048, 35049, 35050, 35901, 36001, 36003, 36004, 37002, 37004, 37007, 37009, 37011, 37013, 37014, 37017, 37018, 37019, 37020, 37021, 37022, 37023, 37026, 37027, 37033, 37034, 37036, 37037, 37038, 37039, 37040, 37041, 37042, 37043, 37044, 37045, 37051, 37053, 37055, 37056, 37060, 37061, 37062, 37063, 37066, 37077, 37705, 37707, 37708, 37801, 37803, 37804, 37805, 37812, 37813, 37814, 37901, 37902, 37903, 37909, 37910, 37911, 37921, 37922, 37923, 37925, 37926, 37927, 37928, 37930, 37931, 37932, 37934, 37946, 37947, 37952, 38006, 38007, 38018, 38039, 38088, 48001, 55001, 55007, 57001, 57002, 57003, 61801,



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61802, 62005, 62007, 62008, 62011, 70001, 70003, 71001, 71003, 71005, 71009, 71011, 71014, 71016, 76001, 76004, 76005, 76010, 76011, 76701, 76703, 76705, 76710, 76711, 76712, 76713, 76714, 76718, 78001, 78002, 78003, 78004, 78005, 78006, 78007, 78009, 78011, 78012, 78015, 78016, 78017, 78018, 78019, 78025, 97001, 97002, 97003, 97053

Process: 001 is located at Building 71 - This process represents FOM 001, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing).

Process: 002 is located at Building 71 - This process represents FOM 002, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing).

Process: 003 is located at Building 71 - Equipment for Family of Material #003, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 005 is located at Building 78 - Equipment for Family of Material #005, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 006 is located at Building 78 - Equipment for Family of Material #006, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 007 is located at Building 30 - Equipment for Family of Material #007, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 008 is located at Building 37 - Equipment for Family of Material #007, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 009 is located at Building 37 - Equipment for Family of Material #009, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 010 is located at Building 37 - Equipment for Family of Material #010, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 011 is located at Building 37 - Equipment for Family of Material #011, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 012 is located at Building 78 - Equipment for Family of Material #012, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 013 is located at Building 76 - Equipment for Family of Material #013, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart



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Process: 022 is located at Building 76 - Equipment for Family of Material #022, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 023 is located at Building 30 - Equipment for Family of Material #023, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 024 is located at Building 30 - Equipment for Family of Material #024, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 025 is located at Building 30 - Equipment for Family of Material #025, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF. This process operates out of building 30 and 78.

Process: 026 is located at Building 30 - Equipment for Family of Material #026, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 027 is located at Building 30 - Equipment for Family of Material #027, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 031 is located at Building 30 - This process represents FOM 031, which is a miscellaneous organic chemical manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing).

Process: 032 is located at Building 30 - Equipment for Family of Material #032, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF. This process operates out of buildings 30 and 78.

Process: 033 is located at Building 30 - Equipment for Family of Material #033, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF. This process operates out of buildings 30 and 78.

Process: 035 is located at Building 30 - Equipment for Family of Material #035, which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 036 is located at Building 30 - Equipment for Family of Material #036 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 037 is located at Building 30 - Equipment for Family of Material #037 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 039 is located at Building 37 - Equipment for Family of Material #039 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.



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Process: 040 is located at Building 76 - Equipment for Family of Material #040 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 042 is located at Building 30 - Equipment for Family of Material #042 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF. This process operates out of buildings 30 and 78.

Process: 043 is located at Building 30 - Equipment for Family of Material #043 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 045 is located at Building 30 - Equipment for Family of Material #045 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 046 is located at Building 71 - Equipment for Family of Material #046 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 047 is located at Building 71 - Equipment for Family of Material #047 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF. This process operates out of buildings 71 and 76.

Process: 048 is located at Building 71 - Equipment for Family of Material #048 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 049 is located at Building 71 - Equipment for Family of Material #049 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 051 is located at Building 71 - Equipment for Family of Material #051 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63, Subpart FFFF.

Process: 054 is located at Building 71 - Equipment for Family of Material #054 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 055 is located at Building 71 - Equipment for Family of Material #055 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 061 is located at Building 32 - Equipment for Family of Material #061 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 064 is located at Building 32 - Equipment for Family of Material #064 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 066 is located at Building 76 - Equipment for Family of Material #066 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 76 and 78.

Process: 067 is located at Building 27 - Equipment for Family of Material #067 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 27, 35 and 70.

Process: 068 is located at Building 71 - Equipment for Family of Material #068 which is a miscellaneous



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organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 71 and 76.

Process: 071 is located at Building 24 - Equipment for Family of Material #071 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 072 is located at Building 71 - Equipment for Family of Material #072 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 073 is located at Building 21 - Equipment for Family of Material #073 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 21 and 35.

Process: 078 is located at Building 23 - Equipment for Family of Material #078 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 23, 24 and 24A.

Process: 080 is located at Building 23 - Equipment for Family of Material #080 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 23, 24, 24A and 71.

Process: 082 is located at Building 23 - Equipment for Family of Material #082 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 23, 24 and 24A.

Process: 083 is located at Building 71 - Equipment for Family of Material #083 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 084 is located at Building 37 - Equipment for Family of Material #084 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 085 is located at Building 76 - Equipment for Family of Material #085 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 086 is located at Building 37 - Equipment for Family of Material #086 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 087 is located at Building 37 - Equipment for Family of Material #087 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 088 is located at Building 37 - Equipment for Family of Material #088 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 089 is located at Building 23 - Equipment for Family of Material #089 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 23, 24 and 24A.

Process: 090 is located at Building 61 - Equipment for Family of Material #090 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 61 and 62.



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Process: 093 is located at Building 23 - Equipment for Family of Material #093 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 094 is located at Building 37 - Equipment for Family of Material #094 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 095 is located at Building 71 - Equipment for Family of Material #095 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 096 is located at Building 37 - Equipment for Family of Material #096 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 097 is located at Building 30 - Equipment for Family of Material #097 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 30 and 78.

Process: 099 is located at Building 78 - Equipment for Family of Material #099 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 100 is located at Building 37 - Equipment for Family of Material #100 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 101 Equipment for Family of Material #101 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 102 is located at Building 30 - Equipment for Family of Material #101 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 30 and 71.

Process: 103 is located at Building 71 - Equipment for Family of Material #103 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 105 is located at Building 30 - Equipment for Family of Material #105 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 106 is located at Building 24 - Equipment for Family of Material #106 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 24 and 37.

Process: 108 is located at Building 76 - Equipment for Family of Material #108 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 109 is located at Building 37 - Equipment for Family of Material #109 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 112 is located at Building 30 - Equipment for Family of Material #112 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 30, 37, 76 and 78.

Process: 113 is located at Building 37 - Equipment for Family of Material #113 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process



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operates out of buildings 37 and 76.

Process: 114 is located at Building 37 - Equipment for Family of Material #114 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 115 is located at Building 23 - Equipment for Family of Material #115 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 23, 24 and 24A.

Process: 116 is located at Building 78 - Equipment for Family of Material #116 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 117 is located at Building 71 - Equipment for Family of Material #117 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 119 is located at Building 23 - Equipment for Family of Material #119 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 23, 24, 24A and 71.

Process: 120 is located at Building 71 - Equipment for Family of Material #120 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 121 is located at Building 37 - Equipment for Family of Material #121 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 122 is located at Building 37 - Equipment for Family of Material #122 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 123 is located at Building 23 - Equipment for Family of Material #123 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 23, 24 and 24A.

Process: 124 is located at Building 37 - Equipment for Family of Material #124 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 125 is located at Building 37 - Equipment for Family of Material #125 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 127 is located at Building 37 - Equipment for Family of Material #127 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 128 is located at Building 24 - Equipment for Family of Material #128 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 24, 71 and 76.

Process: 129 is located at Building 37 - Equipment for Family of Material #129 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 130 is located at Building 37 - Equipment for Family of Material #130 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.



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Process: 131 is located at Building 78 - Equipment for Family of Material #131 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 132 is located at Building 78 - Equipment for Family of Material #132 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 133 is located at Building 78 - Equipment for Family of Material #133 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 134 is located at Building 78 - Equipment for Family of Material #134 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 135 is located at Building 76 - Equipment for Family of Material #135 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 137 is located at Building 30 - Equipment for Family of Material #137 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 139 is located at Building 71 - Equipment for Family of Material #139 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 141 is located at Building 30 - Equipment for Family of Material #141 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 142 is located at Building 31 - Equipment for Family of Material #142 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 143 is located at Building 30 - Equipment for Family of Material #143 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 146 is located at Building 34 - Equipment for Family of Material #146 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 148 is located at Building 30 - Equipment for Family of Material #148 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 149 is located at Building 30 - Equipment for Family of Material #149 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 150 is located at Building 76 - Equipment for Family of Material #150 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 151 is located at Building 71 - Equipment for Family of Material #151 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 152 is located at Building 71 - Equipment for Family of Material #152 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 153 is located at Building 71 - Equipment for Family of Material #153 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.



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Process: 154 is located at Building 71 - Equipment for Family of Material #154 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 156 is located at Building 71 - Equipment for Family of Material #156 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 158 is located at Building 76 - Equipment for Family of Material #158 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 160 is located at Building 30 - Equipment for Family of Material #160 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 161 is located at Building 30 - Equipment for Family of Material #161 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 162 is located at Building 30 - Equipment for Family of Material #162 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 30 and 78.

Process: 163 is located at Building 30 - Equipment for Family of Material #163 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 164 is located at Building 71 - Equipment for Family of Material #164 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 166 is located at Building 37 - Equipment for Family of Material #166 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 167 Equipment for Family of Material #167 which is a miscellaneous organic manufacturing unint (MCPU) that is regulated under 40 CFR Oart 63 Subpart FFFF.

Process: 168 is located at Building 23 - Equipment for Family of Material #168 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF. This process operates out of buildings 23, 24 and 24A.

Process: 172 is located at Building 37 - Equipment for Family of Material #172 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 183 is located at Building 32 - Equipment for Family of Material #183 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 184 is located at Building 37 - Equipment for Family of Material #184 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 185 is located at Building 71 - Equipment for Family of Material #185 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 186 is located at Building 30 - Equipment for Family of Material #186 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.



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Process: 187 is located at Building 30 - Equipment for Family of Material #187 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 188 is located at Building 31 - Equipment for Family of Material #188 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 189 is located at Building 30 - Equipment for Family of Material #189 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Process: 201 Heat exchange system. This process represents cooling water from heat exchange systems within the miscellaneous organic chemical manufacturing units (MCPUs) with C-27018 that are regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing).

Process: 202 Heat exchange system. This process represents cooling water from heat exchange systems within the miscellaneous organic chemical manufacturing units (MCPUs) within C-27035 that are regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing).

Process: 205 This process represents the management of Group 1 residues in containers. The Group 1 residues are generated by the miscellaneous organic chemical manufacturing units (MCPUs) in C-27035 that are regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing).

Process: 206 A batch polymer kettle, PK-9 with condenser receiver vents when the kettle is filled (during charging and chemical additions) and when purging (during drying.) (4) Vacuum stripping with N2 purge

Process: 213 is located at Building 37 - This process represents the management of Group 1 process wastewater that is generated by miscellaneous chemical manufacturing units (MCPUs) that are regulated under 40 CFR Part 63, Subpart FFFF (Miscellaneous Organic Chemical Manufacturing).

Process: 217 1 - the bulk product storage tanks acetoxy catalyst metering tanks and acetoxy feed hoppers vent

02 - bulk product storage tanks and packaging machine feed hoppers which contain sealant-x product

04 - a caulker filling machine uses a small pressure vessel to fill caulkers with sealant.

Process: 400 is located at Building 34 - Equipment leaks. This process represents closed vent system, compressor, connector, pressure relief valve, pump, sampling connection, vessel and receiver, and valve leaks for the Methyl Chloride chemical manufacturing process unit.

Process: 401 MCS to incinerators/scrubbers. This process consists of sources in the Methyl Chlorosilane operations area which vent to the waste incinerators, the MCS vent incinerator, or the MCS vent scrubber.

Process: 402 is located at Building 27 - Methanol storage tanks. Two storage tanks that supply Methanol to the Methyl Chloride reactors in building 34. Both tanks are equipped with an internal floating roof.

Process: 403 is located at Building 34 - Process wastewater. This process represents process wastewater from the Methyl Chloride chemical manufacturing process unit.

Process: 404 is located at Building 34 - Maintenance wastewater. This process represents maintenance wastewater from the Methyl Chloride chemical manufacturing process unit.



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Process: 405 is located at Building 27 - Water scrubber, spent sulfuric storage tank and loading. Sulfuric acid fumes are vented from the head space of the spent sulfuric acid tank.

Process: 406 Heat exchange system. This process represents cooling water from heat exchange systems within the Methyl Chloride chemical manufacturing process unit.

Process: 420 LDH/Siloxane oil production. Insignificant emissions from the Cracker preheaters drain tank which receives water and Cyclic Siloxanes from preheaters on Crackers B C and D.

Process: 422 RKI Normal Operation

Process: 423 RKI Maintenance Operation.

Process: 424 Fixed Box Normal Operation.

Process: 425 Fixed Box Maintenance Operation.

Process: 427 FBI Maintenance mode during soot blowing.

Note that - All other limits during maintenance operations (Process 425) apply during this mode of operation except the air flow to the stack.

Process: 428 FBI Normal operating mode during soot blowing.

Note that - All other limits from normal operation (Process 424) apply during this mode of operation except the air flow to the stack.

Process: 429 FBI Normal operating mode during soot blowing.

Note that - All other limits from normal operation (Process 424) apply during this mode of operation except the air flow to the stack.

Process: 700 is located at Building 62 - Tank farm. Insignificant emissions from 30,000 gallon storage tank 539. Tank has a continuous Nitrogen purge.

Process: 701 Low boiling distillation and redistribution. This process consists of multiple distillation columns and two reactors in the low boiling distillation and redistribution area which vent to the waste incinerators or the MCS vent scrubber.

Process: 702 MCS IV reactor purge. This process consists of a purge on a reactor vessel.

Process: 703 MCS IV Methyl Chloride recovery column. This process consists of the MCS IV Methyl Chloride recovery column which vents to the MCS vent incinerator or the waste incinerator.

Process: 704 is located at Building 34 - Methanol recovery columns. Dual distillation columns which recover Methanol from water scrubber bottom product.

Process: 705 This process consists of slurry and Silane tanks which vent when filled (working losses) to the waste incinerators as an alternate and equivalent means of control.



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Process: 706 is located at Building 27 - HCl compressor and GDH start up. This process represents Hydrogen Chloride fume scrubber for GDH start ups.

Process: 707 117/118 column system. Emissions from the 117/118 columns are transferred to the 547B knockout tank, where condensed vapors are collected. The remaining vapors are sent to an eductor water unit, where the gases are mixed with tempered water and are sent to the chemical sewer.

Process: 708 is located at Building 35 - LDH/Siloxanes oil production. This process represents distillation columns, crackers, Siloxane water removal systems, and neutralizer vents associated with LDH and Siloxanes oil production.

Process: 709 MCS IV Silicon feed hoppers. This process consists of two fresh Silicon feed hoppers in the MCS IV operational area.

Process: 710 Column 114 B Mono/Tri column. This process consists of the 114 B distillation column which vents to the waste incinerators or to the MCS vent scrubber on startup.

Process: 712 South resins. During the vacuum process, emissions from a body kettle condenser pass through a receiver to a vacuum eductor and vent to the RKI.

Process: 713 East resins. During the vacuum process, emissions from a body kettle condenser pass through a receiver to a vacuum eductor and vent to the RKI.

Process: 715 MQ Resins. Resins and polymers are held for further processing in a closed, stirred process kettle.

Process: 719 East and West Hydrolyzers. The East and West Hydrolyzers vent to the East and West High Acid Scrubbers.

Process: 722 East and south hydrolyzers. Emissions from the east and south hydrolyzers that vent to water scrubbers that discharge to the chem sewers.

Process: 723 Batch Mixing The 225 gallon Day Mixer, the 500 Day Mixer, and the 500 gallon B-K Mixer vent through a common vacuum pump. The mixers are used to mix silicone.

Process: 724 Batch Mixing The 3000 liter north and the 3000 liter south Drais mixers vent to venturi scrubbers during filler charges.

Process: 726 East Sytem - This process consists of the East System Flter Press.

Process: 727 West System - manufactures products such as auto polishes, masonry water repellent, impregnant for roofing granules, and process aids for rubber production. It is a batch system that is a hydrolysis system. Associated equipment includes a filter press.

Process: 730 East resins. Under atmospheric conditions, emissions from a body kettle condenser vent. Emissions from the kettle can also go to a receiver vent.

Process: 731 Transfer truck unloading. Tank wagon loading/unloading station.

Process: 732 1M reactor. Local ventilation system used to remove Dimethylformamide vapors during filter



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rebuild.

Process: 733 4000 PUFA. Methyl Styrene storage tank working losses.

Process: 737 Chlorosilane distillation. This process consists of distillation columns in the Chlorosilane distillation area which vent to the MCS vent scrubber.

Process: 741 3M hydrolyzer. A 3000 gallon multifunctional batch system used to manufacture various product grades. The hydrolyzer is used for hydrolysis reactions, cold mixes, and equilibrium processes. Associated equipment includes weigh tanks, drum/tanker charging, filters.

Process: 746 Storage tanks - working losses. This process consists of working losses from storage tanks which vent to the MCS vent scrubber or the waste incinerators.

Process: 748 TCS/FS to incinerators or scrubbers. This process consists of sources in the Tri-Chlorosilane and fumed Silica operating areas which vent to the waste incinerators or the MCS vent scrubbers.

Process: 749 Waste treatment incinerators. This process consists of the Rotary Kiln Incinerator and the Fixed Box Incinerator no. 2 in the waste treatment plant.

Process: FIN This process represents the chemical manufacturing process sources that have been reorganized from the finishing emission unit (F-INISH) to C-27018 due to changes needed for compliance with MON requirements.

Emission unit C27035 - Emission unit C-27035 is comprised of several aboveground storage tanks which are used to store acids. The emission unit also contains three locations within the tank farm which allow for scrapping of acid to the chemical process sewer.

Emission unit C27035 is associated with the following emission points (EP): 27032, 27035, 27038

Process: 056 is located at Building 27 - Equipment for Family of Material #056 which is a miscellaneous organic manufacturing unit (MCPU) that is regulated under 40 CFR Part 63 Subpart FFFF.

Title V/Major Source Status

MOMENTIVE PERFORMANCE MATERIALS is subject to Title V requirements. This determination is based on the following information:

This facility is major for the following permitted emissions:

CONTAMINANT PERMITTED EMISSION RANGE

VOC >250 TPY

CO >250 TPY

PM >250 TPY

PM-10 >250 TPY

SO2 >250 TPY

SO2 >250 TPY

SO2 >250 TPY

SPECIATED HAPS

BENZENE >10 TPY

CHLORINE >10 TPY



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COBALT >10 TPY

1,1,1-TRICHLOROETHANE >10 TPY

ETHYLBENZENE >10 TPY

HEXANE >10 TPY

HYDROGEN CHLORIDE >10 TPY

METHYL ALCOHOL >10 TPY

METHYL CHLORIDE >10 TPY

TOLUENE >10 TPY XYLENE >10 TPY

TOTAL HAPS >250 TPY

Program Applicability

The following chart summarizes the applicability of MOMENTIVE PERFORMANCE MATERIALS with regards to the principal air pollution regulatory programs:

Regulatory Program

Applicability

PSD	NO
NSR (non-attainment)	NO
NESHAP (40 CFR Part 61)	YES
NESHAP (MACT - 40 CFR Part 63)	YES
NSPS	YES
TITLE IV	NO
TITLE V	YES
TITLE VI	NO
RACT	YES
SIP	YES

NOTES:

PSD Prevention of Significant Deterioration (40 CFR 52) - requirements which pertain to major stationary sources located in areas which are in attainment of National Ambient Air Quality Standards (NAAQS) for specified pollutants.

NSR New Source Review (6 NYCRR Part 231) - requirements which pertain to major stationary sources located in areas which are in non-attainment of National Ambient Air Quality Standards (NAAQS)

for specified pollutants.

NESHAP National Emission Standards for Hazardous Air Pollutants (40 CFR 61) - contaminant and source specific emission standards established prior to the Clean Air Act Amendments of 1990 (CAAA)

which were developed for 9 air contaminants (inorganic arsenic, radon, benzene, vinyl chloride, asbestos, mercury, beryllium, radionuclides, and volatile HAP's).

MACT Maximum Achievable Control Technology (40 CFR 63) - contaminant and source specific



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emission standards established by the 1990 CAAA. Under Section 112 of the CAAA, the US EPA is required to develop and promulgate emissions standards for new and existing sources. The standards are to

be based on the best demonstrated control technology and practices in the regulated industry, otherwise known as MACT. The corresponding regulations apply to specific source types and contaminants.

NSPS New Source Performance Standards (40 CFR 60) - standards of performance for specific stationary source categories developed by the US EPA under Section 111 of the CAAA. The standards apply only to those stationary sources which have been constructed or modified after the regulations have been proposed by publication in the Federal Register and only to the specific contaminant(s) listed in the regulation.

Title IV Acid Rain Control Program (40 CFR 72 thru 78) - regulations which mandate the implementation of the acid rain control program for large stationary combustion facilities.

Title VI Stratospheric Ozone Protection (40 CFR 82, Subparts A thru G) - federal requirements that apply to sources which use a minimum quantity of CFC's (chlorofluorocarbons), HCFC's (hydrofluorocarbons) or other ozone depleting substances or regulated substitute substances in equipment such as air conditioners, refrigeration equipment or motor vehicle air conditioners or appliances.

RACT Reasonably Available Control Technology (6 NYCRR Parts 212.10, 226, 227-2, 228, 229, 230, 232, 233, 234, 235, 236) - the lowest emission limit that a specific source is capable of meeting by application of control technology that is reasonably available, considering technological and economic feasibility. RACT is a control strategy used to limit emissions of VOC's and NOx for the purpose of attaining the air quality standard for ozone. The term as it is used in the above table refers to those state air pollution control regulations which specifically regulate VOC and NOx emissions.

SIP State Implementation Plan (40 CFR 52, Subpart HH) - as per the CAAA, all states are empowered and required to devise the specific combination of controls that, when implemented, will bring about attainment of ambient air quality standards established by the federal government and the individual state. This specific combination of measures is referred to as the SIP. The term here refers to those state regulations that are approved to be included in the SIP and thus are considered federally enforceable.

Compliance Status

Facility is in compliance with all requirements.

SIC Codes

SIC or Standard Industrial Classification code is an industrial code developed by the federal Office of Management and Budget for use, among other things, in the classification of establishments by the type of activity in which they are engaged. Each operating establishment is assigned an industry code on the basis

of its primary activity, which is determined by its principal product or group of products produced or distributed, or services rendered. Larger facilities typically have more than one SIC code.

SIC Code Description

2819	INDUSTRIAL INORGANIC CHEMICALS
2821	PLASTICS MATERIALS AND RESINS
2822	SYNTHETIC RUBBER
2869	INDUSTRIAL ORGANIC CHEMICALS, NEC



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SCC Codes

SCC or Source Classification Code is a code developed and used" by the USEPA to categorize processes which result in air emissions for the purpose of assessing emission factor information. Each SCC represents

a unique process or function within a source category logically associated with a point of air pollution emissions. Any operation that causes air pollution can be represented by one or more SCC's.

SCC Code	Description
1-02-004-01	EXTERNAL COMBUSTION BOILERS - INDUSTRIAL INDUSTRIAL BOILER - RESIDUAL OIL Grade 6 Oil
1-02-005-01	EXTERNAL COMBUSTION BOILERS - INDUSTRIAL INDUSTRIAL BOILER - DISTILLATE OIL Grades 1 and 2 Oil
1-02-005-03	EXTERNAL COMBUSTION BOILERS - INDUSTRIAL INDUSTRIAL BOILER - DISTILLATE OIL <10MMBTU/HR **
1-02-006-01	EXTERNAL COMBUSTION BOILERS - INDUSTRIAL INDUSTRIAL BOILER - NATURAL GAS Over 100 MBtu/Hr
1-02-006-02	EXTERNAL COMBUSTION BOILERS - INDUSTRIAL INDUSTRIAL BOILER - NATURAL GAS 10-100 MMBtu/Hr
2-01-001-02	INTERNAL COMBUSTION ENGINES - ELECTRIC GENERATION ELECTRIC UTILITY INTERNAL COMBUSTION ENGINE - DISTILLATE OIL (DIESEL)
3-01-018-47	Reciprocating CHEMICAL MANUFACTURING CHEMICAL MANUFACTURING - PLASTICS PRODUCTION
3-01-026-30	Epoxy Resins CHEMICAL MANUFACTURING CHEMICAL MANUFACTURING - SYNTHETIC RUBBER (MANUFACTURING ONLY)
3-01-026-99	Silicone Rubber CHEMICAL MANUFACTURING CHEMICAL MANUFACTURING - SYNTHETIC RUBBER (MANUFACTURING ONLY)
3-01-070-02	Other Not Classified CHEMICAL MANUFACTURING CHEMICAL MANUFACTURING - INORGANIC CHEMICAL MANUFACTURING (GENERAL)
3-01-820-10	Storage/Transfer CHEMICAL MANUFACTURING CHEMICAL MANUFACTURING - WASTEWATER AGGREGATE CHEMICAL DIANT WASTEWATER CYCTEM, CLARLEIER
3-01-840-01	CHEMICAL PLANT WASTEWATER SYSTEM: CLARIFIER CHEMICAL MANUFACTURING CHEMICAL MANUFACTURING - GENERAL PROCESSES Distillation Units
3-01-999-99	CHEMICAL MANUFACTURING CHEMICAL MANUFACTURING - OTHER NOT CLASSIFIED
3-05-102-99	Specify in Comments Field MINERAL PRODUCTS MINERAL PRODUCTS - BULK MATERIALS STORAGE BINS
3-85-001-10	Other Not Classified COOLING TOWER

COOLING TOWER - PROCESS COOLING



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	OTHER NOT SPECIFIED
3-99-999-94	MISCELLANEOUS MANUFACTURING INDUSTRIES
	MISCELLANEOUS INDUSTRIAL PROCESSES
	Other Not Classified
4-01-002-99	ORGANIC SOLVENT EVAPORATION
	ORGANIC SOLVENT EVAPORATION - DEGREASING
	OTHER NOT CLASSIFIED - OPEN-TOP VAPOR
	DEGREASING
4-07-999-97	ORGANIC CHEMICAL STORAGE
	ORGANIC CHEMICAL STORAGE - MISCELLANEOUS
	Specify in Comments
4-07-999-98	ORGANIC CHEMICAL STORAGE
	ORGANIC CHEMICAL STORAGE - MISCELLANEOUS
	Specify in Comments
4-90-002-06	ORGANIC SOLVENT EVAPORATION
	ORGANIC SOLVENT EVAPORATION WASTE SOLVENT
	RECOVERY OPERATIONS
	Fugitive Leaks
5-03-007-01	SOLID WASTE DISPOSAL - INDUSTRIAL
	SOLID WASTE DISPOSAL: INDUSTRIAL - LIQUID
	WASTE
	General
6-84-800-01	MACT MISCELLANEOUS PROCESSES (CHEMICALS)
	MACT MISC PROCESSES (CHEMICALS) - EQUIPMENT
	LEAKS
	EQUIPMENT LEAKS

Facility Emissions Summary

In the following table, the CAS No. or Chemical Abstract Service code is an identifier assigned to every chemical compound. [NOTE: Certain CAS No.'s contain a 'NY' designation within them. These are not true CAS No.'s but rather an identification which has been developed by the department to identify groups of contaminants which ordinary CAS No.'s do not do. As an example, volatile organic compounds or VOC's are identified collectively by the NY CAS No. 0NY998-00-0.] The PTE refers to the Potential to Emit. This is defined as the maximum capacity of a facility or air contaminant source to emit any air contaminant under its physical and operational design. Any physical or operational limitation on the capacity of the facility or air contamination source to emit any air contaminant, including air pollution control equipment and/or restrictions on the hours of operation, or on the type or amount or material combusted, stored, or processed, shall be treated as part of the design only if the limitation is contained in federally enforceable permit conditions. The PTE Range represents an emission range for a contaminant. Any PTE quantity that is displayed represents a facility-wide emission cap or limitation for that contaminant. If no PTE quantity is displayed, the PTE Range is provided to indicate the approximate magnitude of facility-wide emissions for the specified contaminant in terms of tons per year (tpy). The term 'HAP' refers to any of the hazardous air pollutants listed in section 112(b) of the Clean Air Act Amendments of 1990. Total emissions of all hazardous air pollutants are listed under the special NY CAS No. 0NY100-00-0. In addition, each individual hazardous air pollutant is also listed under its own specific CAS No. and is identified in the list below by the (HAP) designation.

Cas No.	Contaminant Name	PTE
	lbs/yı	Range
000075-65-0	2-METHYL-2-PROPANOL	> 0 but < 2.5 tpy
000092-52-4	1, 1 BIPHENYL	> 0 but < 10 tpy
000079-34-5	1,1,2,2-	> 0 but < 10 tpy
	TETRACHLOROETHANE	
000057-14-7	1,1-DIMETHYL HYDRAZINE	> 0 but < 10 tpy
000120-82-1	1,2,4-TRICHLOROBENZENE	> 0 but < 10 tpy
000084-74-2	1,2-	> 0 but < 10 tpy
	BENZENEDICARBOXYLIC	



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	ACID DIDLENI ECEED	
000120-80-9	ACID, DIBUTYL ESTER 1,2-BENZENEDIOL	> 0 but < 10 tmg
000120-80-9	1,2-DICHLOROETHANE	> 0 but < 10 tpy > 0 but < 10 tpy
000107-00-2	1,2-ETHANEDIOL	> 0 but < 10 tpy > 0 but < 10 tpy
000107-21-1	1,3 DIMETHYL BENZENE	> 0 but < 10 tpy > 0 but < 10 tpy
000095-80-7	1,3-BENZENEDIAMINE, 4-	> 0 but < 10 tpy
000075 00 7	METHYL-	> 0 but < 10 tpy
000106-99-0	1,3-BUTADIENE	> 0 but < 10 tpy
000126-99-8	1,3-BUTADIENE, 2-	> 0 but < 10 tpy
	CHLORO-	17
000085-44-9	1,3-	> 0 but < 10 tpy
	ISOBENZOFURANDIONE	17
000123-31-9	1,4-BENZENEDIOL	> 0 but < 10 tpy
000123-91-1	1,4-DIETHYLENE DIOXIDE	> 0 but < 10 tpy
000098-86-2	1-PHENYLETHANONE	> 0 but < 10 tpy
000542-75-6	1-PROPENE, 1,3-DICHLORO-	> 0 but < 10 tpy
000121-14-2	2,4, DINITRO TOLUENE	> 0 but < 10 tpy
000051-28-5	2,4, DINITROPHENOL	> 0 but < 10 tpy
000088-06-2	2,4,6 TRICHLOROPHENOL	> 0 but < 10 tpy
000108-31-6	2,5 - FURANDIONE	> 0 but < 10 tpy
000053-96-3	2-	> 0 but < 10 tpy
000078 50 1	ACETYLAMINOFLUORENE	> 0 but < 10 tm;
000078-59-1	2-CYCLOHEXEN-1- ONE.3,5,5-TRIMETHYL	> 0 but < 10 tpy
000095-48-7	2-METHYL-PHENOL	> 0 but < 10 tpy
000108-10-1	2-PENTANONE, 4-METHYL	> 0 but < 10 tpy > 0 but < 10 tpy
00079-10-7	2-PROPENOIC ACID	> 0 but < 10 tpy > 0 but < 10 tpy
000140-88-5	2-PROPENOIC ACID, ETHYL	> 0 but < 10 tpy
000110 00 3	ESTER	> 0 вас стотру
000119-90-4	3,3'-	> 0 but < 10 tpy
	DIMETHOXYBENZIDINE	
000107-05-1	3-CHLORO-1-PROPENE	> 0 but < 10 tpy
000101-77-9	4,4'-	> 0 but < 10 tpy
	DIAMINODIPHENYLMETH	
	ANE	
000101-14-4	4,4-METHYLENE BIS(2-	> 0 but < 10 tpy
	CHLOROANILINE)	
0NY502-00-0	40 CFR 60-63 - TOTAL	>= 250 tpy but < 75,000 tpy
	ORGANIC COMPOUNDS	
000000 11 7	(TOC)	0.1 10 .
000060-11-7	4-	> 0 but < 10 tpy
	DIMETHYLAMINOAZOBEN	
000092-93-3	ZENE 4-NITROBIPHENYL	> 0 but < 10 tpy
000092-93-3	ACETALDEHYDE	> 0 but < 10 tpy > 0 but < 10 tpy
000060-35-5	ACETALDENTIDE	> 0 but < 10 tpy > 0 but < 10 tpy
000064-19-7	ACETIC ACID	= 250 tpy but < 75,000 tpy
000108-05-4	ACETIC ACID ETHENYL	> 0 but < 10 tpy
000100 05 1	ESTER	> 0 вас стотру
000079-11-8	ACETIC ACID, CHLORO	> 0 but < 10 tpy
000075-05-8	ACETONITRILE	> 0 but < 10 tpy
000075-36-5	ACETYL CHLORIDE	>= 250 tpy but < 75,000 tpy
000107-02-8	ACROLEIN	> 0 but < 10 tpy
000532-27-4	ALPHA-	> 0 but < 10 tpy
	CHLOROACETOPHENONE	
007664-41-7	AMMONIA	>= 250 tpy but < 75,000 tpy
000062-53-3	ANILINE	> 0 but < 10 tpy
007440-36-0	ANTIMONY	> 0 but < 10 tpy
007440-38-2	ARSENIC	> 0 but < 10 tpy
001332-21-4	ASBESTOS	> 0 but < 10 tpy
000075-55-8	AZIRIDINE, 2-METHYL	> 0 but < 10 tpy
000090-04-0	BENZENAMINE, 2- METHOXY	> 0 but < 10 tpy
000095-53-4	METHOXY BENZENAMINE, 2-METHYL	> 0 but < 10 tpy
000073-33-4	DENZEMANTINE, 2-WETTITE	> 0 out < 10 tpy



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000121-69-7	BENZENAMINE, N, N-	> 0 but < 10 tpy
000071 42 2	DIMETHYL	10 4
000071-43-2	BENZENE (1	>= 10 tpy
000098-82-8	BENZENE, (1-	> 0 but < 10 tpy
000106-46-7	METHYLETHYL) BENZENE, 1,4-DICHLORO-	> 0 but < 10 tpy
000100-40-7	BENZENE, 1,4-DICHLORO- BENZENE. 2.4-	> 0 but < 10 tpy > 0 but < 10 tpy
000304-04-9	DIISOCYANATO-1-	>0 but < 10 tpy
	METHYL-	
000098-07-7	BENZENE,	> 0 but < 10 tpy
000070 07 7	TRICHLOROMETHYL	> 0 but < 10 tpy
000095-47-6	BENZENE,1,2-DIMETHYL	> 0 but < 10 tpy
000092-87-5	BENZIDINE	> 0 but < 10 tpy
000100-44-7	BENZYL CHLORIDE	> 0 but < 10 tpy
007440-41-7	BERYLLIUM	> 0 but < 10 tpy
000057-57-8	BETA-PROPIOLACTONE	> 0 but < 10 tpy
000117-81-7	BIS(2-ETHYLHEXYL)	> 0 but < 10 tpy
	PHTHALATE	
000075-25-2	BROMOFORM	> 0 but < 10 tpy
007440-43-9	CADMIUM	> 0 but < 10 tpy
000133-06-2	CAPTAN	> 0 but < 10 tpy
000051-79-6	CARBAMIC ACID, ETHY	> 0 but < 10 tpy
000000 44.5	ESTER	0.1
000079-44-7	CARBAMIC CHLORIDE,	> 0 but < 10 tpy
000075 15 0	DIMETHYL	0.1
000075-15-0	CARBON DISULFIDE	> 0 but < 10 tpy
000630-08-0	CARBON MONOXIDE	>= 250 tpy but < 75,000 tpy > 0 but < 10 tpy
000056-23-5	CARBON TETRACHLORIDE CARBONYL SULFIDE	> 0 but < 10 tpy > 0 but < 10 tpy
000463-58-1 000133-90-4	CHLORAMBEN	> 0 but < 10 tpy > 0 but < 10 tpy
016887-00-6	CHLORIDE ION CL-	> 0 but < 10 tpy > 0 but < 2.5 tpy
007782-50-5	CHLORINE	> 0 but < 2.5 tpy >= 10 tpy
000108-90-7	CHLOROBENZENE	> 0 but < 10 tpy
000067-66-3	CHLOROFORM	> 0 but < 10 tpy
007738-94-5	CHROMIC ACID	> 0 but < 10 tpy
007440-47-3	CHROMIUM	> 0 but < 10 tpy
007440-48-4	COBALT	>=10 tpy
000091-44-1	COUMARIN, 7-	>= 2.5 tpy but < 10 tpy
	(DIETHYLAMINO)-4-	
	METHYL-	
001319-77-3	CRESYLIC ACID	> 0 but < 10 tpy
000156-62-7	CYANAMIDE, CALCIUM	> 0 but < 10 tpy
	SALT (1:1)	
000057-12-5	CYANIDE	> 0 but < 10 tpy
000334-88-3	DIAZOMETHANE	> 0 but < 10 tpy
000132-64-9	DIBENZOFURAN	> 0 but < 10 tpy
000075-09-2	DICHLOROMETHANE	> 0 but < 10 tpy
000131-11-3	DIMETHYL PHTHALATE	> 0 but < 10 tpy
000067-64-1	DIMETHYL KETONE	>= 250 tpy but < 75,000 tpy
000075-78-5	DIMETHYLDICHLOROSILA NE	> 0 but < 2.5 tpy
022431-89-6	DIOXANE,1,2-3,3,6,6-	> 0 but < 2.5 tpy
022431-09-0	TETRAMETHYL	> 0 but < 2.5 tpy
000071-55-6	ETHANE, 1,1,1-TRICHLORO	>= 10 tpy
000071 55 6	ETHANE, 1,1,2-TRICHLORO	> 0 but < 10 tpy
000075-34-3	ETHANE, 1,1-DICHLORO-	> 0 but < 10 tpy
000111-44-4	ETHANE, 1,1'-OXYBIS 2-	> 0 but < 10 tpy
· · · · · · · · · · · · · · · · · · ·	CHLORO	
000106-93-4	ETHANE, 1,2-DIBROMO	> 0 but < 10 tpy
000075-00-3	ETHANE, CHLORO	> 0 but < 10 tpy
000067-72-1	ETHANE, HEXACHLORO	> 0 but < 10 tpy
000111-42-2	ETHANOL, 2,2'-IMINOBIS-	> 0 but < 10 tpy
000110-80-5	ETHANOL, 2-ETHOXY-	> 0 but < 10 tpy
000075-35-4	ETHENE,1,1-DICHLORO	> 0 but < 10 tpy



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000510-15-6	ETHYL 4,4'-	> 0 but < 10 tpy
	DICHLOROBENZILATE	
000064-17-5	ETHYL ALCOHOL	>= 250 tpy but < 75,000 tpy
000106 99 7	(ETHANOL) ETHYL OXIRANE	> 0. but < 10 toy
000106-88-7		> 0 but < 10 tpy
000100-41-4	ETHYLBENZENE	>= 10 tpy
000079-06-1	ETHYLENE CARBOXAMIDE	> 0 but < 10 tpy
000075-21-8	ETHYLENE OXIDE	> 0 but < 10 tpy
000096-45-7	ETHYLENE THIOUREA	> 0 but < 10 tpy
000151-56-4	ETHYLENEIMINE	> 0 but < 10 tpy
000050-00-0	FORMALDEHYDE	> 0 but < 10 tpy
000068-12-2	FORMAMIDE, N,N-	> 0 but < 10 tpy
000000122	DIMETHYL	y 0 out (10 tp)
0NY100-00-0	HAP	>= 250 tpy but < 75,000 tpy
000076-44-8	HEPTACHLOR	> 250 tpy but $< 75,000$ tpy > 0 but < 10 tpy
		> 0 but < 10 tpy > 0 but < 10 tpy
000118-74-1	HEXACHLOROBENZENE	
000087-68-3	HEXACHLOROBUTADIENE	> 0 but < 10 tpy
000077-47-4	HEXACHLOROCYCLOPENT	> 0 but < 10 tpy
	ADIENE	
000541-05-9	HEXAMETHYLCYCLOTRISI	>= 250 tpy but < 75,000 tpy
	LOXANE	
000999-97-3	HEXAMETHYLDISILAZANE	>= 250 tpy but < 75,000 tpy
000107-46-0	HEXAMETHYLDISILOXAN	>= 250 tpy but < 75,000 tpy
	E	
000110-54-3	HEXANE	>= 10 tpy
000822-06-0	HEXANE, 1,6-	> 0 but < 10 tpy
000822-00-0		>0 but < 10 tpy
000202 01 2	DIISOCYANATO-	0.1 (.10 (
000302-01-2	HYDRAZINE	> 0 but < 10 tpy
001333-74-0	HYDROGEN	>= 250 tpy but < 75,000 tpy
007647-01-0	HYDROGEN CHLORIDE	>= 10 tpy
007664-39-3	HYDROGEN FLUORIDE	> 0 but < 10 tpy
000122-66-7	HYRAZINE, 1,2 - DIPHENYL	> 0 but < 10 tpy
000067-63-0	ISOPROPYL ALCOHOL	>= 250 tpy but < 75,000 tpy
007439-92-1	LEAD	> 0 but < 10 tpy
001309-60-0	LEAD DIOXIDE	> 0 but < 10 tpy
007439-96-5	MANGANESE	> 0 but < 10 tpy
007439-97-6	MERCURY	> 0 but < 10 tpy
000062-75-9	METHANAMINE, N-	> 0 but < 10 tpy
000002-73-7	METHYL-N-NITROSO	> 0 but < 10 tpy
000542 88 1		> 0 hust < 10 tmm
000542-88-1	METHANE, OXYBIS	> 0 but < 10 tpy
	(CHLORO)	
000072-43-5	METHOXYCHLOR	> 0 but < 10 tpy
000080-62-6	METHYL ACRYLIC	> 0 but < 10 tpy
	ACIDMETHYL ESTER	
000067-56-1	METHYL ALCOHOL	>= 10 tpy
000074-83-9	METHYL BROMIDE	> 0 but < 10 tpy
000074-87-3	METHYL CHLORIDE	>= 10 tpy
000107-30-2	METHYL	> 0 but < 10 tpy
	CHLOROMETHYLETHER	
000078-93-3	METHYL ETHYL KETONE	> 0 but < 10 tpy
000060-34-4	METHYL HYDRAZINE	> 0 but < 10 tpy > 0 but < 10 tpy
00000-34-4	METHYL IODIDE	> 0 but < 10 tpy > 0 but < 10 tpy
000624-83-9	METHYL ISOCYANATE	> 0 but < 10 tpy
001634-04-4	METHYL TERTBUTYL	> 0 but < 10 tpy
	ETHER	
000101-68-8	METHYLENE BISPHENYL	> 0 but < 10 tpy
	ISOCYANATE	
000075-79-6	METHYLTRICHLOROSILAN	>= 250 tpy but < 75,000 tpy
	Е	17
001185-55-3	METHYLTRIMETHOXYSIL	>= 250 tpy but < 75,000 tpy
301103 33 3	ANE	> = 255 tpy out < 75,000 tpy
000121-44-8	N,N-DIETHYL	> 0 but < 10 tpy
000121-44-0		≥ 0 out < 10 tpy
000001 20 2	ETHANAMINE	> 0 byt + 10 to
000091-20-3	NAPHTHALENE	> 0 but < 10 tpy



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007440-02-0	NICKEL METAL AND	> 0 but < 10 tpy
007110 02 0	INSOLUBLE COMPOUNDS	> o but < 10 tpy
000098-95-3	NITROBENZENE	> 0 but < 10 tpy
010102-44-0	NITROGEN DIOXIDE	>= 250 tpy but < 75,000 tpy
000059-89-2	NITROSOMORPHOLINE	> 0 but < 10 tpy
000684-93-5	NITROSO-N-METHYLUREA	> 0 but < 10 tpy > 0 but < 10 tpy
000556-67-2	OCTAMETHYLCYCLOTETR	> 0 but < 10 tpy >= 250 tpy but < 75,000 tpy
000330-07-2	A SILOXANE	>= 230 tpy but < 73,000 tpy
000110 02 7	O-TOLIDINE	> 0 but < 10 torr
000119-93-7		> 0 but < 10 tpy
0NY210-00-0	OXIDES OF NITROGEN	>= 250 tpy but < 75,000 tpy
000106-89-8	OXIRANE,	> 0 but < 10 tpy
000000 67.1	(CHLOROMETHYL)	0.1 10 .
000092-67-1	P-AMINODIPHENYL	> 0 but < 10 tpy
000100-02-7	PARA-NITROPHENOL	> 0 but < 10 tpy
0NY075-00-0	PARTICULATES	>= 250 tpy but < 75,000 tpy
000082-68-8	PENTACHLORONITROBEN	> 0 but < 10 tpy
	ZENE	
000540-84-1	PENTANE, 2,2,4-	> 0 but < 10 tpy
	TRIMETHYL-	
000127-18-4	PERCHLOROETHYLENE	> 0 but < 10 tpy
000108-95-2	PHENOL	> 0 but < 10 tpy
000534-52-1	PHENOL, 2-METHYL-4,6-	> 0 but < 10 tpy
	DINITRO	
000108-39-4	PHENOL, 3-METHYL	> 0 but < 10 tpy
000106-44-5	PHENOL, 4-METHYL	> 0 but < 10 tpy
000087-86-5	PHENOL, PENTACHLORO	> 0 but < 10 tpy
007803-51-2	PHOSPHINE	> 0 but < 10 tpy
000062-73-7	PHOSPHORIC ACID, 2,2-	> 0 but < 10 tpy
000002 /2 /	DICHLOROETHENYL	y 0 out (10 tp)
	DIMETHYL ESTER	
000680-31-9	PHOSPHORIC TRIAMIDE,	> 0 but < 10 tpy
000000-31-7	HEXAMETHYL	> 0 but < 10 tpy
007723-14-0		> 0 but < 10 tpy
	PHOSPHORUS (YELLOW)	1.
0NY075-00-5	PM-10	>= 250 tpy but < 75,000 tpy
001336-36-3	POLYCHLORINATED	> 0 but < 10 tpy
000106 50 3	BIPHENYL	0.1
000106-50-3	P-PHENYLENEDIAMINE	> 0 but < 10 tpy
001120-71-4	PROPANE SULTONE	> 0 but < 10 tpy
000096-12-8	PROPANE, 1,2-DIBROMO-3-	> 0 but < 10 tpy
	CHLORO	
000078-87-5	PROPANE, 1,2-DICHLORO	> 0 but < 10 tpy
000075-56-9	PROPANE, 1,2-EPOXY-	> 0 but < 10 tpy
000079-46-9	PROPANE, 2-NITRO	> 0 but < 10 tpy
000107-13-1	PROPENENITRILE	> 0 but < 10 tpy
000123-38-6	PROPIONALDEHYDE	> 0 but < 10 tpy
000091-22-5	QUINOLINE	> 0 but < 10 tpy
000106-51-4	QUINONE	> 0 but < 10 tpy
010043-92-2	RADON	> 0 but < 10 tpy
007782-49-2	SELENIUM	> 0 but < 10 tpy
068479-14-1	SILANE, CHLORO METHYL	>= 250 tpy but < 75,000 tpy
	DERIVS	1, 1,
001719-58-0	SILANE,	> 0 but < 2.5 tpy
	CHLOROETHENYLDIMETH	
	YL	
000124-70-9	SILANE,	> 0 but < 2.5 tpy
000124 70 9	DICHLOROETHENYLMETH	> 0 but < 2.5 tpy
	YL	
001112 20 6		> 0 hut < 2.5 tmm
001112-39-6	SILANE,	> 0 but < 2.5 tpy
000075 04 5	DIMETHOXYDIMETHYL	. 0.1 2.5
000075-94-5	SILANE,	> 0 but < 2.5 tpy
000000000	TRICHLOROETHENYL	
000993-07-7	SILANE, TRIMETHYL-	>= 250 tpy but < 75,000 tpy
001066-35-9	SILANE, CHLORODIMETHY	> 0 but < 2.5 tpy
	L	



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063148-62-9	SILOXANES AND	>= 250 tpy but < 75,000 tpy
	SILICONES,DI-ME	
000100-42-5	STYRENE	> 0 but < 10 tpy
000096-09-3	STYRENE OXIDE	> 0 but < 10 tpy
007446-09-5	SULFUR DIOXIDE	>= 250 tpy but < 75,000 tpy
000064-67-5	SULFURIC ACID, DIETHYL	> 0 but < 10 tpy
	ESTER	
000077-78-1	SULFURIC ACID,	> 0 but < 10 tpy
	DIMETHYL ESTER	
010026-04-7	TETRACHLORO SILANE	> 0 but < 2.5 tpy
007550-45-0	TITANIUM	> 0 but < 10 tpy
	TETRACHLORIDE	
000108-88-3	TOLUENE	>= 10 tpy
000079-01-6	TRICHLOROETHYLENE	> 0 but < 10 tpy
000095-95-4	TRICHLOROPHENOL, 2,4,5	> 0 but < 10 tpy
000593-60-2	VINYL BROMIDE	> 0 but < 10 tpy
000075-01-4	VINYL CHLORIDE	> 0 but < 10 tpy
0NY998-00-0	VOC	>= 250 tpy but < 75,000 tpy
001330-20-7	XYLENE, M, O & P MIXT.	>= 10 tpy
000106-42-3	XYLENE, PARA-	> 0 but < 10 tpy

NOTIFICATION OF GENERAL PERMITTEE OBLIGATIONS

Item A: Emergency Defense - 6 NYCRR 201-1.5

An emergency constitutes an affirmative defense to an action brought for noncompliance with emissions limitations or permit conditions for all facilities in New York State.

- (a) The affirmative defense of emergency shall be demonstrated through properly signed, contemporaneous operating logs, or other relevant evidence that:
 - (1) An emergency occurred and that the facility owner and/or operator can identify the cause(s) of the emergency;
 - (2) The equipment at the permitted facility causing the emergency was at the time being properly operated;
 - (3) During the period of the emergency the facility owner and/or operator took all reasonable steps to minimize levels of emissions that exceeded the emission standards, or other requirements in the permit; and
 - (4) The facility owner and/or operator notified the Department within two working days after the event occurred. This notice must contain a description of the emergency, any steps taken to mitigate emissions, and corrective actions taken.
- (b) In any enforcement proceeding, the facility owner and/or operator seeking to establish the occurrence of an emergency has the burden of proof.
- (c) This provision is in addition to any emergency or upset provision contained in any applicable requirement.

Item B: Public Access to Recordkeeping for Title V Facilities - 6 NYCRR 201-1.10(b)

The Department will make available to the public any permit application, compliance plan, permit, and monitoring and compliance certification report pursuant to Section 503(e) of the Act, except for information entitled to confidential treatment pursuant to 6 NYCRR Part 616 - Public Access to records and Section 114(c) of the Act.

Item C: Timely Application for the Renewal of Title V Permits -6 NYCRR Part 201-6.3(a)(4)



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Owners and/or operators of facilities having an issued Title V permit shall submit a complete application at least 180 days, but not more than eighteen months, prior to the date of permit expiration for permit renewal purposes.

Item D: Certification by a Responsible Official - 6 NYCRR Part 201-6.3(d)(12)

Any application, form, report or compliance certification required to be submitted pursuant to the federally enforceable portions of this permit shall contain a certification of truth, accuracy and completeness by a responsible official. This certification shall state that based on information and belief formed after reasonable inquiry, the statements and information in the document are true, accurate, and complete.

Item E: Requirement to Comply With All Conditions - 6 NYCRR Part 201-6.5(a)(2)

The permittee must comply with all conditions of the Title V facility permit. Any permit non-compliance constitutes a violation of the Act and is grounds for enforcement action; for permit termination, revocation and reissuance, or modification; or for denial of a permit renewal application.

Item F: Permit Revocation, Modification, Reopening, Reissuance or Termination, and Associated Information Submission Requirements - 6 NYCRR Part 201-6.5(a)(3)

This permit may be modified, revoked, reopened and reissued, or terminated for cause. The filing of a request by the permittee for a permit modification, revocation and reissuance, or termination, or of a notification of planned changes or anticipated noncompliance does not stay any permit condition.

Item G: Cessation or Reduction of Permitted Activity Not a Defense - 6 NYCRR 201-6.5(a)(5)

It shall not be a defense for a permittee in an enforcement action to claim that a cessation or reduction in the permitted activity would have been necessary in order to maintain compliance with the conditions of this permit.

Item H: Property Rights - 6 NYCRR 201-6.5(a)(6)

This permit does not convey any property rights of any sort or any exclusive privilege.

Item I: Severability - 6 NYCRR Part 201-6.5(a)(9)

If any provisions, parts or conditions of this permit are found to be invalid or are the subject of a challenge, the remainder of this permit shall continue to be valid.

Item J: Permit Shield - 6 NYCRR Part 201-6.5(g)

All permittees granted a Title V facility permit shall be covered under the protection of a permit shield, except as provided under 6 NYCRR Subpart 201-6. Compliance with the conditions of the permit shall be deemed compliance with any applicable requirements as of the date of permit issuance, provided that such applicable requirements are included and are specifically identified in the permit, or the Department, in acting on the permit application or revision, determines in writing that other requirements specifically identified are not applicable to the major stationary source, and the permit includes the determination or a concise summary thereof. Nothing herein shall preclude the Department from revising or revoking the permit pursuant to 6 NYCRR Part 621 or from exercising its summary



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abatement authority. Nothing in this permit shall alter or affect the following:

- i. The ability of the Department to seek to bring suit on behalf of the State of New York, or the Administrator to seek to bring suit on behalf of the United States, to immediately restrain any person causing or contributing to pollution presenting an imminent and substantial endangerment to public health, welfare or the environment to stop the emission of air pollutants causing or contributing to such pollution;
- ii. The liability of a permittee of the Title V facility for any violation of applicable requirements prior to or at the time of permit issuance;
- iii. The applicable requirements of Title IV of the Act;
- iv. The ability of the Department or the Administrator to obtain information from the permittee concerning the ability to enter, inspect and monitor the facility.

Item K: Reopening for Cause - 6 NYCRR Part 201-6.5(i)

This Title V permit shall be reopened and revised under any of the following circumstances:

- i. If additional applicable requirements under the Act become applicable where this permit's remaining term is three or more years, a reopening shall be completed not later than 18 months after promulgation of the applicable requirement. No such reopening is required if the effective date of the requirement is later than the date on which this permit is due to expire, unless the original permit or any of its terms and conditions has been extended by the Department pursuant to the provisions of Part 2 01-6.7 and Part 621.
- ii. The Department or the Administrator determines that the permit contains a material mistake or that inaccurate statements were made in establishing the emissions standards or other terms or conditions of the permit.
- iii. The Department or the Administrator determines that the Title V permit must be revised or reopened to assure compliance with applicable requirements.
- iv. If the permitted facility is an "affected source" subject to the requirements of Title IV of the Act, and additional requirements (including excess emissions requirements) become applicable. Upon approval by the Administrator, excess emissions offset plans shall be deemed to be incorporated into the permit.

Proceedings to reopen and issue Title V facility permits shall follow the same procedures as apply to initial permit issuance but shall affect only those parts of the permit for which cause to reopen exists.

Reopenings shall not be initiated before a notice of such intent is provided to the facility by the Department at least thirty days in advance of the date that the permit is to be reopened, except that the Department may provide a shorter time period in the case of an emergency.

Item L: Permit Exclusion - ECL 19-0305

The issuance of this permit by the Department and the receipt thereof by the Applicant does not and shall not be construed as barring, diminishing, adjudicating or in any way affecting any legal, administrative or equitable rights or claims, actions, suits, causes of



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action or demands whatsoever that the Department may have against the Applicant for violations based on facts and circumstances alleged to have occurred or existed prior to the effective date of this permit, including, but not limited to, any enforcement action authorized pursuant to the provisions of applicable federal law, the Environmental Conservation Law of the State of New York (ECL) and Chapter III of the Official Compilation of the Codes, Rules and Regulations of the State of New York (NYCRR). The issuance of this permit also shall not in any way affect pending or future enforcement actions under the Clean Air Act brought by the United States or any person.

Item M: Federally Enforceable Requirements - 40 CFR 70.6(b)

All terms and conditions in this permit required by the Act or any applicable requirement, including any provisions designed to limit a facility's potential to emit, are enforceable by the Administrator and citizens under the Act. The Department has, in this permit, specifically designated any terms and conditions that are not required under the Act or under any of its applicable requirements as being enforceable under only state regulations.

NOTIFICATION OF GENERAL PERMITTEE OBLIGATIONS

Item A: General Provisions for State Enforceable Permit Terms and Condition - 6 NYCRR Part 201-5

Any person who owns and/or operates stationary sources shall operate and maintain all emission units and any required emission control devices in compliance with all applicable Parts of this Chapter and existing laws, and shall operate the facility in accordance with all criteria, emission limits, terms, conditions, and standards in this permit. Failure of such person to properly operate and maintain the effectiveness of such emission units and emission control devices may be sufficient reason for the Department to revoke or deny a permit.

The owner or operator of the permitted facility must maintain all required records on-site for a period of five years and make them available to representatives of the Department upon request. Department representatives must be granted access to any facility regulated by this Subpart, during normal operating hours, for the purpose of determining compliance with this and any other state and federal air pollution control requirements, regulations or law.

Regulatory Analysis

Location Facility/EU/EP/P	Regulation rocess/ES	Condition	Short Description
 FACILITY	ECL 19-0301	479	Powers and Duties of the Department with respect to air pollution control
FACILITY	40CFR 52-A.21	27, 28, 31, 32, 33, 34, 35, 37	Prevention of Significant Deterioration
FACILITY	40CFR 60-A.11	111	General provisions - compliance with standards and maintenance



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FACILITY	40CFR 60-A.11(d)	112	requirements General provisions - compliance with standards and maintenance
FACILITY	40CFR 60-A.12	113	requirements General provisions - Circumvention
FACILITY	40CFR 60-A.13(a)	114	General provisions - Monitoring
FACILITY	40CFR 60-A.13(d)	115	requirements General provisions - Monitoring
FACILITY	40CFR 60-A.13(e)	116	requirements General provisions - Monitoring
FACILITY	40CFR 60-A.13(h)	117	requirements General provisions - Monitoring
FACILITY	40CFR 60-A.4	105	requirements General provisions - Address
FACILITY	40CFR 60-A.7(a)	1 -19	Notification and Recordkeeping
FACILITY	40CFR 60-A.7(b)	107	Notification and
FACILITY	40CFR 60-A.7(c)	108	Recordkeeping Notification and Recordkeeping
FACILITY	40CFR 60-A.7(d)	109	Notification and
FACILITY	40CFR 60-A.7(f)	110	Recordkeeping Notification and
FACILITY	40CFR 60-Db.43b(f)	118	Recordkeeping Standard for Particulate Matter
FACILITY	40CFR 60-Db.43b(g)	119	Opacity. Standard for Particulate Matter
FACILITY	40CFR 60-Db.44b(a)(1)	120	Exemption. Standard for Nitrogen Oxides Firing Natural Gas and Distillate
FACILITY	40CFR 60-Db.44b(h)	121	Oil. (see narrative) Standards for Nitrogen Oxides
FACILITY	40CFR 60-Db.45b(j)	122	Provisions. Compliance and Performance Test Methods and Procedures for Sulfur
FACILITY	40CFR 60-Db.48b(c)	123	Dioxide. Emission Monitoring for Particulate Matter and Nitrogen
FACILITY	40CFR 60-Db.48b(f)	124	Oxides. Emission Monitoring for Particulate Matter and Nitrogen
FACILITY	40CFR 60-Db.49b(f)	125	Oxides. Reporting and Recordkeeping
FACILITY	40CFR 60-Db.49b(g)	126	Requirements. Reporting and Recordkeeping Requirements.



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a	40 GTD 60 Dl 40l ()	4.0.5	
FACILITY	40CFR 60-Db.49b(r)	127	Reporting and Recordkeeping Requirements.
FACILITY	40CFR 60-	128	NSPS for volatile
FACILITI	Kb.112b(a)(3)	120	organic liquid
	ND.112D(a)(3)		storage vessels-
			standard for volatile
			organic compounds
			(VOC)
FACILITY	40CFR 60-Kb.113b(c)	129	NSPS for volatile
			organic liquid
			storage vessels-
			testing and
			procedures
FACILITY	40CFR 60-Kb.115b(c)	130	NSPS for volatile
			organic liquid
			storage vessels-
			reporting and
			recordkeeping
	40GED CO KI 11Ch (h)	1.2.1	requirements
FACILITY	40CFR 60-Kb.116b(b)	131	NSPS for volatile
			organic liquid storage vessels-
			monitoring of
			operations
FACILITY	40CFR 60-NNN.662(a)	132	Standards of
	,,,		performance for VOC
			emissions from SOCMI
			distillation
			operations -
			standards
FACILITY	40CFR 60-NNN.663(a)	133	Standards of
			performance for VOC
			emissions from SOCMI
			distillation operations -
			standards
FACILITY	40CFR 60-NNN.665	134	Standards of
			performance for VOC
			emissions from SOCMI
			distillation
			operations -
			reporting and
			recordkeeping
FACILITY	40GED 60 DDD 700/a)	125	requirements Standards of
FACILITY	40CFR 60-RRR.702(a)	135	performance for VOC
			emissions from SOCMI
			reactor processes -
			standards
FACILITY	40CFR 61-A	136	General Provisions -
			applicability of
			part 61
FACILITY	40CFR 61-M.145	137	Asbestos standards:
			standard for
			demolition and
FACTITTY	40CED 62 7 C/a\/1\	1 2 0	renovation
FACILITY	40CFR 63-A.6(e)(1)	138	General Provisions - Operations and
			Maintenance
			Requirements During
			Startup, Shutdown,
			and Malfunction
FACILITY	40CFR 63-A.6(e)(1)(i)	139	Operation and
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			Maintenance (MACT
FACILITY	40CFR 63-A.6(e)(3)	140	Gen. Prov.) Startup, Shutdown
FACILITY	40CFR 63-A.6(f)(1)	141	and Malfunction Plan Compliance with Nonopacity Standards (MACT Gen. Prov.)
FACILITY	40CFR 63-A.6(f)(2)(i)	142	(MACT Gen. Prov.) Methods for Determining Compliance (MACT Gen. Prov.)
FACILITY	40CFR 63- A.6(f)(2)(ii)	143	Methods for determining compliance (MACT Gen. Prov.)
FACILITY	40CFR 63-DD.680(d)	242	Offsite Waste and Recovery Operations NESHAP - Facility- wide exemption
FACILITY	40CFR 63- EEE.1203(a)(1)	303	Hazardous Waste Combustion NESHAP - Interim Emission Standards and Operating Limits - existing sources
FACILITY	40CFR 63- EEE.1203(a)(2)	304	Mercury emission standard
FACILITY	40CFR 63- EEE.1203(a)(3)	305	lead and cadmium, combined emission limit for existing hazardous waste combustors
FACILITY	40CFR 63- EEE.1203(a)(4)	306	arsenic, berillium and chromium, combined, emission limit for hazardous waste incinerators
FACILITY	40CFR 63- EEE.1203(a)(5)	1 -31	carbon monoxide and hydrocarbon emission limits for existing hazardous waste incinerators
FACILITY	40CFR 63- EEE.1203(a)(6)	308	hydrochloric acid and chlorine gas, combined, emissions limit for existing hazardous waste incinerators
FACILITY	40CFR 63- EEE.1203(a)(7)	309	particulate matter emissions limit for existing hazardous waste incinerators
FACILITY	40CFR 63- EEE.1203(c)(1)	310	Hazardous Waste Combustion NESHAP - Interim Emission Standards and Operating Limits - 99.99% DRE standard
FACILITY	40CFR 63- EEE.1203(c)(3)	311	Hazardous Waste Combustion NESHAP - Interim Emission Standards and Operating Limits - POHC's



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FACILITY	40CFR 63- EEE.1206(a)(1)	312	Hazardous Waste Combustion NESHAP - Compliance Date for existing haz. waste
FACILITY	40CFR 63-EEE.1206(b)	313	incinerators Compliance with standards
FACILITY	40CFR 63-EEE.1206(c)	315, 1 -32	Operating requirements
FACILITY	40CFR 63-EEE.1207	316	Performance Test Requirements
FACILITY	40CFR 63-EEE.1209	1 -33, 1 -34, 1 - 35, 1 -36, 1 -37, 1	Monitoring
FACILITY	40CFR 63- EEE.1209(a)(1)	-38, 1 -39, 1 -40 317	Hazardous Waste Combustion NESHAP - Monitoring Standards - CEMS and COMS - oxygen, hydrocarbon, and CO CEMS
FACILITY	40CFR 63- EEE.1209(a)(1)	318	requirement Hazardous Waste Combustion NESHAP - Monitoring Standards - CEMS and COMS - PM CEMS requirement
FACILITY	40CFR 63- EEE.1209(a)(2)	319	Hazardous Waste Combustor NESHAP - performance specifications
FACILITY	40CFR 63- EEE.1209(a)(3)	320	Hazardous Waste Combustion NESHAP - Monitoring Standards - CEMS and COMS - CO CEMS readings
FACILITY	40CFR 63- EEE.1209(a)(6)	321	exceeding the span Hazardous Waste Combustion NESHAP - Continuous Emission Monitoring - Initial calculation of rolling averages
FACILITY	40CFR 63- EEE.1209(a)(6)	322	Hazardous Waste Combustion NESHAP - Monitoring Standards - CEMS and COMS - calc. of rolling averages - intermittent
FACILITY	40CFR 63- EEE.1209(a)(6)	323	operation Hazardous Waste Combustion NESHAP - Monitoring Standards - CEMS & COMS - calc. of rolling avg haz. waste feed is cut off
FACILITY	40CFR 63- EEE.1209(a)(7)	324	Hazardous Waste Combustor NESHAP - Operating parameter limits for hydrocarbons
FACILITY	40CFR 63- EEE.1209(c)(1)	325	Hazardous Waste Combustor NESHAP -



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FACILITY	40CFR 63- EEE.1209(c)(2)	326	General feedstream anaylsis requirements Hazardous Waste Combustor NESHAP - Feedstream analysis plan
FACILITY	40CFR 63- EEE.1209(c)(4)	327	Hazardous Waste Combustor NESHAP - Compliance with feedrate limits
FACILITY	40CFR 63- EEE.1209(j)(1)	328, 329, 330	Hazardous Waste Combustor NESHAP - DRE monitoring
FACILITY	40CFR 63- EEE.1209(j)(3)	337, 338, 339, 340, 341, 342, 343, 1 -41	Hazardous Waste Combustor NESHAP - DRE monitoring requirements
FACILITY	40CFR 63- EEE.1209(j)(4)	345, 346, 347	Hazardous Waste Combustor NESHAP - DRE standards - operation of waste firing system
FACILITY	40CFR 63- EEE.1209(1)(1)	348, 349	Hazardous Waste Combustor NESHAP - Mercury monitoring - feedrate of total mercury limit
FACILITY	40CFR 63- EEE.1209(m)(1)	350, 351, 352, 354, 355, 356, 357, 358, 359, 360, 361, 362, 363, 364, 1 -42	Hazardous Waste Combustion NESHAP - Monitoring Standards - PM operating parameter limits for wet scrubbers
FACILITY	40CFR 63- EEE.1209(m)(1)	365	Hazardous Waste Combustion NESHAP - Monitoring Standards - PM operating parameter limits for wet scrubbers
FACILITY	40CFR 63- EEE.1209(m)(1)	366, 367	Hazardous Waste Combustion NESHAP - Monitoring Requirements - Particulate Matter - Wet scrubbers
FACILITY	40CFR 63- EEE.1209(m)(3)	368, 369, 370, 371	Hazardous Waste Combustion NESHAP - Monitoring Standards - PM maximum ash feedrate
FACILITY	40CFR 63- EEE.1209(n)(2)	372, 373	Hazardous Waste Combustion NESHAP - Monitoring Standards - semivolatile and low volatility metals - maximum feedrate of metal
FACILITY	40CFR 63- EEE.1209(n)(2)	1 -43	Hazardous Waste Combustor NESHAP - monitoring provisions for semivolatile and low-volatile metals
FACILITY	40CFR 63- EEE.1209(n)(4)	374, 375, 376, 377	Hazardous Waste Combustor NESHAP -



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			monitoring provisions for semivolatile and low volatile metal standards
FACILITY	40CFR 63- EEE.1209(o)(3)	378, 379	Hazardous Waste Combustor NESHAP - Hydrochloric acid and chlorine gas monitoring provisions
FACILITY	40CFR 63- EEE.1209(o)(3)	380	Hazardous Waste Combustor NESHAP - Hydrochloric acid and chlorine gas monitoring provisions
FACILITY	40CFR 63- EEE.1209(o)(3)	381, 382	Hazardous Waste Combustor NESHAP - Hydrochloric acid and chlorine gas monitoring provisions
FACILITY	40CFR 63- EEE.1209(o)(3)	383, 384, 386, 387, 1 -44	5 2
FACILITY	40CFR 63-EEE.1209(p)	388, 1 -45	Hazardous Waste Combustor NESHAP - Monitoring provisions - Maximum combustion chamber pressure
FACILITY	40CFR 63-EEE.1210(a)	390	Hazardous Waste Combustion NESHAP - Notification
FACILITY	40CFR 63-EEE.1210(b)	391	Requirements Hazardous Waste Combustion NESHAP - Notification Requirements - Notification of Intent to Comply
FACILITY	40CFR 63-EEE.1210(d)	392	Hazardous Waste Combustion NESHAP - Notification Requirements - Notification of Compliance
FACILITY	40CFR 63-EEE.1211(a)	393, 394, 395, 396	Hazardous Waste Combustion NESHAP - Recordkeeping and Reporting Requirements
FACILITY	40CFR 63-EEE.1211(b)	397, 398, 399	Hazardous Waste Combustor NESHAP - Recordkeeping
FACILITY	40CFR 63-EEE.1211(c)	400	requirements Hazardous Waste Combustion NESHAP - Recordkeeping and Reporting Requirements - Documentation of Compliance
FACILITY	40CFR 63-EEE.1219(a)	401, 402, 404, 405, 406, 407, 1 -30	Hazardous Waste Combustion NESHAP - Replacement Standards



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			existing sources
FACILITY	40CFR 63-	408	Hazardous Waste
	EEE.1219(c)(1)		Combustion NESHAP - Replacement Standards
			- 99.99% DRE standard
FACILITY	40CFR 63-	409	Hazardous Waste
	EEE.1219(c)(3)		Combustion NESHAP -
			Replacement Standards - POHC's (principal
			organic hazardous
			constituents)
FACILITY	40CFR 63-EEE.1219(e)	410	Hazardous Waste
			Combustion NESHAP - Replacement Standards
			- Alternative to the
			PM Standard
FACILITY	40CFR 63-F.102(a)(2)	144, 145	Subpart F - HON
			NESHAP - general standards
FACILITY	40CFR 63-F.104	148, 149	Subpart F - HON
		,	NESHAP - heat
			exchange system
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			exchange system
			requirements
FACILITY	40CFR 63-F.105	151, 152	Subpart F - HON NESHAP - maintenance
			wastewater
			requirements
FACILITY	40CFR 63-FFFF.2450(a)	411	Miscellaneous Organic
			Chemical Manufacturing NESHAP
			(MON) - General
			Requirements
FACILITY	40CFR 63-FFFF.2450(b)	412	Miscellaneous Organic Chemical
			Manufacturing NESHAP
			(MON) - Determination
			of halogenated vent
FACILITY	40CFR 63-FFFF.2450(f)	413 1 -46	streams Miscellaneous Organic
TACIBITI	40CIR 03 IIII.2430(I)	413, 1 40	Chemical
			Manufacturing NESHAP
			(MON) - Halogen
			Reduction Device Requirements
FACILITY	40CFR 63-FFFF.2450(h)	414	Miscellaneous Organic
			Chemical
			Manufacturing NESHAP (MON) - Design
			Evaluations
FACILITY	40CFR 63-FFFF.2450(i)	415	Miscellaneous Organic
			Chemical
			Manufacturing NESHAP (MON) - Outlet
			Concentration
			Correction for
FACILITY	400mp 63 mmm 04E0/4)	416	Combustion Devices Miscellaneous Organic
LUCIUIII	40CFR 63-FFFF.2450(j)	±±0	Chemical
			Manufacturing NESHAP



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FACILITY	40CFR 63-FFFF.2450(k)	417	(MON) - CEMS Miscellaneous Organic Chemical Manufacturing NESHAP
FACILITY	40CFR 63-FFFF.2450(1)	418	(MON) - Continuous Parameter Monitoring Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Startup,
FACILITY	40CFR 63-FFFF.2450(p)	419	Shutdown, and Malfunctions Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Opening of
FACILITY	40CFR 63-FFFF.2455(a)	1 -47, 1 -48, 1 - 49, 1 -50, 3 -83	Safety Devices Miscellaneous Organic Chemical Manufacturing NESHAP
FACILITY	40CFR 63-FFFF.2455(b)	422	(MON) - Continuous Process Vents - Emission limits Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Continuous
FACILITY	40CFR 63-FFFF.2460(a)	423, 424, 425, 426	Process Vents - Group 1 or TRE calculations Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Batch Process
FACILITY	40CFR 63-FFFF.2460(b)	427	Vents - Emission limits Miscellaneous Organic Chemical Manufacturing NESHAP
FACILITY	40CFR 63-FFFF.2460(c)	428	(MON) - Batch Process Vents - Group status Miscellaneous Organic Chemical Manufacturing NESHAP
FACILITY	40CFR 63- FFFF.2460(c)(7	429	(MON) - Batch Process Vents - Exceptions to Subpart SS Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Batch Process Vents - Intermittent flow to the control
FACILITY	40CFR 63-FFFF.2465(a)	1 -52, 1 -53, 1 - 54, 1 -55, 1 -56	device Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Process Vents
FACILITY	40CFR 63-FFFF.2480	438	Emitting Halogens or PM - emission limits Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Equipment leak provisions



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FACILITY	40CFR 63-FFFF.2485(c)	439	Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Wastewater Requirements - group 1 wastewater streams
FACILITY	40CFR 63-FFFF.2520(c)	440, 441, 442	Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Reporting Requirements - Precompliance report
FACILITY	40CFR 63-FFFF.2525	443	Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Recordkeeping Requirements
FACILITY	40CFR 63-FFFF.2535(g)	444	Miscellaneous Organic Chemical Manufacturing NESHAP (MON) - Compliance With Other Regulations For Wastewater
FACILITY	40CFR 63-G.113	153	Subpart G - HON NESHAP for Process Vents, Storage Vessels,etc-process vent provisions- reference control technology
FACILITY	40CFR 63-G.113(a)(2)	154	Group 1 Process Vents - emission reductions
FACILITY	40CFR 63-G.113(b)	155	Subpart G - HON NESHAP for Process Vents, Storage Vessels, etc-process vent provisions- reference control technology
FACILITY	40CFR 63-G.114	156	Subpart G - HON NESHAP for Process Vents, Storage Vessels, etc-process vent provisions- monitoring requirements
FACILITY	40CFR 63- G.114(a)(1)(i)	1 -20, 1 -21	Subpart G - HON NESHAP for Process Vents, Storage Vessels, etc-process vent provisions- monitoring requirements
FACILITY	40CFR 63-G.114(a)(3)	159	Subpart G - HON NESHAP for Process Vents, Storage Vessels,etc-process vent provisions- monitoring requirements
FACILITY	40CFR 63- G.114(a)(4)(i)	160, 161	Subpart G - HON NESHAP for Process Vents, Storage



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FACILITY	40CFR 63- G.114(a)(4)(ii	162, 164, 165, 166, 167, 168, 169, 1 -22	Vents, Storage Vessels,etc-process vent provisions-
FACILITY	40CFR 63-G.119(b)	170	monitoring requirements HON NESHAP - storage vessel provisions- reference control
FACILITY	40CFR 63-G.119(e)	171	technology HON NESHAP - storage vessel provisions- reference control
FACILITY	40CFR 63-G.123(a)	172	technology HON NESHAP - storage vessel provisions -
FACILITY	40CFR 63-G.132(a)(3)	173	recordkeeping HON - process wastewater provisions
FACILITY	40CFR 63-G.132(f)	174	- general HON - process wastewater provisions - general
FACILITY	40CFR 63-G.133(a)(1)	175, 176	HON - process wastewater provisions - wastewater tanks
FACILITY	40CFR 63-G.133(a)(2)	177	HON - process wastewater provisions - wastewater tanks
FACILITY	40CFR 63-G.133(f)	178	HON - process wastewater provisions - wastewater tanks
FACILITY	40CFR 63-G.135(b)	179, 180, 181	HON - process wastewater provisions - containers
FACILITY	40CFR 63-G.135(c)	182	HON - process wastewater provisions - containers
FACILITY	40CFR 63-G.135(e)	183	HON - process wastewater provisions - containers
FACILITY	40CFR 63-G.135(f)	184	HON - process wastewater provisions - containers
FACILITY	40CFR 63-G.136	185	HON - process wastewater provisions - individual drain
FACILITY	40CFR 63-G.138(a)	186	systems HON - process wastewater provisions - oil-water
FACILITY	40CFR 63-G.138(k)	187	separators Hazardous Organic NESHAP - Residuals from Group 1
FACILITY	40CFR 63-G.139(b)	188	Wastewater Streams HON - process wastewater provisions - control devices



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FACILITY	40CFR 63-G.139(c)	1 -23	HON - process wastewater provisions - control devices
FACILITY	40CFR 63-G.139(f)	190	HON - process wastewater provisions - control devices
FACILITY	40CFR 63-G.140	1 -24	HON - process wastewater provisions - inspection and monitoring of operations
FACILITY	40CFR 63-G.143(e)	1 -25	HON - process wastewater provisions - inspection and monitoring of operations
FACILITY	40CFR 63-G.143(g)	193, 1 -26	HON - process wastewater provisions - inspection and monitoring of operations
FACILITY	40CFR 63-G.145(h)	1 -27	HON - process wastewater provisions - test methods, procedures to determine compliance
FACILITY	40CFR 63-G.146(b)	194	HON - process wastewater provisions - reporting
FACILITY	40CFR 63-G.147	195	HON - process wastewater provisions - recordkeeping
FACILITY	40CFR 63-G.148	196	Leak inspection provisions
FACILITY	40CFR 63-G.148(b)(1)	197	Leak inspection provisions
FACILITY	40CFR 63-G.148(d)	198	Leak inspection provisions
FACILITY	40CFR 63-G.148(e)	199	Leak inspection provisions
FACILITY	40CFR 63-G.148(i)	200	Leak inspection provisions
FACILITY	40CFR 63-G.148(j)	201	Leak inspection provisions
FACILITY	40CFR 63-G.152(d)(1)	202	General reporting and continuous records
FACILITY	40CFR 63- GGGGG.7881(c)	445	Site Remediation NESHAP - Sources Subject Only To Limited Recordkeeping
FACILITY	40CFR 63-H.160	203	Subpart H - HON NESHAP for Equipment Leaks
FACILITY	40CFR 63-H.162(c)	204	Subpart H - HON NESHAP for Equipment Leaks - standards:general
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FACILITY	40CFR 63-H.162(f)	205, 206	standards:general Subpart H - HON NESHAP for Equipment Leaks -



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FACILITY	40CFR 63-H.163(a)	207	standards:general Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.163(b)(1)	208	standards:pumps in light liquid service Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.163(b)(2)	209	standards:pumps in light liquid service Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.163(b)(3)	210	standards:pumps in light liquid service Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.163(d)(1)	211	standards:pumps in light liquid service Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.164(i)	212	standards:pumps in light liquid service Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.165(d)(2)	213	standards:compressors Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.166	214	standards:pressure relief devices in gas/vapor service Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.167(a)(1)	215	standards:sampling connection systems Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.167(b)	216	standards:open-ended valves or lines Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.167(c)	217	standards:open-ended valves or lines Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.167(d)	218	standards:open-ended valves or lines Subpart H - HON NESHAP for Equipment Leaks -
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FACILITY	40CFR 63-H.168(f)(1)	220	gas/ vapor and in light liquid service Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.168(h)	221	standards:valves in gas/ vapor and in light liquid service Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.168(i)	222	standards:valves in gas/ vapor and in light liquid service Subpart H - HON NESHAP for Equipment Leaks - standards:valves in
FACILITY	40CFR 63-H.171(a)	223	gas/ vapor and in light liquid service Subpart H - HON NESHAP for Equipment Leaks - standards:delay of
FACILITY	40CFR 63-H.171(b)	224	repair Subpart H - HON NESHAP for Equipment
FACILITY	40CFR 63-H.171(c)	225	Leaks - standards:delay of repair Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.171(d)	226	standards:delay of repair Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.171(e)	227	standards:delay of repair Subpart H - HON NESHAP for Equipment Leaks -
FACILITY	40CFR 63-H.174(a)	228	standards:delay of repair Subpart H - HON NESHAP for Equipment Leaks - standards:connectors
FACILITY	40CFR 63- H.174(c)(1)(i)	229	in gas/vapor service and in light liquid service Subpart H - HON NESHAP for Equipment Leaks - standards:connectors
FACILITY	40CFR 63-H.174(c)(2)	230	in gas/vapor service and in light liquid service Subpart H - HON NESHAP for Equipment Leaks - standards:connectors



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			·
			<pre>in gas/vapor service and in light liquid</pre>
			service
FACILITY	40CFR 63-H.174(f)	231	Subpart H - HON
			NESHAP for Equipment Leaks -
			standards:connectors
			in gas/vapor service
			and in light liquid service
FACILITY	40CFR 63-H.174(g)	232	Subpart H - HON
			NESHAP for Equipment
			Leaks -
			standards:connectors in gas/vapor service
			and in light liquid
			service
FACILITY	40CFR 63-H.174(h)(1)	233	Subpart H - HON NESHAP for Equipment
			Leaks -
			standards:connectors
			in gas/vapor service
			and in light liquid service
FACILITY	40CFR 63-H.175	234	Subpart H - HON
			NESHAP for Equipment Leaks - quality
			improvement program
			for valves
FACILITY	40CFR 63-H.181(a)	235	Subpart H - HON
			NESHAP for Equipment Leaks - recordkeeping
			requirements
FACILITY	40CFR 63-H.181(b)	236	Subpart H - HON
			NESHAP for Equipment Leaks - recordkeeping
			requirements
FACILITY	40CFR 63-H.181(c)	237	Subpart H - HON
			NESHAP for Equipment Leaks - recordkeeping
			requirements
FACILITY	40CFR 63-H.181(d)	238	Subpart H - HON
			NESHAP for Equipment Leaks - recordkeeping
			requirements
FACILITY	40CFR 63-H.181(f)	239	Subpart H - HON
			NESHAP for Equipment Leaks - recordkeeping
			requirements
FACILITY	40CFR 63-H.181(h)	240	Subpart H - HON
			NESHAP for Equipment Leaks - recordkeeping
			requirements
FACILITY	40CFR 63-H.182(d)	241	Subpart H - HON
			NESHAP for Equipment Leaks - reporting
			requirements
FACILITY	40CFR 63-	446, 447	Hydrochloric Acid
	NNNNN.9000(a)		Production NESHAP - Emission Limits
FACILITY	40CFR 63-	448, 449	Hydrochloric Acid
	NNNNN.9000(b)		Production NESHAP -
FACILITY	40CFR 63-	450	Operating Limits Hydrochloric Acid
	100111 00	200	marconionic Acid



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	NNNNN.9005(a)		Production NESHAP - General Requirements
FACILITY	40CFR 63- NNNNN.9005(b)	451	Hydrochloric Acid Production NESHAP - General Requirements
FACILITY	40CFR 63- NNNNN.9005(c)	452	Hydrochloric Acid Production NESHAP - General Requirements -
FACILITY	40CFR 63- NNNNN.9005(d)	453	Startup/shutdown/malf unction plan Hydrochloric Acid Production NESHAP - General Requirements - monitoring system requirements
FACILITY	40CFR 63- NNNNN.9020(b)	454	Hydrochloric Acid Production NESHAP - Performance Tests - Percent reduction
FACILITY	40CFR 63- NNNNN.9020(e)	455	requirements Hydrochloric Acid Production NESHAP - Performance Test Procedures - Establishing of
FACILITY	40CFR 63- NNNNN.9025(a)	456	operating parameters Hydrochloric Acid Production NESHAP - Monitoring system requirements - Continuous monitoring
FACILITY	40CFR 63- NNNNN.9025(b)	457	system operation Hydrochloric Acid Production NESHAP - Monitoring System Requirements - scrubber monitoring
FACILITY	40CFR 63- NNNNN.9030(a)	458, 459	requirements Hydrochloric Acid Production NESHAP - Initial Compliance - Emission limits
FACILITY	40CFR 63- NNNNN.9030(b)	460	Hydrochloric Acid Production NESHAP - Initial Compliance - Operating limits
FACILITY	40CFR 63- NNNNN.9035(b)	461	Hydrochloric Acid Production NESHAP - Continuous Compliance Monitoring - caustic scrubbers or water scrubbers/adsorbers
FACILITY	40CFR 63- NNNNN.9035(d)	462	Hydrochloric Acid Production NESHAP - Continuous Compliance Monitoring - requirement to continuously monitor
FACILITY	40CFR 63- NNNNN.9035(e)	463	during operation Hydrochloric Acid Production NESHAP - Continuous Compliance Monitoring -



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			Collection of data
			for monitoring
FACILITY	40CFR 63-	464	Hydrochloric Acid
	NNNNN.9040(c)		Production NESHAP -
			Continuous Compliance
			- deviations
FACILITY	40CFR 63-	465	Hydrochloric Acid
	NNNNN.9045(f)		Production NESHAP -
			Notification of
			Compliance Status -
			Deadline for
			submittal
FACILITY	40CFR 63-	466	Hydrochloric Acid
	NNNNN.9045(g)		Production NESHAP -
			Notification of
			Compliance Status -
			additional
			information to be
			submitted
FACILITY	40CFR 63-	467	Hydrochloric Acid
	NNNNN.9050(a)		Production NESHAP -
			Reporting
D3 GTT TEN/	40 GED 62	4.60	Requirements
FACILITY	40CFR 63-	468	Hydrochloric Acid Production NESHAP -
	NNNNN.9050(b)		
			Reporting Requirements -
			Schedule to submit
			semiannual reports
FACILITY	40CFR 63-	469	Hydrochloric Acid
TACIBLL	NNNNN.9050(c)	400	Production NESHAP -
	111111111111111111111111111111111111111		Reporting
			Requirements -
			Information to submit
			in compliance report
FACILITY	40CFR 63-	470	Hydrochloric Acid
	NNNNN.9050(d)		Production NESHAP -
			Reporting
			Requirements -
			Information to submit
			for deviations in
			compliance report
FACILITY	40CFR 63-	471	Hydrochloric Acid
	NNNNN.9050(e)		Production NESHAP -
			Reporting
			Requirements -
			Semiannual Title V
	40000 60	450	report for deviations
FACILITY	40CFR 63-	472	Hydrochloric Acid
	NNNNN.9050(f)		Production NESHAP -
			Reporting Requirements -
			Startup, shutdown,
			malfunction reporting
FACILITY	40CFR 63-NNNNN.9055	473	Hydrochloric Acid
TACIBITI	40CI (C 03 IVIVIVIVI . 5033	473	Production NESHAP -
			Recordkeeping
			Requirements
FACILITY	40CFR 63-NNNNN.9060	474	Hydrochloric Acid
-			Production NESHAP -
			Recordkeeping
			Requirements
FACILITY	40CFR 63-SS.983(a)	3 -28	GMACT - Standards for
			closed vent systems -



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FACILITY	40CFR 63-SS.983(b)	3 -29	closed vent system equipment and operating requirements GMACT - Standards for
			closed vent systems - closed vent system inspection requirements
FACILITY	40CFR 63-SS.983(c)	3 -30	GMACT - Requirements for closed vent systems - closed vent system inspection procedures
FACILITY	40CFR 63-SS.983(d)	3 -31	GMACT - Requirements for closed vent systems - closed vent system leak repair
FACILITY	40CFR 63-SS.988(a)	3 -32	provisions NESHAP For Closed Vent Systems, Control Devices, etc Incinerators, boilers, and process heaters equipment and
FACILITY	40CFR 63-SS.988(b)	3 -33, 3 -34	operating NESHAP For Closed Vent Systems, Control Devices, etc Incinerators, boilers, and process heaters - performance
FACILITY	40CFR 63-SS.990(a)	3 -35	tests NESHAP For Closed Vent Systems, Control Devices, etc Absorbers & Condensers as Control Devices - equipment
FACILITY	40CFR 63-SS.990(b)	3 -36	and operation NESHAP For Closed Vent Systems, Control Devices, etc Absorbers & Condensers as Control Devices - performance
FACILITY	40CFR 63-SS.994(a)(2)	252	testing NESHAP for Closed Vent Systems & Control Devices - Halogen Scrubbers & Other Reduction Devices - equipment
FACILITY	40CFR 63-SS.994(b)	253, 254	and operating NESHAP for Closed Vent Systems & Control Devices - Halogen Scrubbers & Other Reduction Devices - performance
FACILITY	40CFR 63-SS.996	3 -37	testing GMACT - General monitoring requirements for



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FACILITY	40CFR 63-SS.996(d)	3 -38	control and recovery devices NESHAP for Closed Vent Systems & Control Devices - Alternatives to Montroling
FACILITY	40CFR 63-SS.998(a)(2)	3 -39, 3 -40	Requirements Recordkeeping Requirements
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FACILITY	40CFR 63-UU.1019	3 -46	NESHAP for Equipment Leaks
FACILITY	40CFR 63-UU.1022	3 -47	Equipment Identification
FACILITY	40CFR 63-UU.1023(a)	3 -48	NESHAP for Equipment Leaks - Control Level 2 - Instrument and Sensory Monitoring for Leaks
FACILITY	40CFR 63-UU.1023(b)	3 -49	NESHAP for Equipment Leaks - Control Level 2 - Instrument and Sensory Monitoring for Leaks - Instrument monitoring methods
FACILITY	40CFR 63-UU.1023(c)	3 -50	NESHAP for Equipment Leaks - Control Level 2 - Instrument and Sensory Monitoring for Leaks - Use of background adjustments
FACILITY	40CFR 63-UU.1023(e)	3 -51	NESHAP for Equipment Leaks - Control Level 2 - Instrument and Sensory Monitoring for Leaks - Leak identification and records



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FACILITY	40CFR 63-UU.1024(a)	3	-52	NESHAP for Equipment Leaks - Control Level 2 - Leak Repair -
FACILITY	40CFR 63-UU.1024(c)	3	-53	Leak repair schedule NESHAP for Equipment Leaks - Control Level 2 - Leak Repair - Leak identification removal
FACILITY	40CFR 63-UU.1024(d)	3	-54	NESHAP for Equipment Leaks - Control Level 2 - Leak Repair - Delay of repair
FACILITY	40CFR 63-UU.1024(e)	3	-55	NESHAP for Equipment Leaks - Control Level 2 - Leak Repair - Unsafe to repair connectors
FACILITY	40CFR 63-UU.1024(f)	3	-56	NESHAP for Equipment Leaks - Control Level 2 - Leak Repair - Records
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FACILITY	40CFR 63-UU.1025(c)	3	-58	NESHAP for Equipment Leaks - Control Level 2 - Valves in Gas, Vapor, and Light Liquid Service - Percent leaking valves
FACILITY	40CFR 63-UU.1025(d)	3	-59	NESHAP for Equipment Leaks - Control Level 2 - Valves in Gas, Vapor, and Light Liquid Service - Leak repair
FACILITY	40CFR 63- UU.1025(e)(1)	3	-60	NESHAP for Equipment Leaks - Control Level 2 - Valves in Gas, Vapor, and Light Liquid Service - Unsafe to monitor
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FACILITY	40CFR 63- UU.1025(e)(3)	3	-62	NESHAP for Equipment Leaks - Control Level 2 - Valves in Gas, Vapor, and Light Liquid Service - Fewer than 250 valves
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FACILITY	40CFR 63-UU.1026(e)	3 -66	Visual inspections NESHAP for Equipment Leaks - Control Level 2 - Pumps in Light Liquid Service - Special provisions for pumps
FACILITY	40CFR 63-UU.1027(b)	3 -67	NESHAP for Equipment Leaks - Control Level 2 - Connectors in gas, vapor, and light liquid service - Leak Detection
FACILITY	40CFR 63- UU.1027(e)(1)	3 -68	NESHAP for Equipment Leaks - Control Level 2 - Connectors in gas, vapor, and light liquid service - Unsafe to monitor
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FACILITY	40CFR 63-UU.1030	3 -73	GMACT - NESHAP for Equipment Leaks - Control Level 2 - Standards for pressure relief devices in gas/vapor service
FACILITY	40CFR 63-UU.1031(f)	3 -74	NESHAP for Equipment Leaks - Control Level 2 - Compressors - Alternative standards
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FACILITY	40CFR 63-00.1036	3 - 78	emission limitation:
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			General equipment leak records
FACILITY	40CFR 63-UU.1038(c)	3 -80	NESHAP for Equipment
FACILITI	40CFR 63-00.1036(C)	3 -80	Leaks - Control Level
			2 - Recordkeeping -
			Specific equipment
			leak records
FACILITY	40CFR 63-UU.1039(a)	3 -81	Reporting
			Requirements
FACILITY	40CFR 63-UU.1039(b)	3 -82	Reporting
			Requirements
FACILITY	40CFR 63-	475	Reciprocating
	ZZZZ.6590(b)(3		Internal Combustion
			Engine NESHAP -
			Stationary RICE
			Subject to Limited
			Requirements
FACILITY	40CFR 68	20	Chemical accident
			prevention provisions
FACILITY	40CFR 82-F	21	Protection of
			Stratospheric Ozone -
			recycling and
			emissions reduction
FACILITY	6NYCRR 200.6	1	Acceptable ambient
			air quality.
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			equipment.
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			noncompliance and
			violations
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			reintroduction of collected
			contaminants to the
			air
FACILITY	6NYCRR 201-3.2(a)	12	Exempt Activities -
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			Conditions
FACILITY	6NYCRR 201-6.5(a)(4)	14	General conditions
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			Fees
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FACILITY	6NYCRR 201-6.5(c)	3	Permit conditions for
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			Compliance Menitoring
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FACILITY	6NYCRR 202-2.1	6	Emission Statements - Applicability
FACILITY	6NYCRR 202-2.5	7	Emission Statements - record keeping
FACILITY	6NYCRR 211.1	3 -4	requirements. General Prohibitions - air pollution prohibited
FACILITY	6NYCRR 211.2	481, 3 -85	General Prohibitions - visible emissions
FACILITY	6NYCRR 211.3	19	limited. General Prohibitions - visible emissions limited
FACILITY	6NYCRR 212	46	General Process Emission Sources
FACILITY	6NYCRR 212.10(a)(2)	55, 56	NOx and VOC RACT required at major facilities
FACILITY	6NYCRR 212.10(c)(4)(i)	3 -8, 3 -9, 3 -10, 3 -11, 3 -12, 3 - 13, 3 -14, 3 -15, 3 -16, 3 -17, 3 -18, 3 -19, 3 -20, 3 -	NOx and VOC RACT required at major
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FACILITY	6NYCRR 227-1.2(a)(1)	84	Particulate Emissions from Liquid Fuels.
FACILITY	6NYCRR 227-1.3	85	Smoke Emission Limitations.
FACILITY	6NYCRR 227-1.3(a)	3 -26	Smoke Emission
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- CAIR NOx Ozone

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FACILITY 6NYCRR 243-8.5(e) 2 -8 Compliance certification re: recordkeeping and reporting - Monitoring and Reporting Monitoring and Reporting - Monitoring and reporting - Monitoring and	FACILITY	6NYCRR 243-8.3	2 -6	periods - Monitoring
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	FACILITY	6NYCRR 243-8.5(e)	2 -8	certification re: recordkeeping and reporting - Monitoring and

Applicability Discussion:

Mandatory Requirements: The following facility-wide regulations are included in all Title V permits:

ECL 19-0301

This section of the Environmental Conservation Law establishes the powers and duties assigned to the Department with regard to administering the air pollution control program for New York State.

6 NYCRR 200.6

Acceptable ambient air quality - prohibits contravention of ambient air quality standards without mitigating measures

6 NYCRR 200.7

Anyone owning or operating an air contamination source which is equipped with an emission control device must operate the control consistent with ordinary and necessary practices, standards and procedures, as per manufacturer's specifications and keep it in a satisfactory state of maintenance and repair so that it operates effectively

6 NYCRR 201-1.4

This regulation specifies the actions and recordkeeping and reporting requirements for any violation of an applicable state enforceable emission standard that results from a necessary scheduled equipment maintenance, start-up, shutdown, malfunction or upset in the event that these are unavoidable.

6 NYCRR 201-1.7

Requires the recycle and salvage of collected air contaminants where practical

6 NYCRR 201-1.8

Prohibits the reintroduction of collected air contaminants to the outside air



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6 NYCRR 201-3.2 (a)

An owner and/or operator of an exempt emission source or unit may be required to certify that it operates within the specific criteria described in this Subpart. All required records must be maintained on-site for a period of 5 years and made available to department representatives upon request. In addition, department representatives must be granted access to any facility which contains exempt emission sources or units, during normal operating hours, for the purpose of determining compliance with this and any other state and federal air pollution control requirements, regulations, or law.

6 NYCRR 201-3.3 (a)

The owner and/or operator of a trivial emission source or unit may be required to certify that it operates within the specific criteria described in this Subpart. All required records must be maintained on-site for a period of 5 years and made available to department representatives upon request. In addition, department representatives must be granted access to any facility which contains trivial emission sources or units subject to this Subpart, during normal operating hours, for the purpose of determining compliance with this and any other state and federal air pollution control requirements, regulations, or law.

6 NYCRR Subpart 201-6

This regulation applies to those terms and conditions which are subject to Title V permitting. It establishes the applicability criteria for Title V permits, the information to be included in all Title V permit applications as well as the permit content and terms of permit issuance. This rule also specifies the compliance, monitoring, recordkeeping, reporting, fee, and procedural requirements that need to be met to obtain a Title V permit, modify the permit and demonstrate conformity with applicable requirements as listed in the Title V permit. For permitting purposes, this rule specifies the need to identify and describe all emission units, processes and products in the permit application as well as providing the Department the authority to include this and any other information that it deems necessary to determine the compliance status of the facility.

6 NYCRR 201-6.5 (a) (4)

This mandatory requirement applies to all Title V facilities. It requires the permittee to provide information that the Department may request in writing, within a reasonable time, in order to determine whether cause exists for modifying, revoking and reissuing, or terminating the permit or to determine compliance with the permit. The request may include copies of records required to be kept by the permit.

6 NYCRR 201-6.5 (a) (7)

This is a mandatory condition that requires the owner or operator of a facility subject to Title V requirements to pay all applicable fees associated with the emissions from their facility.

6 NYCRR 201-6.5 (a) (8)

This is a mandatory condition for all facilities subject to Title V requirements. It allows the Department to inspect the facility to determine compliance with this permit, including copying records, sampling and monitoring, as necessary.

6 NYCRR 201-6.5 (c)

This requirement specifies, in general terms, what information must be contained in any required compliance monitoring records and reports. This includes the date, time and place of any sampling, measurements and analyses; who performed the analyses; analytical techniques and methods used as well as any required QA/QC procedures; results of the analyses; the operating conditions at the time of sampling or measurement and the identification of any permit deviations. All such reports must also be certified by the designated responsible official of the facility.



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6 NYCRR 201-6.5 (c) (2)

This requirement specifies that all compliance monitoring and recordkeeping is to be conducted according to the terms and conditions of the permit and follow all QA requirements found in applicable regulations. It also requires monitoring records and supporting information to be retained for at least 5 years from the time of sampling, measurement, report or application. Support information is defined as including all calibration and maintenance records and all original strip-chart recordings for continuous monitoring instrumentation, and copies of all reports required by the permit.

6 NYCRR 201-6.5 (c) (3) (ii)

This regulation specifies any reporting requirements incorporated into the permit must include provisions regarding the notification and reporting of permit deviations and incidences of noncompliance stating the probable cause of such deviations, and any corrective actions or preventive measures taken.

6 NYCRR 201-6.5 (d) (5)

This condition applies to every Title V facility subject to a compliance schedule. It requires that reports, detailing the status of progress on achieving compliance with emission standards, be submitted semiannually.

6 NYCRR 201-6.5 (e)

Sets forth the general requirements for compliance certification content; specifies an annual submittal frequency; and identifies the EPA and appropriate regional office address where the reports are to be sent.

6 NYCRR 201-6.5 (f) (6)

This condition allows changes to be made at the facility, without modifying the permit, provided the changes do not cause an emission limit contained in this permit to be exceeded. The owner or operator of the facility must notify the Department of the change. It is applicable to all Title V permits which may be subject to an off permit change.

6 NYCRR 202-1.1

This regulation allows the department the discretion to require an emission test for the purpose of determining compliance. Furthermore, the cost of the test, including the preparation of the report are to be borne by the owner/operator of the source.

6 NYCRR 202-2.1

Requires that emission statements shall be submitted on or before April 15th each year for emissions of the previous calENDar year.

6 NYCRR 202-2.5

This rule specifies that each facility required to submit an emission statement must retain a copy of the statement and supporting documentation for at least 5 years and must make the information available to department representatives.

6 NYCRR 211.2

This regulation limits opacity from sources to less than or equal to 20 percent (six minute average) except for one continuous six-minute period per hour of not more than 57 percent opacity.

6 NYCRR 211.3

This condition requires that the opacity (i.e., the degree to which emissions other than water reduce the transmission of light) of the emissions from any air contamination source be less than 20 percent (six minute average) except for one continuous six-minute period per hour of not more than 57 percent.



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6 NYCRR Part 215

Except as allowed by section 215.3 of 6 NYCRR Part 215, no person shall burn, cause, suffer, allow or permit the burning of any materials in an open fire.

6 NYCRR 215.2

Except as allowed by section 215.3 of 6 NYCRR Part 215, no person shall burn, cause, suffer, allow or permit the burning of any materials in an open fire.

40 CFR Part 68

This Part lists the regulated substances and there applicability thresholds and sets the requirements for stationary sources concerning the prevention of accidental releases of these substances.

40 CFR Part 82, Subpart F

Subpart F requires the reduction of emissions of class I and class II refrigerants to the lowest achievable level during the service, maintenance, repair, and disposal of appliances in accordance with section 608 of the Clean Air Act AmENDments of 1990. This subpart applies to any person servicing, maintaining, or repairing appliances except for motor vehicle air conditioners. It also applies to persons disposing of appliances, including motor vehicle air conditioners, refrigerant reclaimers, appliance owners, and manufacturers of appliances and recycling and recovery equipment. Those individuals, operations, or activities affected by this rule, may be required to comply with specified disposal, recycling, or recovery practices, leak repair practices, recordkeeping and/or technician certification requirements.

Facility Specific Requirements

In addition to Title V, MOMENTIVE PERFORMANCE MATERIALS has been determined to be subject to the following regulations:

40 CFR 52.21

This citation applies to facilities that are subject to Prevention of Significant Deterioration provisions;

ie: facilities that are located in an attainment area and that emit pollutants which are listed in $40\ CFR\ 52.21(b)(23)(i)$.

40 CFR 60.11

This regulation specifies the type of opacity monitoring requirements in relation to compliance with the standards and maintenance requirements.

40 CFR 60.11 (d)

This regulation specifies the type of opacity monitoring requirements in relation to compliance with the standards and maintenance requirements.

40 CFR 60.112b (a) (3)

This regulation requires owner or operators of storage vessels with the dimensions listed below, to install a closed vent system and control device to collect all volatile organic compounds that are discharged from the vessel. This requirement applies to storage vessels with the following dimensions: design capacity > 151 m3 containing a VOL that, as stored, has a maximum true vapor pressure > 5.2 kPa but < 76.6 kPa or with a design capacity > 75 m3 but < 151 m3 containing a VOL that, as stored, has a maximum true vapor pressure > 27.6 kPa but less than 76.7 kPa. The emissions from the storage vessel must be monitored and be less than 500 parts per million.

40 CFR 60.113b (c)



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This regulation allows the owner or operator of the storage vessel equipped with a closed vent system and control device to be exempt from the requirements of 40 CFR 60.8 (General Provisions). The source owner or operator must provide documentation that the control device will achieve the required control efficiency during maximum loading conditions.

40 CFR 60.115b (c)

This regulation requires the owner or operator to keep records of the operating plan and record the measured values of the parameters monitored for the closed vent system.

40 CFR 60.116b (b)

Owners or operators of affected storage tanks with capacities greater than or equal to 10,000 gallons must keep records of the tanks dimensions and an analysis of its capacity for the life of the tank. If the tank's capacity is less than 20,000 gallons, then it is subject to no other provisions of this subpart.

40 CFR 60.12

This regulation prohibits an owner or operator from concealing emissions in violation of applicable standards by any means.

40 CFR 60.13 (a)

This regulation specifies that all New Source Performance Standard (NSPS) affected sources that are required to have continuous monitoring systems (CMS) are subject to the requirements of Appendix B of 40 CFR Part 60 and if the CMS is used to demonstrate compliance with emission limits on a continuous basis, then it is also subject to Appendix F of 40 CFR Part 60.

40 CFR 60.13 (d)

This regulation contains the requirements for daily drift testing for continuous monitoring systems required by 40 CFR Part 60.

40 CFR 60.13 (e)

This regulation specifies minimum frequency of operation requirements for continuous monitoring systems required by 40 CFR Part 60.

40 CFR 60.13 (h)

This regulation specifies the data averaging requirements for continuous monitoring systems subject to 40 CFR Part 60.

40 CFR 60.4

This condition lists the USEPA Region 2 address for the submittal of all communications to the "Administrator". In addition, all such communications must be copied to NYSDEC Bureau of Quality Assurance (BQA).

40 CFR 60.43b (f)

This regulation specifies maximum allowable opacity for affected affected sources. The opacity of the emission may not exceed 20%, except for one six minute period when the maximum opacity may not exceed 27%.

40 CFR 60.43b (g)

This regulation specifies that the particulate matter and opacity standards apply at all times, except during periods of startup, shutdown or malfunction.



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40 CFR 60.44b (a) (1)

These standards apply to all boilers firing natural gas and/or distillate oil except as provided in 40 CFR 60.44b(a)(4) Duct Burners Used in a Comdined Cycle System.

40 CFR 60.44b (h)

This regulation specifies that the NSPS nitrogen oxide standards apply at all time including periods of startup, shutdown, or malfunction.

40 CFR 60.45b (j)

This regulation specifies that owner or operators that combust very low sulfur oil are not subject to compliance and performance testing requirements for Sulfur Dioxide if they obtain fuel receipts as described in 40 CFR 60.49b(r)

40 CFR 60.48b (c)

This regulation requires that the continuous monitoring system (CMS) and data recorder for nitrogen oxides be operated during all periods of operation of the affected facility except for CMS breakdowns and repairs. Data must be recorded during calibration checks, and zero and span adjustments.

40 CFR 60.48b (f)

This regulation requires that standby methods of obtaining minimum emissions data for oxides of nitrogen be specified by the source owner or operator.

40 CFR 60.49b (f)

This subdivision specifies that monitored opacity records must be kept at the facility.

40 CFR 60.49b (g)

This subdivision requires reporting and recordkeeping for affected steam generating units - specific oxides of nitrogen requirements.

40 CFR 60.49b (r)

This regulation specifies that owner or operators that combust very low sulfur oil are required to obtain fuel receipts. The oil need not meet the fuel nitrogen content specification in the definition of distillate oil. Reports shall be submitted to the Administrator certifying that only very low sulfur oil meeting this definition was combusted

40 CFR 60.662 (a)

Conditions under 40CFR60.662(a) require total organic compound emissions (not counting methane or ethane) from distillation operations at synthetic organic chemical manufacturing facilities to be reduced by 98% or to a concentration of 20 parts per million whichever is less stringent. This is part of the Federal New Source Performance Standards and applies only to facilities constructed, reconstructed or modified since December 30, 1983.

40 CFR 60.663 (a)

Conditions under 40CFR60.663(a) dictate the parameter(s) to be monitored for distillation operations using incinerators to control their total organic compound emissions. This provides an assurance of continuous compliance with the emission standard.

40 CFR 60.665

Conditions under 40CFR60.665 describe the reporting and recordkeeping requirements for facilities



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subject to the Distillation Operations New Source Performance Standards, as well as those that are exempt due to having a total resource effectiveness index value greater than 8.

40 CFR 60.7 (a)

This regulation requires any owner or operator subject to a New Source Performance Standard (NSPS) to furnish the Administrator with notification of the dates of: construction or reconstruction, initial startup, any physical or operational changes, commencement of performance testing for continuous monitors and anticipated date for opacity observations as required.

40 CFR 60.7 (b)

This regulation requires the owner or operator to maintain records of the occurrence and duration of any startup, shutdown, or malfunction of the source or control equipment or continuous monitoring system.

40 CFR 60.7 (c)

This requirement details the information to be submitted in excess emissions and monitoring systems performance reports which must be submitted at least semi-annually for sources with compliance monitoring systems.

40 CFR 60.7 (d)

This condition specifies the required information and format for a summary report form and details when either a summary form and/or excess emissions reports are required.

40 CFR 60.7 (f)

This condition specifies requirements for maintenance of files of all measurements, including continuous monitoring system (CMS), monitoring device, and performance testing measurements; all CMS performance evaluations; all CMS or monitoring device calibration checks; adjustments and maintenance performed on these systems or devices for at least two years.

40 CFR 60.702 (a)

Conditions under 40CFR60.702(a) require total organic compound emissions (not counting methane or ethane) from reactor processes at synthetic organic chemical manufacturing facilities to be reduced by 98% or to a concentration of 20 parts per million whichever is less stringent. This is part of the Federal New Source Performance Standards and applies only to facilities constructed, reconstructed or modified since June 29, 1990. Applicability under this section also triggers monitoring under §703, testing under §704, and reporting and recordkeeping under §705.

40 CFR 61.145

This regulation, 40 CFR 61 Subpart M, lists the general provisions that a facility subject to a National Emissions Standard for Hazardous Air Pollutant for Asbestos demolition and renovation is subject to.

40 CFR 63.1019

This regulation, 40 CFR 63 Subpart UU, details applicability requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.102 (a) (2)

This condition specifies that the requirements of the HON rule do not apply during periods of startup, shutdown, or malfunction. The rule also does not apply when the process unit's lines are drained and depressurized.



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40 CFR 63.1022

Conditions under this section relate to the identification of equipment subject to Subpart UU. Physical tagging of the equipment (pupms, valves, connectors, etc.) is not required, but is allowed as one method of identification. Other allowable methods are by a site plan, log entries, designation of process boundaries, etc. Equipment identification is needed so equipment subject to leak detection monitoring can be differentiated from equipment not needing monitoring.

40 CFR 63.1023 (a)

This regulation, 40 CFR 63 Subpart UU, details instrument and sensory monitoring requirements for leaks for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1023 (b)

This regulation, 40 CFR 63 Subpart UU, details instrument and sensory monitoring requirements for leaks for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1023 (c)

This regulation, 40 CFR 63 Subpart UU, details instrument and sensory monitoring requirements for leaks for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1023 (e)

This regulation, 40 CFR 63 Subpart UU, details instrument and sensory monitoring requirements for leaks for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1024 (a)

This regulation, 40 CFR 63 Subpart UU, details leak repair requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1024 (c)

This regulation, 40 CFR 63 Subpart UU, details leak repair requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1024 (d)

This regulation, 40 CFR 63 Subpart UU, details leak repair requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1024 (e)

This regulation, 40 CFR 63 Subpart UU, details leak repair requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1024 (f)

This regulation, 40 CFR 63 Subpart UU, details leak repair requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1025 (b)

This regulation, 40 CFR 63 Subpart UU, details standards for valves in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1025 (c)

This regulation, 40 CFR 63 Subpart UU, details standards for valves in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control



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Level 2.

40 CFR 63.1025 (d)

This regulation, 40 CFR 63 Subpart UU, details standards for valves in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1025 (e) (1)

This regulation, 40 CFR 63 Subpart UU, details standards for valves in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1025 (e) (2)

This regulation, 40 CFR 63 Subpart UU, details standards for valves in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1025 (e) (3)

This regulation, 40 CFR 63 Subpart UU, details standards for valves in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1026

This regulation, 40 CFR 63 Subpart UU, details standards for pumps in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1026 (b) (4)

This regulation, 40 CFR 63 Subpart UU, details standards for pumps in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1026 (e)

This regulation, 40 CFR 63 Subpart UU, details standards for pumps in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1027 (b)

This regulation, 40 CFR 63 Subpart UU, details standards for connectors in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1027 (e) (1)

This regulation, 40 CFR 63 Subpart UU, details standards for connectors in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1027 (e) (2)

This regulation, 40 CFR 63 Subpart UU, details standards for connectors in gas and vapor service and in light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1028

This regulation, 40 CFR 63 Subpart UU, details standards for agitators in gas and vapor service and in



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light liquid service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1029

This regulation, 40 CFR 63 Subpart UU, details standards for pumps, valves, connectors, and agitators in heavy liquid service; pressure relief devices in liquid service; and instrumentation systems for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1030

This regulation, 40 CFR 63 Subpart UU, details standards for pressure relief devices in gas and vapor service for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1031 (f)

This regulation, 40 CFR 63 Subpart UU, details standards for compressors for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1032

This regulation, 40 CFR 63 Subpart UU, details standards for sampling connection systems for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1033

This regulation, 40 CFR 63 Subpart UU, details standards for open-ended valves or lines for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1035

When a large percentage of the pumps within the facility and subject to this rule leak, a quality improvement program (QIP) to reduce the number of leaking pumps is triggered. Conditions under this section describe the requirements QIP including it's recordkeeping and reporting requirements.

40 CFR 63.1036

Conditions under this section provide alternatives to the leak detection and repair standards of sections 63.1025 through 63.1033. They also describe the means of tracking changes of operation between the alternatives.

40 CFR 63.1038 (b)

This regulation, 40 CFR 63 Subpart UU, details record keeping requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1038 (c)

This regulation, 40 CFR 63 Subpart UU, details record keeping requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1039 (a)

This regulation, 40 CFR 63 Subpart UU, details reporting requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.1039 (b)

This regulation, 40 CFR 63 Subpart UU, details reporting requirements for sources subject to the National Emission Standards for Equpment Leaks-Control Level 2.

40 CFR 63.104



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If there are heat exchangers in a process unit that is subject to the Hazardous Organic NESHAP rule, the facility must monitor the heat exchangers for leaks in order to prevent organic hazardous air pollutants from entering the coolant water supply. The facility can choose to either monitor the cooling water directly or measure some other parameter that would indicate a leak in the heat exchange equipment.

40 CFR 63.105

This condition requires that the facility prepare a plan on how to manage the wastewater containing organic hazardous air pollutants that is generated during process unit maintenance or shutdown. This plan should include every task that creates this type of wastewater and how best to handle the water to minimize the amount of organic hazardous air pollutants that get released to the atmosphere.

40 CFR 63.113

This regulation, 40 CFR 63 Subpart G, provides the reference control technology for process vents subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.113 (a) (2)

This allows the owner/operator to either reduce the total OHAP concentration in the vent stream by 98% by weight or to reduce the total OHAP or TOC concentration to 20 ppmv, whichever is less stringent.

40 CFR 63.113 (b)

This condition controls the emissions of hazardous air pollutants by requiring that if the facility is controlling emissions of the gas stream by using a process heater or a boiler, then the stream must be introduced into the flame zone. This helps to ensure complete combustion within the boiler/process heater and therefore minimizes the amount of hazardous air pollutants that could escape to the atmosphere.

40 CFR 63.114

This regulation, 40 CFR 63 Subpart G, provides the monitoring requirements for process vents subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.114 (a) (1) (i)

This regulation, 40 CFR 63 Subpart G, provides the monitoring requirements for process vents subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.114 (a) (3)

This regulation, 40 CFR 63 Subpart G, provides the monitoring requirements for process vents subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.114 (a) (4) (i)

This regulation, 40 CFR 63 Subpart G, provides the monitoring requirements for process vents subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.



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40 CFR 63.114 (a) (4) (ii)

This regulation, 40 CFR 63 Subpart G, provides the monitoring requirements for process vents subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.119 (b)

In order to reduce the emissions of organic hazardous air pollutants from storage vessels, a facility may elect to install a fixed roof and an internal floating roof on the storage vessel. This condition requires the facility to install certain equipment (seals, gaskets, etc.) designed to reduce any direct contact between the liquid in the storage tank and the atmosphere. Periodic inspections to insure that there are no leaks from the internal floating roof into the atmosphere are also required in this condition.

40 CFR 63.119 (e)

In order to reduce the emissions of organic hazardous air pollutants from storage vessels, a facility may elect to install a system that routes all of the emissions from the storage vessel to a control device. This condition requires that the control device reduces the organic hazardous air pollutants in this captured stream by 90-95% depending on when the control device was installed.

40 CFR 63.1203 (a) (1)

This regulation, 40 CFR 63 Subpart EEE, provides the standards for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1203 (a) (2)

- (a) Emission limits for existing sources You must not discharge or cause combustion gasses to be emitted into the atmosphere that contain:
 - (2) Mercury in excess of 130 μg/dscm corrected to 7 percent oxygen;

40 CFR 63.1203 (a) (3)

- (a) Emission limits for existing sources You must not discharge or cause combustion gasses to be emitted into the atmosphere that contain:
- (3) Lead and cadmium in excess of 240 μg/dscm, combined emissions, corrected to 7 percent oxygen;

40 CFR 63.1203 (a) (4)

- (a) Emission limits for existing sources You must not discharge or cause combustion gasses to be emitted into the atmosphere that contain:
- (4) Arsenic, beryllium, and chromium in excess of 97 μg/dscm, combined emissions, corrected to 7 percent oxygen;

40 CFR 63.1203 (a) (5) (i)

- (a) Emission limits for existing sources You must not discharge or cause combustion gasses to be emitted into the atmosphere that contain:
- (5) For carbon monoxide and hydrocarbons, either:
- (i) Carbon monoxide in excess of 100 parts per million by volume, over an hourly rolling average (monitored continuously with a continuous emissions monitoring system), dry basis and corrected to 7 percent oxygen. If you elect to comply with this carbon monoxide standard rather than the



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hydrocarbon standard under paragraph (a)(5)(ii) of this section, you must also document that, during the destruction and removal efficiency (DRE) test runs or their equivalent as provided by § 63.1206(b)(7), hydrocarbons do not exceed 10 parts per million by volume during those runs, over an hourly rolling average (monitored continuously with a continuous emissions monitoring system), dry basis, corrected to 7 percent oxygen, and reported as propane; or

(ii) Hydrocarbons in excess of 10 parts per million by volume, over an hourly rolling average (monitored continuously with a continuous emissions monitoring system), dry basis, corrected to 7 percent oxygen, and reported as propane;

40 CFR 63.1203 (a) (6)

- (a) Emission limits for existing sources You must not discharge or cause combustion gasses to be emitted into the atmosphere that contain:
- (6) Hydrochloric acid and chlorine gas in excess of 77 parts per million by volume, combined emissions, expressed as hydrochloric acid equivalents, dry basis and corrected to 7 percent oxygen; and

40 CFR 63.1203 (a) (7)

- (a) Emission limits for existing sources You must not discharge or cause combustion gasses to be emitted into the atmosphere that contain:
 - (7) Particulate matter in excess of 34 mg/dscm corrected to 7 percent oxygen.

40 CFR 63.1203 (c) (1)

This regulation, 40 CFR 63 Subpart EEE, provides the standards for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1203 (c) (3) (ii)

This regulation, 40 CFR 63 Subpart EEE, provides the standards for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1206 (a) (1) (ii) ('A')

This regulation, 40 CFR 63 Subpart EEE, details when and how a facility must comply with the applicable requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1206 (b)

Summary of Compliance with standards (see regulation for detailed descriptions)

- (1) Applicability.
- (2) Methods for determining compliance.
- (3) Finding of compliance.
- (4) Extension of compliance with emission standards.
- (5) Changes in design, operation, or maintenance.
- (6) Compliance with the carbon monoxide and hydrocarbon emission standards.
- (7) Compliance with the DRE standard.
- (8) Applicability of particulate matter and opacity standards during particulate matter CEMS correlation tests.
- (9) Alternative standards for existing or new hazardous waste burning lightweight aggregate kilns using MACT.
- (10) Alternative standards for existing or new hazardous waste burning cement kilns using MACT.



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- (11) Calculation of hazardous waste residence time.
- (12) Documenting compliance with the standards based on performance testing.
- (13) Cement kilns and lightweight aggregate kilns that feed hazardous waste at a location other than the end where products are normally discharged and where fuels are normally fired.
- (14) Alternative particulate matter standard for incinerators with de minimis metals.

40 CFR 63.1206 (c)

Summary of Operating requirements --

- (1) General.
- (2) Startup, shutdown, and malfunction plan.
- (3) Automatic waste feed cutoff
- (4) ESV openings
- (5) Combustion System Leaks
- (6) Operator training and certification.
- (7) Operation and maintenance plan

40 CFR 63.1207

Summary of the performance testing requirements:

- (a) General.
- (b) Types of performance tests
- (c) Initial comprehensive performance test
- (d) Frequency of testing.
- (e) Notification of performance test and CMS performance evaluation, and approval of test plan and CMS performance evaluation plan.
- (f) Content of performance test plan.
- (g) Operating conditions during testing.
- (h) Operating conditions during subsequent testing.
- (i) Time extension for subsequent performance tests.
- (j) Notification of Compliance
- (k) Failure to submit a timely notification of compliance.
- (l) Failure of performance test
- (m) Waiver of Performance Test
- (n) Feedrate limits for nondetectable constituents.

40 CFR 63.1209

63.1209 What are the monitoring requirements?

- (a) Continuous emissions monitoring systems (CEMS) and continuous opacity monitoring systems (COMS).
- (b) Other continuous monitoring systems (CMS).
- (c) Analysis of feedstreams.
- (d) Performance evaluations.
- (e) Conduct of monitoring.
- (f) Operation and maintenance of continuous monitoring systems.
- (g) Alternative monitoring requirements other than continuous emissions monitoring systems (CEMS).
- (h) Reduction of monitoring data.
- (i) When an operating parameter is applicable to multiple standards.
- (j) DRE.
- (k) Dioxins and furans.



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- (1) Mercury
- (m) Particulate matter.
- (n) Semivolatile metals and low volatility metals.
- (o) Hydrochloric acid and chlorine gas.
- (p) Maximum combustion chamber pressure.
- (q) Operating under different modes of operation.

40 CFR 63.1209 (a) (1) (i)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (a) (1) (iii)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (a) (2)

This condition requires the facility to ensure that the continuous monitor that is installed to be properly maintained and operated so that the emission results it reads is accurate.

40 CFR 63.1209 (a) (3) (i)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (a) (6) (i)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (a) (6) (ii)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.40

40 CFR 63.1209 (a) (6) (iii)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (a) (7)

This condition explains how the facility is expected to ensure that the emission standard for hydrocarbons is not exceeded. Basically, the facility is expected to set limits based on the readings of a continuous monitor and limits relating to a specific destruction and removal efficiency (DRE) during the performance test and continuously comply with them.

40 CFR 63.1209 (c) (1)

This condition requires the facility to analyze each feedstream to determine whether the properties of the feedstream are within the parameter limits.



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40 CFR 63.1209 (c) (2)

This condition requires the facility to develop a feedstream analysis plan in order to determine whether the properties of the feedstream meet the operating limits in this subpart. This analysis should include information on what the facility will measure, and how the parameter will be measured. The plan will be recorded in the facility's operating record.

40 CFR 63.1209 (c) (4)

This condition describes how the facility is expected to comply with the feedstream parameter limits. The condition requires a continuous monitoring system to measure the proper parameters of the feedstream so that the facility can calculate and record the parameter to ensure the parameter's limit is not exceeded.

40 CFR 63.1209 (j) (1)

This condition requires that in order for the facility to determine if it is complying with the destruction and removal efficiency standard, then a minimum combustion temperature must be established during the performance test. This temperature would be representative of the minimum temperature that will destroy the hazardous air pollutant emissions sufficiently to satisfy the limit in this subpart.

40 CFR 63.1209 (j) (3)

This condition requires that in order for the facility to determine if it is complying with the destruction and removal efficiency standard, then a maximum hazardous waste feedrate must be established during the performance test. This feedrate would be representative of the maximum value that will ensure that the hazardous air pollutant emissions are sufficiently reduced to satisfy the emission limits in this subpart.

40 CFR 63.1209 (j) (4)

This condition requires that in order for the facility to determine if it is complying with the destruction and removal efficiency standard, then parameters must be established during the performance test which indicate proper operation of the waste firing system.

40 CFR 63.1209 (1) (1)

During the comprehensive performance test, the maximum level of mercury is established which will ensure that the hazardous waste combustor does not exceed the emission limit for mercury. The facility will then need to monitor the mercury content of the hazardous waste to prove that the limit has not been exceeded.

40 CFR 63.1209 (m) (1) (i) ('B') ('1')

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (m) (1) (i) ('B') ('2')

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (m) (1) (i) ('B') ('4')

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.



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40 CFR 63.1209 (m) (3)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (n) (2)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1209 (n) (2) (ii)

When the facility is monitoring the hazardous waste feedstream for the amount of metals being loaded into the hazardous waste combustor, the facility must set a limit based on the loading during the comprehensive performance test. This condition allows the facility to use extrapolation if they wish to feed more metals into the combustor, as long as the calculation shows that the facility will still be under the emission limits for metals.

40 CFR 63.1209 (n) (4)

In order for the hazardous waste combustor to meet the emission limits for metals, then during the comprehensive performance test the facility must establish operating limits that prove that the facility will be in compliance with the metal limits as long as the operating parameter is being met. This condition specifically requires the facility to set a limit for the amount of chlorine and chloride in the hazardous waste feedstream.

40 CFR 63.1209 (o) (3) (ii)

If the facility equips the hazardous waste combustor with a low energy wet scrubber, then this condition requires the facility to monitor certain parameters to make sure the scrubber is working properly to control hydrochloric acid and chloride gas emissions. This condition specifically requires the facility to monitor the pressure drop across the scrubber.

40 CFR 63.1209 (o) (3) (iii)

If the facility equips the hazardous waste combustor with a low energy wet scrubber, then this condition requires the facility to monitor certain parameters to make sure the scrubber is working properly to control hydrochloric acid and chloride gas emissions. This condition specifically requires the facility to monitor the minimum liquid feed pressure in the scrubber.

40 CFR 63.1209 (o) (3) (iv)

If the facility equips the hazardous waste combustor with a wet scrubber, then this condition requires the facility to monitor certain parameters to make sure the scrubber is working properly to control hydrochloric acid and chloride gas emissions. This condition specifically requires the facility to monitor the pH in the scrubber.

40 CFR 63.1209 (o) (3) (v)

If the facility equips the hazardous waste combustor with a low energy wet scrubber, then this condition requires the facility to monitor certain parameters to make sure the scrubber is working properly to control hydrochloric acid and chloride gas emissions. This condition specifically requires the facility to monitor the minimum liquid-gas ratio or minimum scrubber water flowrate and maximum flue gas flowrate in the scrubber.

40 CFR 63.1209 (p)

This condition reduces the emissions of hazardous air pollutants by requiring the facility to keep the



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pressure inside of the combustion chamber of the hazardous waste combustor under that of the atmosphere outside of the combustor. This reduces the chance of leaks from the combustor escaping into the atmosphere.

40 CFR 63.1210 (a)

This regulation, 40 CFR 63 Subpart EEE, details the notification requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1210 (b)

This regulation, 40 CFR 63 Subpart EEE, details the notification requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1210 (d)

This regulation, 40 CFR 63 Subpart EEE, details the notification requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1211 (a)

This regulation, 40 CFR 63 Subpart EEE, details the record keeping and reporting requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1211 (b)

This condition lists the information that the facility must keep on record at the plant. This information will assist the NYSDEC when the facility is inspected in order to determine whether the plant has been in compliance with the emission standards listed in this subpart EEE. Information that must be recorded includes instrument readings which indicate whether any control devices were working, whether there were any startups, shutdowns, or malfunctions at the facility, and whether the plant has changed its operation in a way that could affect the emissions from the incinerator.

40 CFR 63.1211 (c)

This regulation, 40 CFR 63 Subpart EEE, details the record keeping and reporting requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1219 (a)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1219 (c) (1)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.1219 (c) (3) (ii)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.



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40 CFR 63.1219 (e)

This regulation, 40 CFR 63 Subpart EEE, details the monitoring requirements for a facility subject to the requirements for Hazardous Waste Incinerators subject to a National Emissions Standard for Hazardous Air Pollutant from Hazardous Waste Combustors.

40 CFR 63.123 (a)

This condition requires the facility to keep a record of the dimensions and the capacity of any storage vessel that is subject to the HON rule.

40 CFR 63.132 (a) (3)

According to this condition, the facility must keep certain records for wastewater streams that are not considered a high risk of hazardous air pollutant emissions. These records will ensure that the stream(s) remain a minor source of emissions and are subject to verification by the New York State DEC.

40 CFR 63.132 (f)

This regulation, 40 CFR 63 Subpart G, provides the general process waste water requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.133 (a) (1)

This regulation, 40 CFR 63 Subpart G, provides the requirements for waste water tanks subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.133 (a) (2)

This regulation, 40 CFR 63 Subpart G, provides the requirements for waste water tanks subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.133 (f)

This regulation, 40 CFR 63 Subpart G, provides the requirements for waste water tanks subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.135 (b)

This regulation, 40 CFR 63 Subpart G, provides the requirements for containers subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.135 (c)

This regulation, 40 CFR 63 Subpart G, provides the requirements for containers subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.135 (e)

This regulation, 40 CFR 63 Subpart G, provides the requirements for containers subject to a National



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40 CFR 63.135 (f)

This regulation, 40 CFR 63 Subpart G, provides the requirements for containers subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.136

This regulation, 40 CFR 63 Subpart G, provides the requirements for individual drain systems subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.138 (a)

This regulation, 40 CFR 63 Subpart G, provides the requirements for treatment processes managing Group 1 wastewater streams and/or residuals removed from streams and/or residuals removed from Group 1 wastewater streams subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.138 (k)

This regulation, 40 CFR 63 Subpart G, provides the requirements for treatment processes managing Group 1 wastewater streams and/or residuals removed from streams and/or residuals removed from Group 1 wastewater streams subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.139 (b)

This regulation, 40 CFR 63 Subpart G, contains provisions for process wastewater control devices subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.139 (c)

This regulation, 40 CFR 63 Subpart G, contains provisions for process wastewater control devices subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.139 (f)

This regulation, 40 CFR 63 Subpart G, contains provisions for process wastewater control devices subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.140

This regulation, 40 CFR 63 Subpart G, contains provisions for process wastewater delay of repair of sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.



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40 CFR 63.143 (e)

This regulation, 40 CFR 63 Subpart G, contains provisions for the inspection and monitoring of operations for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.143 (g)

This regulation, 40 CFR 63 Subpart G, contains provisions for the inspection and monitoring of operations for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.145 (h)

This regulations details the test methods and procedures to determine compliance for Process wastewater sources.

40 CFR 63.146 (b)

This regulation, 40 CFR 63 Subpart G, contains the reporting requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.147

This regulation, 40 CFR 63 Subpart G, contains the recordkeeping requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.148

This regulation, 40 CFR 63 Subpart G, contains the leak inspection requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.148 (b) (1)

This condition requires any vapor collection system and closed-vent system that consists of hard-piping to be periodically checked for leaks of organic hazardous air pollutants. There shall be an initial inspection of the entire system using an analyzer. Subsequently, the systems shall be looked at annually and checked to see if there is any physical evidence (sight, smell, etc.) of a leak.

40 CFR 63.148 (d)

This condition requires the facility to repair any leaks found on a closed-vent or vapor collection system that is subject to the HON rule. This condition helps minimize the fugitive losses of organic hazardous air pollutants by ensuring that the facility repairs all leaks within 15 days. Adequate records also are required in order to keep track of the leaks in these systems.

40 CFR 63.148 (e)

This condition allows a facility that found leaks in a vapor collection system or closed-vent system to delay the repair of these leaks. The leaks may be delayed if doing so would create more emissions of organic hazardous air pollutants than otherwise would result from leaving the leak alone.



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40 CFR 63.148 (i)

This regulation, 40 CFR 63 Subpart G, contains the leak inspection requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.148 (j)

This regulation, 40 CFR 63 Subpart G, contains the leak inspection requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants from the Synthetic Organic Chemical Manufacturing Industry for Process Vents, Storage Vessels, Transfer Operations, and Wastewater.

40 CFR 63.152 (d) (1)

This condition requires the facility to submit reports of startups, shutdowns, and malfunctions that occur during each 6-month period.

40 CFR 63.160

This section of the Equipment Leaks portion of the Hazardous Organic NESHAP rule describes the types of equipment subject to the rule and types that are exempt. It also describes how overlap with other federal regulations are handled.

40 CFR 63.162 (c)

This regulation, 40 CFR 63 Subpart H, contains the General Standards for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.162 (f)

This condition requires the facility to identify which pieces of equipment is leaking hazardous air pollutants. The facility is generally allowed to remove the indicator sign once the equipment has been remonitored and is no longer leaking.

40 CFR 63.163 (a)

This regulation, 40 CFR 63 Subpart H, contains the Standards for pumps in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.163 (b) (1)

This regulation, 40 CFR 63 Subpart H, contains the Standards for pumps in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.163 (b) (2)

This paragraph of the Equipment Leaks rule defines leaks for pumps in light liquid service. Leaks are not violations but trigger attempts at repair.

40 CFR 63.163 (b) (3)

This regulation, 40 CFR 63 Subpart H, contains the Standards for pumps in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.163 (d) (1)

This paragraph of the equipment leaks rule describes how to calculate the percent of leaking pumps in light liquid service. The result is used to determine whether or not a quality improvement program for pumps is required.



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40 CFR 63.164 (i)

This regulation, 40 CFR 63 Subpart H, contains the Standards for compressors subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.165 (d) (2)

This regulation, 40 CFR 63 Subpart H, contains the standards for pressure relief devices in gas/vapor service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.166

This condition reduces the emissions of hazardous air pollutants by requiring the facility to install sampling connection systems in such a way that the sampling system is either closed or disposed of in an approved method.

40 CFR 63.167 (a) (1)

This regulation, 40 CFR 63 Subpart H, contains the standards for open-ended valves or lines subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.167 (b)

This condition reduces the fugitive emissions of hazardous air pollutants by requiring that when a facility has an open-ended valve or line that is subject to subpart H, there needs to be a valve on the process side that is closed before the second valve is closed. This will greatly reduce the accidental release of fluids that contain hazardous air pollutants.

40 CFR 63.167 (c)

This regulation, 40 CFR 63 Subpart H, contains the standards for open-ended valves or lines subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.167 (d)

This regulation, 40 CFR 63 Subpart H, contains the standards for open-ended valves or lines subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.168 (b)

This regulation, 40 CFR 63 Subpart H, contains the standards for valves in gas/vapor service and in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.168 (f) (1)

This regulation, 40 CFR 63 Subpart H, contains the standards for valves in gas/vapor service and in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.168 (h)

This regulation, 40 CFR 63 Subpart H, contains the standards for valves in gas/vapor service and in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.168 (i)

This regulation, 40 CFR 63 Subpart H, contains the standards for valves in gas/vapor service and in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for



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Equipment Leaks.

40 CFR 63.171 (a)

This condition allows the facility to delay repair of a leaking piece of equipment if the facility deems it to be technically infeasible to do so. The repair must be done the next time the process is not in operation.

40 CFR 63.171 (b)

This condition allows the facility to delay the repair of a leaking piece of equipment if the leaking equipment is isolated and no longer contains organic hazardous air pollutants.

40 CFR 63.171 (c)

This condition allows facilities the option to delay the repair of certain types of equipment that are leaking hazardous air pollutants if the repair of that equipment would cause more emissions than if they left the equipment alone. In these cases, the material that was purged during the repair must be collected and controlled in order to further reduce the emissions of hazardous air pollutants.

40 CFR 63.171 (d)

This condition allows the facility to delay the repair of pumps if the repair entails:

- implementing a quality improvement program (QIP) for the pump,
- replacing the pump with one that is much less susceptible to leaking, or
- venting emissions from the pump to a closed-vent system with a control device.

The facility will be given up to six months to repair the leaking pump.

40 CFR 63.171 (e)

This condition allows the facility to extend a delayed repair beyond a process unit shutdown for valves if certain, specific extenuating circumstances are being faced.

40 CFR 63.174 (a)

This condition reduces the emissions of hazardous air pollutants by requiring the facility to periodically check for leaks in certain connectors. The facility then has a limited amount of time in order to repair the leak and stop the fugitive emissions of hazardous air pollutants. The facility may reduce the frequency of monitoring for leaks if the percentage of connectors that are leaking is below a certain threshold. Records must be kept and reports must be submitted verifying compliance with this condition.

40 CFR 63.174 (c) (1) (i)

This condition specifies the different monitoring requirements for connectors that has been opened. The facility must either monitor the connector right away or must automatically count it as a leaking connector when calculating the monitoring frequency of connectors throughout the facility.

40 CFR 63.174 (c) (2)

This regulation, 40 CFR 63 Subpart H, contains the standards for connectors in gas/vapor service and in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.174 (f)

This condition allows the facility to skip the periodic monitoring of connectors that are not safe for personnel to monitor. A written plan must be developed requiring monitoring as often as possible during times when it is safe to monitor the connector.



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40 CFR 63.174 (g)

This condition allows the facility to delay repairing of a connector if it is deemed to be unsafe for personnel to repair until the next shutdown.

40 CFR 63.174 (h) (1)

This regulation, 40 CFR 63 Subpart H, contains the standards for connectors in gas/vapor service and in light liquid service and subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.175

This regulation, 40 CFR 63 Subpart H, contains the requirements for a quality improvement program for valves subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.181 (a)

This condition specifies certain recordkeeping requirements for facilities that are subject to Subpart H. These requirements basically require the facility to make all of the records readily accessible so that they may be verified by an inspector.

40 CFR 63.181 (b)

This condition lists some of the records that the facility must keep in order to verify compliance with Subpart H. This condition specifically requires the company to keep lists of each piece of equipment that is supposed to be monitored according to the provisions in Subpart H.

40 CFR 63.181 (c)

This regulation, 40 CFR 63 Subpart H, contains recordkeeping requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.181 (d)

This regulation, 40 CFR 63 Subpart H, contains recordkeeping requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.181 (f)

This regulation, 40 CFR 63 Subpart H, contains recordkeeping requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.181 (h)

This regulation, 40 CFR 63 Subpart H, contains recordkeeping requirements for sources subject to a National Emissions Standard for Organic Hazardous Air Pollutants for Equipment Leaks.

40 CFR 63.182 (d)

This condition lists the items that the facility must enter in their semi-annual periodic report. The items include the number of pieces of equipment that were monitored, how many pieces of equipment were found to be leaking and whether the leaks were repaired.

40 CFR 63.2450 (a)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.



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40 CFR 63.2450 (b)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2450 (f)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2450 (h)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2450 (i)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2450 (j)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2450 (k)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2450 (1)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2450 (p)

This regulation, 40 CFR 63 Subpart FFFF, details the general requirements to comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2455 (a)

This regulation, 40 CFR 63 Subpart FFFF, details when a facility must comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2455 (b)

This regulation, 40 CFR 63 Subpart FFFF, details when a facility must comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2460 (a)



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This regulation, 40 CFR 63 Subpart FFFF, details when a facility must comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2460 (b)

This regulation, 40 CFR 63 Subpart FFFF, details when a facility must comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2460 (c)

This regulation, 40 CFR 63 Subpart FFFF, details when a facility must comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2460 (c) (7)

This regulation, 40 CFR 63 Subpart FFFF, details when a facility must comply with the requirements for National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2465 (a)

This regulation, 40 CFR 63 Subpart FFFF, details the requirements to meet for process vents that emit hydrogen halide and halogen HAP or PM HAP for facilities sujbect to the National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2480

This regulation, 40 CFR 63 Subpart FFFF, details the requirements to meet for equipment leaks for facilities sujbect to the National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2485 (c)

This regulation, 40 CFR 63 Subpart FFFF, details the requirements to meet for wastewater streams and liquid streams in open systems within an MCPU for facilities sujbect to the National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2520 (c)

This regulation, 40 CFR 63 Subpart FFFF, details what reorts must be submitted and when for facilities sujbect to the National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2525

This regulation, 40 CFR 63 Subpart FFFF, details what reports must be submitted and when for facilities subject to the National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.2535 (g)

This regulation, 40 CFR 63 Subpart FFFF, details compliance options when part of a plant is subject to both this subpart and anothre subpart for facilities subject to the National Emission Standards for Hazardous Air Pollutants: Miscellaneous Organic Chemical Manufacturing.

40 CFR 63.6 (e) (1)

This condition requires the facility to address the emissions of hazardous air pollutants (HAPs)



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during periods when the process(es) are starting up, shutting down, or malfunctioning. This condition requires the facility to come up with a startup, shutdown, malfunction plan (SSMP) which addresses how the plant personnel will react to each of the situations when the process(es) are not functioning normally and what steps will be taken to reduce the release of HAPs to the atmosphere.

If the facility takes actions which aren't in the SSMP, then the facility needs to notify NYSDEC, and update the SSMP accordingly.

The facility must have the SSMP available upon request for the NYSDEC to review.

40 CFR 63.6 (e) (1) (i)

Paragraph 63.6(e) requires that affected sources including air pollution control equipment must be operated and maintained to minimize emissions "at least to the level required by all relevant standards." It further requires that this be done at all time including during periods of startup, shutdown, and malfunction (SSM). Also operation during those times must be according to a SSM plan. §63.6(f) indicates however that nonopacity emission standards do <u>not</u> apply during SSM periods. Thus at those times the owner or operator must minimize emissions.

40 CFR 63.6 (e) (3)

Paragraph 63.6(e)(3) requires a startup, shutdown, and malfunction (SSM) plan for MACT-affected sources and that the plan be followed.

40 CFR 63.6 (f) (1)

This section states that nonopacity standards apply at all times except during periods of startup, shutdown, and malfunction.

40 CFR 63.6 (f) (2) (i)

§63.6(f)(2) states that compliance with nonopacity standards shall be based on the results of performance tests using procedures in §63.7 and on conformance with the operation and maintenance requirements of §63.6(e).

40 CFR 63.6 (f) (2) (ii)

§63.6(f)(2) states that compliance with nonopacity standards shall be based on the results of performance tests using procedures in §63.7 and on conformance with the operation and maintenance requirements of §63.6(e).

40 CFR 63.6590 (b) (3)

This condition lists the types of engines that are exempt from the provisions in this NESHAP rule. The types of engines include:

Existing 2-stroke lean burn

Existing 4-stroke lean burn

Existing compression ignition

Existing emergency

Existing limited-use

Existing landfill/digester gas fuel-fired

40 CFR 63.680 (d)

This regulation, 40 CFR 63 Subpart DD, lists the applicability and designation of affected sources subject to a National Emissions Standard for Hazardous Air Pollutant from Off-Site Waste and Recovery



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Operations.

40 CFR 63.7881 (c)

This regulation, 40 CFR 63 Subpart GGGGG, details who is subject to the National Emissions Standard for Hazardous Air Pollutants from Site Remediation.

40 CFR 63.9000 (a)

This regulation, 40 CFR 63 Subpart NNNNN, details the applicable emission limits and work practice standards for sources subject to the requirements for National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9000 (b)

This regulation, 40 CFR 63 Subpart NNNNN, details the applicable emission limits and work practice standards for sources subject to the requirements for National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9005 (a)

This regulation, 40 CFR 63 Subpart NNNNN, details the general requirements for sources subject to the requirements for National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9005 (b)

This regulation, 40 CFR 63 Subpart NNNNN, details the general requirements for sources subject to the requirements for National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9005 (c)

This regulation, 40 CFR 63 Subpart NNNNN, details the general requirements for sources subject to the requirements for National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9005 (d)

This regulation, 40 CFR 63 Subpart NNNNN, details the general requirements for sources subject to the requirements for National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9020 (b)

This regulation, 40 CFR 63 Subpart NNNNN, specifies required performance tests and proceedures for sources subject to the requirements for National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9020 (e)

This regulation, 40 CFR 63 Subpart NNNNN, specifies required performance tests and proceedures for sources subject to the requirements for National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9025 (a)

This regulation, 40 CFR 63 Subpart NNNNN, specifies monitoring installation, operation and maintenance requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.



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40 CFR 63.9025 (b)

This regulation, 40 CFR 63 Subpart NNNNN, specifies monitoring installation, operation and maintenance requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9030 (a)

This regulation, 40 CFR 63 Subpart NNNNN, specifies initial compliance demonstration requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9030 (b)

This regulation, 40 CFR 63 Subpart NNNNN, specifies initial compliance demonstration requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9035 (b)

This regulation, 40 CFR 63 Subpart NNNNN, specifies continuous compliance monitoring and data collection requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9035 (d)

This regulation, 40 CFR 63 Subpart NNNNN, specifies continuous compliance monitoring and data collection requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9035 (e)

This regulation, 40 CFR 63 Subpart NNNNN, specifies continuous compliance monitoring and data collection requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9040 (c)

This regulation, 40 CFR 63 Subpart NNNNN, specifies continuous compliance emission limits and work practice requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9045 (f)

This regulation, 40 CFR 63 Subpart NNNNN, specifies notification submittal requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9045 (g)

This regulation, 40 CFR 63 Subpart NNNNN, specifies notification submittal requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9050 (a)

This regulation, 40 CFR 63 Subpart NNNNN, specifies report submittal requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9050 (b)

This regulation, 40 CFR 63 Subpart NNNNN, specifies report submittal requirements for sources subject



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to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9050 (c)

This regulation, 40 CFR 63 Subpart NNNNN, specifies report submittal requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9050 (d)

This regulation, 40 CFR 63 Subpart NNNNN, specifies report submittal requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9050 (e)

This regulation, 40 CFR 63 Subpart NNNNN, specifies report submittal requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9050 (f)

This regulation, 40 CFR 63 Subpart NNNNN, specifies report submittal requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9055

This regulation, 40 CFR 63 Subpart NNNNN, specifies records retention requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.9060

This regulation, 40 CFR 63 Subpart NNNNN, specifies records retention and format requirements for sources subject to National Emission Standards for Hazardous Air Pollutants from Hazardous Waste Combustors.

40 CFR 63.983 (a)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for closed vent systems subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.983 (b)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for closed vent systems subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.983 (c)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for closed vent systems subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.983 (d)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for closed vent systems subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.988 (a)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for incinerators, boilers, and process heaters subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery



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Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.988 (b)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for incinerators, boilers, and process heaters subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.990 (a)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for absorbers, condensers, and carbon adsorbers used as contol devices for sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.990 (b)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for absorbers, condensers, and carbon adsorbers used as contol devices for sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.994 (a) (2)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for halogen scrubbers and other halogen reduction devices on sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.994 (b)

This regulation, 40 CFR 63 Subpart SS, contains the requirements for halogen scrubbers and other halogen reduction devices on sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.996

This regulation, 40 CFR 63 Subpart SS, contains the general monitoring requirements for control and recovery devices on sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.996 (d)

This regulation, 40 CFR 63 Subpart SS, contains the general monitoring requirements for control and recovery devices on sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.998 (a) (2)

This regulation, 40 CFR 63 Subpart SS, contains the recordkeeping requirements for sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.998 (b)

This regulation, 40 CFR 63 Subpart SS, contains the recordkeeping requirements for sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.998 (c)

This regulation, 40 CFR 63 Subpart SS, contains the recordkeeping requirements for sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.



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40 CFR 63.998 (c) (1)

This regulation, 40 CFR 63 Subpart SS, contains the recordkeeping requirements for sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.998 (c) (2)

This regulation, 40 CFR 63 Subpart SS, contains the recordkeeping requirements for sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR 63.998 (d) (1)

This regulation, 40 CFR 63 Subpart SS, contains the recordkeeping requirements for sources subject to a National Emissions Standard for Closed Vent Systems, Control Devices, Recovery Devices and Routing to a Fuel Gas System or a Process.

40 CFR Part 61, Subpart A

This regulation, 40 CFR 61 Subpart A, lists the general provisions that a facility subject to a National Emissions Standard for Hazardous Air Pollutant is subject to.

6 NYCRR 201-6.5 (f)

This regulation defines in general terms under what circumstances changes would be allowed without a permit modification provided the permit contains sufficient operational flexibility provisions.

6 NYCRR 211.1

This provision prohibits general emissions of air contaminants to the outdoor atmosphere of such quantity, characteristic or duration which are injurious to human, plant or animal life or to property, or which unreasonably interfere with the comfortable enjoyment of life or property.

6 NYCRR 212.10 (a) (2)

6 NYCRR 212.10(a)(2) has the Reasonably Available Control Technology requirements for major facilities in upstate NY.

6 NYCRR 212.10 (c) (4) (i)

VOC removal efficiency greater than 81% is considered RACT.

6 NYCRR 212.10 (c) (4) (iii)

This rule allows those sources which cannot achieve an overall removal efficiency of 81% or use coatings that don't exceed 3.5 lbs. VOC/gallon as applied for technological or economic reasons to use process specific reasonably available control technology (RACT) demonstrations for sources of volatile organic compounds (VOC) which are acceptable to the department and have been submitted to EPA for approval as a revision to the State Implementation Plan by the department.

6 NYCRR 212.2

6NYCRR 212.2 specifies that the commissioner shall issue an environmental rating for each air contaminant from each emission point when an application for an air permit is made.

6 NYCRR 212.3 (a)



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This rule requires compliance with the degree of control specified in Tables 2, 3 and 4 for existing (on or before July 1, 1973) process emission sources.

6 NYCRR 212.4 (a)

This rule requires compliance with the degree of control specified in Tables 2, 3 and 4 for new (after July 1, 1973) process emission sources.

6 NYCRR 212.4 (b)

212.4(b) establishes a limit on gas and liquid particulates.

6 NYCRR 212.4 (c)

This rule requires existing sources (in operation after July 1, 1973) of solid particulates with environmental rating of B or C which are not subject to Table 5 "Processes for which Permissible Emission Rate is Based on Process Weight, to be limited to an particulate emission rate not to exceed 0.05 grains per dry standard cubic foot.

6 NYCRR 212.5 (d)

This section specifies that if best available control technologies are implemented the commissioner may specify, under certain situations, a less restrictive emission rate.

6 NYCRR 212.6 (a)

This rule specifies an opacity limitation of less than 20% for any six consecutive minute period for all process emission sources.

6 NYCRR 212.9 (b)

This section refers to Table 2 which specifies the degree of control required for Gases and Liquid Particulate Emissions (Environmental Rating of A, B, C or D) and Solid Particulate Emissions (Environmental Rating A or D) but excluding Volatile Organic Compound Emissions in the New York City Metropolitan Area.

6 NYCRR 225-1.2 (a) (2)

This regulation prohibits any person from selling, offering for sale, purchasing or using any fuel which contains sulfur in a quantity exceeding the limitations set forth in Table 1, Table 2, or Table 3 of this section.

6 NYCRR 225-1.7 (c)

This regulation requires requires that measurements be made daily of the rate of each fuel burned, the gross heat content and ash content of each fuel burned (determined at least once per week), and the average electrical output (daily) and hourly generation rate.

6 NYCRR 227.2 (b) (1)

This regulation is from the 1972 version of Part 227 and still remains as part of New York's SIP. The rule establishes a particulate limit of 0.10 lbs/mmBtu based on a 2 hour average emission for any oil fired stationary combustion installation.

6 NYCRR 227-1.2 (a) (1)

This regulation establishes a particulate emission limit in terms of lbs per mmBtu of heat input for stationary combustion units of greater than 250 mmBtu/hr heat input capacity which fire coal, oil, or coal derived fuels.

6 NYCRR 227-1.3



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This regulation requires a limitation and compliance monitoring for opacity from a stationary combustion installation.

6 NYCRR 227-1.3 (a)

This regulation prohibits any person from operating a stationary combustion installation which emits smoke equal to or greater than 20% opacity except for one six-minute period per hour of not more than 27% opacity.

6 NYCRR 227-2.2 (b) (1)

227-2.2(b)(1) defines the term "actuial 1990 baseline emissions"

6 NYCRR 227-2.4 (a) (1)

This condition lists the emission limitations for very large boilers.

6 NYCRR 227-2.4 (b) (1)

This paragraph provides a table for gas only, gas and/or oil firing capable, pulverized coal, and overfeed stoker emission limits. Compliance is determined by a stack test.

6 NYCRR 227-2.4 (d)

This rule specifies that the reasonably available control technology (RACT) requirement for small boilers (< or = 50 million BTUs/hr) at Title V facilities consists of an annual tune-up.

6 NYCRR 227-2.6

This regulation establishes the compliance testing, monitoring, and reporting requirements for NOx RACT affected stationary combustion installations.

6 NYCRR 229.3 (e) (1)

This regulation requires fixed roof storage tanks subject to Part 229 to be equipped with an internal floating roof with a liquid-mounted primary seal and gasketed fittings, or equivalent control. Furthermore, replacement of other than liquid mounted seals is to be performed only when the tank is cleaned and gas-freed for other purposes.

6 NYCRR 229.3 (e) (2) (iv)

This section requires a tank with submerged fill for storage of volatile organic liquids

6 NYCRR 229.3 (e) (2) (v)

This section requires the tank to be equipped with conservation vents for storage of volatile organic liquids.

6 NYCRR 229.5 (d)

This section requires facilities subject to the requirements under Part 229.3, to maintain a record of the capacity of the volatile organic liquid storage tanks, in gallons, for a period of 5 years.

6 NYCRR 231-2.6

The provisions of Subpart 231-2 apply to new or modified major facilities. The contaminants of concern state-wide are nitrogen oxides and volatile organic compounds since New York State is located in the ozone transport region and because there are ozone non-attainment areas within the state. In the New York City metropolitan area, carbon monoxide is also a non-attainment contaminant. In addition, particulate matter less than 10 microns in size (PM-10) is a non-attainment contaminant in Manhattan County.



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The requirements and criteria for creating and certifying emission reduction credits (ERCs) are set forth in section 231-2.6.

6 NYCRR 243-1.6 (c)

This citation explains the general provisions of the Clean Air Interstate Rule (CAIR) NOx Ozone Season Trading Program. This ozone season NOx cap and trade program runs from May 1 through September 30 each year, starting in 2009. Each source shall hold a tonnage equivalent in CAIR NOx Ozone Season allowances that is not less than the total tons of NOx emissions for the ozone season.

6 NYCRR 243-1.6 (d)

This citation for the Clean Air Interstate Rule (CAIR) NOx Ozone Season Trading Program explains some of the penalties that can be imposed on a CAIR NOx Ozone Season source that does not surrender enough CAIR NOx Ozone Season allowances to cover their NOx Ozone Season emissions.

6 NYCRR 243-1.6 (e)

This citation for the Clean Air Interstate Rule (CAIR) NOx Ozone Season Trading Program requires that all reports be submitted as required by this program, and that copies of all records and submissions made for this program be kept on site for at least five years.

6 NYCRR 243-8.1

This citation of the Clean Air Interstate Rule (CAIR) NOx Ozone Season Trading Program explains that CAIR NOx Ozone Season Trading Program sources must install, certify and operate monitoring systems the meet the monitoring, recordkeeping, and reporting requirements in Subpart 6 NYCRR 243-8 and in Subpart H of 40 CFR Part 75.

6 NYCRR 243-8.3

This citation of the Clean Air Interstate Rule (CAIR) NOx Ozone Season Trading Program explains what to do when an emission monitoring system fails quality assurance, quality control, or data validation requirements.

6 NYCRR 243-8.5 (d)

This citation of the Clean Air Interstate Rule (CAIR) NOx Ozone Season Trading Program explains the what requirements the quarterly reports must meet.

6 NYCRR 243-8.5 (e)

This citation of the Clean Air Interstate Rule (CAIR) NOx Ozone Season Trading Program explains the compliance certification requirements the source must follow for each quarterly report.

6 NYCRR Part 212

6 NYCRR Part 212 contains all the requirements for General Process Soruces.

6 NYCRR Part 226

This regulation specifies the general requirements, equipment specifications and operating requirements for open-top vapor, conveyorized and cold cleaning degreasers.

6 NYCRR Subpart 201-7

This regulation sets forth an emission cap that cannot be exceeded by the facility. In this permit that cap is

6 NYCRR Subpart 231-2

The provisions of Subpart 231-2 apply to new or modified major facilities. The contaminants of concern



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state-wide are nitrogen oxides and volatile organic compounds since New York State is located in the ozone transport region and because there are ozone non-attainment areas within the state. In addition, particulate matter less than 10 microns in size (PM-10) is a non-attainment contaminant in Manhattan County.

Compliance Certification Summary of monitoring activities at MOMENTIVE PERFORMANCE MATERIALS:

Location Facility/EU/EP/Process/ES	Cond No	No. Type of Monitoring	
FACILITY	111	record keeping/maintenance procedures	
FACILITY	112	record keeping/maintenance procedures	
FACILITY	113	record keeping/maintenance procedures	
FACILITY	114	record keeping/maintenance procedures	
FACILITY	115	record keeping/maintenance procedures	
FACILITY	116	record keeping/maintenance procedures	
FACILITY	117	record keeping/maintenance procedures	
FACILITY	1-19	record keeping/maintenance procedures	
FACILITY	107	record keeping/maintenance procedures	
FACILITY	108	record keeping/maintenance procedures	
FACILITY	109	record keeping/maintenance procedures	
FACILITY	110	record keeping/maintenance procedures	
FACILITY	118	monitoring of process or control device parameters	
		as surrogate	
FACILITY	119	record keeping/maintenance procedures	
FACILITY	120	continuous emission monitoring (cem)	
FACILITY	121	record keeping/maintenance procedures	
FACILITY	122	record keeping/maintenance procedures	
FACILITY	123	record keeping/maintenance procedures	
FACILITY	124	record keeping/maintenance procedures	
FACILITY	125	record keeping/maintenance procedures	
FACILITY	126	record keeping/maintenance procedures	
FACILITY	127	record keeping/maintenance procedures	
FACILITY	128	record keeping/maintenance procedures	
FACILITY	129	record keeping/maintenance procedures	
FACILITY	130	record keeping/maintenance procedures	
FACILITY	131	record keeping/maintenance procedures	
FACILITY	132	intermittent emission testing	
FACILITY	133	record keeping/maintenance procedures	
FACILITY	134	record keeping/maintenance procedures	
FACILITY	135	intermittent emission testing	
FACILITY	141	record keeping/maintenance procedures	
FACILITY	142	record keeping/maintenance procedures	
FACILITY	143	record keeping/maintenance procedures	
FACILITY	242	record keeping/maintenance procedures	
FACILITY	303	intermittent emission testing	
FACILITY	304	intermittent emission testing	
FACILITY	305	intermittent emission testing	
FACILITY	306	intermittent emission testing	
FACILITY	1-31	continuous emission monitoring (cem)	
FACILITY	308	intermittent emission testing	
FACILITY	309	intermittent emission testing	
FACILITY	310	intermittent emission testing	
FACILITY	311	record keeping/maintenance procedures	
FACILITY	312	record keeping/maintenance procedures	
FACILITY	313	record keeping/maintenance procedures	
FACILITY	1-32	record keeping/maintenance procedures	



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FACILITY	315	record keeping/maintenance procedures
FACILITY	316	record keeping/maintenance procedures
FACILITY	1-33	monitoring of process or control device parameters
FACILITI	1-33	as surrogate
FACILITY	1-34	monitoring of process or control device parameters
PACILITI	1-34	as surrogate
FACILITY	1-35	monitoring of process or control device parameters
FACILITY	1-35	
DAGIT IMW	1 26	as surrogate
FACILITY	1-36	monitoring of process or control device parameters
DAGIT IMW	1 27	as surrogate
FACILITY	1-37	monitoring of process or control device parameters
DA GIL IMV	1 20	as surrogate
FACILITY	1-38	monitoring of process or control device parameters
DAGIT IMW	1 20	as surrogate
FACILITY	1-39	monitoring of process or control device parameters
DA GII IMW	1 40	as surrogate
FACILITY	1-40	monitoring of process or control device parameters
DAGTI IMW	217	as surrogate
FACILITY	317	record keeping/maintenance procedures
FACILITY	318	record keeping/maintenance procedures record keeping/maintenance procedures
FACILITY	319	record keeping/maintenance procedures record keeping/maintenance procedures
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FACILITY	326	record keeping/maintenance procedures
FACILITY	327	record keeping/maintenance procedures
FACILITY	328	monitoring of process or control device parameters
	200	as surrogate
FACILITY	329	monitoring of process or control device parameters
	222	as surrogate
FACILITY	330	monitoring of process or control device parameters
		as surrogate
FACILITY	1-41	monitoring of process or control device parameters
		as surrogate
FACILITY	337	monitoring of process or control device parameters
DA GII IMW	220	as surrogate
FACILITY	338	monitoring of process or control device parameters
DAGTI IMW	220	as surrogate
FACILITY	339	monitoring of process or control device parameters as surrogate
FACILITY	340	monitoring of process or control device parameters
PACILITI	340	
FACILITY	341	as surrogate monitoring of process or control device parameters
LUCITIII	フェエ	as surrogate
FACILITY	342	monitoring of process or control device parameters
PACIBITI	342	as surrogate
FACILITY	343	monitoring of process or control device parameters
TACIBITI	343	as surrogate
FACILITY	345	monitoring of process or control device parameters
111011111	313	as surrogate
FACILITY	346	monitoring of process or control device parameters
111011111	310	as surrogate
FACILITY	347	monitoring of process or control device parameters
	J = /	as surrogate
FACILITY	348	monitoring of process or control device parameters
	5 2 5	as surrogate
FACILITY	349	monitoring of process or control device parameters
	2.2	as surrogate
FACILITY	1-42	monitoring of process or control device parameters
		as surrogate
FACILITY	350	monitoring of process or control device parameters
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FACILITY 376 monitoring of process or control device parameters as surrogate FACILITY 377 monitoring of process or control device parameters as surrogate FACILITY 378 monitoring of process or control device parameters as surrogate FACILITY 379 monitoring of process or control device parameters as surrogate FACILITY 380 monitoring of process or control device parameters as surrogate FACILITY 381 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 384 monitoring of process or control device parameters as surrogate FACILITY 386 monitoring of process or control device parameters as surrogate FACILITY 387 monitoring of process or control device parameters as surrogate	FACILITY	375	
FACILITY 377 monitoring of process or control device parameters as surrogate FACILITY 378 monitoring of process or control device parameters as surrogate FACILITY 379 monitoring of process or control device parameters as surrogate FACILITY 380 monitoring of process or control device parameters as surrogate FACILITY 381 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 1-44 monitoring of process or control device parameters as surrogate	FACILITY	376	monitoring of process or control device parameters
FACILITY 378 monitoring of process or control device parameters as surrogate FACILITY 379 monitoring of process or control device parameters as surrogate FACILITY 380 monitoring of process or control device parameters as surrogate FACILITY 381 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 1-44 monitoring of process or control device parameters	FACILITY	377	monitoring of process or control device parameters
FACILITY 379 monitoring of process or control device parameters as surrogate FACILITY 380 monitoring of process or control device parameters as surrogate FACILITY 381 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 1-44 monitoring of process or control device parameters	FACILITY	378	monitoring of process or control device parameters
FACILITY 380 monitoring of process or control device parameters as surrogate FACILITY 381 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 1-44 monitoring of process or control device parameters	FACILITY	379	monitoring of process or control device parameters
FACILITY 381 monitoring of process or control device parameters as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 1-44 monitoring of process or control device parameters	FACILITY	380	
as surrogate FACILITY 382 monitoring of process or control device parameters as surrogate FACILITY 1-44 monitoring of process or control device parameters	FACILITY	381	<u> </u>
as surrogate as surrogate FACILITY 1-44 monitoring of process or control device parameters	FACILITY	382	as surrogate
			as surrogate
	FACILITY	1-44	



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FACILITY	383	monitoring of process or control device parameters as surrogate
FACILITY	384	monitoring of process or control device parameters as surrogate
FACILITY	386	monitoring of process or control device parameters as surrogate
FACILITY	387	monitoring of process or control device parameters as surrogate
FACILITY	1-45	monitoring of process or control device parameters as surrogate
FACILITY	388	monitoring of process or control device parameters as surrogate
FACILITY	390	record keeping/maintenance procedures
FACILITY	391	record keeping/maintenance procedures
FACILITY	392	record keeping/maintenance procedures
FACILITY	393	record keeping/maintenance procedures
FACILITY	394	record keeping/maintenance procedures
FACILITY	395	record keeping/maintenance procedures
FACILITY	396	record keeping/maintenance procedures
		record keeping/maintenance procedures
FACILITY	397	
FACILITY	398	record keeping/maintenance procedures
FACILITY	399	record keeping/maintenance procedures
FACILITY	400	record keeping/maintenance procedures
FACILITY	1-30	intermittent emission testing
FACILITY	401	intermittent emission testing
FACILITY	402	intermittent emission testing
FACILITY	404	intermittent emission testing
FACILITY	405	intermittent emission testing
FACILITY	406	intermittent emission testing
FACILITY	407	continuous emission monitoring (cem)
FACILITY	407	intermittent emission testing
		5
FACILITY	409	record keeping/maintenance procedures
FACILITY	410	record keeping/maintenance procedures
FACILITY	144	record keeping/maintenance procedures
FACILITY	145	record keeping/maintenance procedures
FACILITY	148	record keeping/maintenance procedures
FACILITY	149	record keeping/maintenance procedures
FACILITY	151	record keeping/maintenance procedures
FACILITY	152	record keeping/maintenance procedures
FACILITY	411	record keeping/maintenance procedures
FACILITY	412	record keeping/maintenance procedures
FACILITY	1-46	record keeping/maintenance procedures
FACILITY	413	record keeping/maintenance procedures
FACILITY	414	record keeping/maintenance procedures
FACILITY	415	record keeping/maintenance procedures
FACILITY	416	record keeping/maintenance procedures
FACILITY	417	record keeping/maintenance procedures
FACILITY	418	record keeping/maintenance procedures
FACILITY	419	record keeping/maintenance procedures
FACILITY	1-47	monitoring of process or control device parameters
		as surrogate
FACILITY	1-48	monitoring of process or control device parameters
		as surrogate
FACILITY	1-49	monitoring of process or control device parameters
		as surrogate
FACILITY	1-50	monitoring of process or control device parameters
		as surrogate
FACILITY	3-83	monitoring of process or control device parameters
		as surrogate
FACILITY	422	record keeping/maintenance procedures
FACILITY	423	monitoring of process or control device parameters
		as surrogate
FACILITY	424	monitoring of process or control device parameters
PACILITI	724	
		as surrogate



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FACILITY	425	monitoring of process or control device parameters as surrogate
FACILITY	426	monitoring of process or control device parameters as surrogate
FACILITY	427	record keeping/maintenance procedures
	428	
FACILITY		record keeping/maintenance procedures
FACILITY	429	record keeping/maintenance procedures
FACILITY	1-52	monitoring of process or control device parameters as surrogate
FACILITY	1-53	monitoring of process or control device parameters
		as surrogate
FACILITY	1-54	monitoring of process or control device parameters
FACILITY	1-54	
		as surrogate
FACILITY	1-55	monitoring of process or control device parameters
		as surrogate
FACILITY	1-56	monitoring of process or control device parameters
		as surrogate
FACILITY	438	record keeping/maintenance procedures
FACILITY	439	record keeping/maintenance procedures
FACILITY	440	record keeping/maintenance procedures
FACILITY	441	record keeping/maintenance procedures
FACILITY	442	record keeping/maintenance procedures
FACILITY	443	record keeping/maintenance procedures
FACILITY	444	record keeping/maintenance procedures
FACILITY	153	record keeping/maintenance procedures
FACILITY	154	intermittent emission testing
FACILITY	155	record keeping/maintenance procedures
		record keeping/maintenance procedures
FACILITY	156	
FACILITY	1-20	monitoring of process or control device parameters as surrogate
FACILITY	1-21	monitoring of process or control device parameters
		as surrogate
FACILITY	159	monitoring of process or control device parameters as surrogate
DAGILIMY	1.60	5
FACILITY	160	monitoring of process or control device parameters
		as surrogate
FACILITY	161	monitoring of process or control device parameters
		as surrogate
FACILITY	1-22	monitoring of process or control device parameters
		as surrogate
FACILITY	162	monitoring of process or control device parameters
		as surrogate
FACILITY	164	monitoring of process or control device parameters
		as surrogate
FACILITY	165	monitoring of process or control device parameters
TACIBITI	103	as surrogate
ENCII IUN	166	monitoring of process or control device parameters
FACILITY	100	5 2
		as surrogate
FACILITY	167	monitoring of process or control device parameters
		as surrogate
FACILITY	168	monitoring of process or control device parameters
		as surrogate
FACILITY	169	monitoring of process or control device parameters
		as surrogate
FACILITY	170	record keeping/maintenance procedures
FACILITY	171	intermittent emission testing
		record keeping/maintenance procedures
FACILITY	172	
FACILITY	173	record keeping/maintenance procedures
FACILITY	174	record keeping/maintenance procedures
FACILITY	175	record keeping/maintenance procedures
FACILITY	176	record keeping/maintenance procedures
FACILITY	177	record keeping/maintenance procedures
FACILITY	178	
FACILITY FACILITY	178 179	record keeping/maintenance procedures record keeping/maintenance procedures



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FACILITY	180	record keeping/maintenance procedures
FACILITY	181	record keeping/maintenance procedures
FACILITY	182	record keeping/maintenance procedures
FACILITY	183	record keeping/maintenance procedures
FACILITY	184	record keeping/maintenance procedures
FACILITY	185	record keeping/maintenance procedures
FACILITY	186	record keeping/maintenance procedures
FACILITY	187	record keeping/maintenance procedures
FACILITY	188	record keeping/maintenance procedures
FACILITY	1-23	record keeping/maintenance procedures
FACILITY	190	record keeping/maintenance procedures
FACILITY	1-24	record keeping/maintenance procedures
FACILITY	1-25	record keeping/maintenance procedures
FACILITY	1-26	record keeping/maintenance procedures
FACILITY	193	record keeping/maintenance procedures
FACILITY	1-27	monitoring of process or control device parameters
		as surrogate
FACILITY	194	record keeping/maintenance procedures
FACILITY	195	record keeping/maintenance procedures
FACILITY	196	record keeping/maintenance procedures
FACILITY	197	work practice involving specific operations
FACILITY	198	record keeping/maintenance procedures
FACILITY	199	record keeping/maintenance procedures
FACILITY	200	record keeping/maintenance procedures
FACILITY	201	record keeping/maintenance procedures
FACILITY	202	record keeping/maintenance procedures
FACILITY	445	record keeping/maintenance procedures
FACILITY	203	record keeping/maintenance procedures
FACILITY	204	record keeping/maintenance procedures
FACILITY	205	record keeping/maintenance procedures
FACILITY	206	record keeping/maintenance procedures
FACILITY	207	record keeping/maintenance procedures
FACILITY	208	record keeping/maintenance procedures
FACILITY	209	record keeping/maintenance procedures
FACILITY	210 211	record keeping/maintenance procedures record keeping/maintenance procedures
FACILITY FACILITY	211	record keeping/maintenance procedures
FACILITY	212	record keeping/maintenance procedures
FACILITY	213	record keeping/maintenance procedures
FACILITY	215	record keeping/maintenance procedures
FACILITY	216	record keeping/maintenance procedures
FACILITY	217	record keeping/maintenance procedures
FACILITY	218	record keeping/maintenance procedures
FACILITY	219	work practice involving specific operations
FACILITY	220	record keeping/maintenance procedures
FACILITY	221	record keeping/maintenance procedures
FACILITY	222	record keeping/maintenance procedures
FACILITY	223	record keeping/maintenance procedures
FACILITY	224	record keeping/maintenance procedures
FACILITY	225	record keeping/maintenance procedures
FACILITY	226	record keeping/maintenance procedures
FACILITY	227	record keeping/maintenance procedures
FACILITY	228	work practice involving specific operations
FACILITY	229	record keeping/maintenance procedures
FACILITY	230	record keeping/maintenance procedures
FACILITY	231	record keeping/maintenance procedures
FACILITY	232	record keeping/maintenance procedures
FACILITY	233	record keeping/maintenance procedures
FACILITY	234	record keeping/maintenance procedures
FACILITY	235	record keeping/maintenance procedures
FACILITY	236	record keeping/maintenance procedures
FACILITY	237	record keeping/maintenance procedures
FACILITY	238	record keeping/maintenance procedures
FACILITY	239	record keeping/maintenance procedures



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FACILITY	240	record keeping/maintenance procedures
FACILITY	240	record keeping/maintenance procedures
FACILITY	446	record keeping/maintenance procedures
FACILITY	447	record keeping/maintenance procedures
FACILITY	448	monitoring of process or control device parameters
		as surrogate
FACILITY	449	monitoring of process or control device parameters
		as surrogate
FACILITY	450	record keeping/maintenance procedures
FACILITY	451	record keeping/maintenance procedures
FACILITY	452	record keeping/maintenance procedures
FACILITY	453	record keeping/maintenance procedures
FACILITY	454	record keeping/maintenance procedures
FACILITY	455	record keeping/maintenance procedures
FACILITY	456	record keeping/maintenance procedures
FACILITY	457	record keeping/maintenance procedures
FACILITY	458	record keeping/maintenance procedures
FACILITY	459	record keeping/maintenance procedures
FACILITY	460	record keeping/maintenance procedures
FACILITY	461	record keeping/maintenance procedures
FACILITY	462	record keeping/maintenance procedures
FACILITY	463	record keeping/maintenance procedures
FACILITY	464	record keeping/maintenance procedures
FACILITY	465	record keeping/maintenance procedures
FACILITY	466	record keeping/maintenance procedures
FACILITY	467	record keeping/maintenance procedures
FACILITY FACILITY	468 469	record keeping/maintenance procedures record keeping/maintenance procedures
FACILITY	469	record keeping/maintenance procedures record keeping/maintenance procedures
FACILITY	470	record keeping/maintenance procedures
FACILITY	472	record keeping/maintenance procedures
FACILITY	473	record keeping/maintenance procedures
FACILITY	474	record keeping/maintenance procedures
FACILITY	3-28	record keeping/maintenance procedures
FACILITY	3-29	record keeping/maintenance procedures
FACILITY	3-30	record keeping/maintenance procedures
FACILITY	3-31	record keeping/maintenance procedures
FACILITY	3-32	record keeping/maintenance procedures
FACILITY	3-33	record keeping/maintenance procedures
FACILITY	3-34	record keeping/maintenance procedures
FACILITY	3-35	record keeping/maintenance procedures
FACILITY	3-36	record keeping/maintenance procedures
FACILITY	252	record keeping/maintenance procedures
FACILITY	253	record keeping/maintenance procedures
FACILITY	254	record keeping/maintenance procedures
FACILITY	3 - 37	record keeping/maintenance procedures
FACILITY	3-38	record keeping/maintenance procedures
FACILITY	3-39	record keeping/maintenance procedures
FACILITY	3-40	record keeping/maintenance procedures
FACILITY	3-41	record keeping/maintenance procedures
FACILITY	3-42 3-43	record keeping/maintenance procedures
FACILITY FACILITY	3-43	record keeping/maintenance procedures record keeping/maintenance procedures
FACILITY	3-44	record keeping/maintenance procedures
FACILITY	3-45	record keeping/maintenance procedures
FACILITY	3-40	record keeping/maintenance procedures
FACILITY	3-48	record keeping/maintenance procedures
FACILITY	3-49	record keeping/maintenance procedures
FACILITY	3-50	record keeping/maintenance procedures
FACILITY	3-51	record keeping/maintenance procedures
FACILITY	3-52	record keeping/maintenance procedures
FACILITY	3-53	record keeping/maintenance procedures
FACILITY	3-54	record keeping/maintenance procedures
FACILITY	3-55	record keeping/maintenance procedures
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FACILITY	3-56	record keeping/maintenance procedures
FACILITY	3-57	record keeping/maintenance procedures
FACILITY	3-58	record keeping/maintenance procedures
FACILITY	3-59	record keeping/maintenance procedures
FACILITY	3-60	record keeping/maintenance procedures
FACILITY	3-61	record keeping/maintenance procedures
FACILITY	3-62	record keeping/maintenance procedures
FACILITY	3-63	record keeping/maintenance procedures
	3-63	record keeping/maintenance procedures record keeping/maintenance procedures
FACILITY		
FACILITY	3-65	record keeping/maintenance procedures
FACILITY	3-66	record keeping/maintenance procedures
FACILITY	3-67	record keeping/maintenance procedures
FACILITY	3-68	record keeping/maintenance procedures
FACILITY	3-69	record keeping/maintenance procedures
FACILITY	3 - 70	record keeping/maintenance procedures
FACILITY	3-71	record keeping/maintenance procedures
FACILITY	3-72	record keeping/maintenance procedures
FACILITY	3-73	record keeping/maintenance procedures
FACILITY	3-74	record keeping/maintenance procedures
FACILITY	3 - 75	record keeping/maintenance procedures
FACILITY	3-76	record keeping/maintenance procedures
FACILITY	3-77	record keeping/maintenance procedures
FACILITY	3-78	record keeping/maintenance procedures
FACILITY	3-79	record keeping/maintenance procedures
FACILITY	3-80	record keeping/maintenance procedures
FACILITY	3-81	record keeping/maintenance procedures
FACILITY	3-82	record keeping/maintenance procedures
FACILITY	475	record keeping/maintenance procedures
FACILITY	22	record keeping/maintenance procedures
FACILITY	23	record keeping/maintenance procedures
FACILITY	5	record keeping/maintenance procedures
FACILITY	25	record keeping/maintenance procedures
FACILITY	26	record keeping/maintenance procedures
FACILITY	27	record keeping/maintenance procedures
FACILITY	28	work practice involving specific operations
FACILITY	29	work practice involving specific operations work practice involving specific operations
		2 2 2
FACILITY	30	work practice involving specific operations
FACILITY FACILITY	30 31	work practice involving specific operations work practice involving specific operations
FACILITY FACILITY FACILITY	30 31 32	work practice involving specific operations work practice involving specific operations work practice involving specific operations
FACILITY FACILITY FACILITY FACILITY	30 31 32 33	work practice involving specific operations
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	30 31 32 33 34	work practice involving specific operations
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	30 31 32 33 34 35	work practice involving specific operations record keeping/maintenance procedures
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	30 31 32 33 34 35 36	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	30 31 32 33 34 35	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	30 31 32 33 34 35 36	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	30 31 32 33 34 35 36 37	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters
FACILITY	30 31 32 33 34 35 36 37 6 46	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37 6 46	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters
FACILITY	30 31 32 33 34 35 36 37 6 46	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37 6 46 55	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures
FACILITY	30 31 32 33 34 35 36 37 6 46 55	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures
FACILITY	30 31 32 33 34 35 36 37 6 46 55	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures sourrogate
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9 3-10	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9 3-10	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9 3-10	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9 3-10 3-11 3-12	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9 3-10	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9 3-10 3-11 3-12 3-13	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	30 31 32 33 34 35 36 37 6 46 55 56 3-8 3-9 3-10 3-11 3-12	work practice involving specific operations record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures record keeping/maintenance procedures record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters



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FACILITY	3-15	monitoring of process or control device parameters as surrogate
FACILITY	3-16	record keeping/maintenance procedures
FACILITY	3-17	monitoring of process or control device parameters as surrogate
FACILITY	3-18	monitoring of process or control device parameters as surrogate
FACILITY	3-19	monitoring of process or control device parameters as surrogate
FACILITY	3-20	monitoring of process or control device parameters as surrogate
FACILITY	3-21	record keeping/maintenance procedures
FACILITY	3-22	monitoring of process or control device parameters as surrogate
FACILITY	3-23	monitoring of process or control device parameters as surrogate
FACILITY	3-24	monitoring of process or control device parameters as surrogate
FACILITY	3-25	record keeping/maintenance procedures
FACILITY	73	monitoring of process or control device parameters as surrogate
FACILITY	74	monitoring of process or control device parameters as surrogate
FACILITY	75	record keeping/maintenance procedures
FACILITY	78	record keeping/maintenance procedures
FACILITY	79	record keeping/maintenance procedures
FACILITY	80	monitoring of process or control device parameters as surrogate
FACILITY	47	record keeping/maintenance procedures
FACILITY	48	record keeping/maintenance procedures
FACILITY	49	record keeping/maintenance procedures
FACILITY	50	record keeping/maintenance procedures
PACIBLII	50	record keeping/maintenance procedures
EV CII IUA	2 =	monitoring of progogg or gentral device parameters
FACILITY	3-5	monitoring of process or control device parameters as surrogate
FACILITY	51	as surrogate monitoring of process or control device parameters as surrogate
FACILITY FACILITY	51 53	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures
FACILITY FACILITY FACILITY	51 53 3-6	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate
FACILITY FACILITY FACILITY	51 53 3-6 1-1	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY FACILITY FACILITY FACILITY	51 53 3-6 1-1 1-2	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	51 53 3-6 1-1 1-2 1-4	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	51 53 3-6 1-1 1-2 1-4	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	51 53 3-6 1-1 1-2 1-4 1-5	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7 1-7	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7 1-7 1-8 1-9	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7 1-7 1-8 1-9 1-10	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7 1-7 1-8 1-9	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate
FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7 1-7 1-8 1-9 1-10	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters
FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7 1-7 1-8 1-9 1-10 1-11	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate
FACILITY	51 53 3-6 1-1 1-2 1-4 1-5 1-6 3-7 1-7 1-8 1-9 1-10 1-11 1-13	as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate record keeping/maintenance procedures monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate monitoring of process or control device parameters as surrogate



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		as surrogate
FACILITY	1-16	monitoring of process or control device parameters
		as surrogate
FACILITY	1-17	monitoring of process or control device parameters
		as surrogate
FACILITY	1-18	monitoring of process or control device parameters
		as surrogate
FACILITY	3-86	monitoring of process or control device parameters
		as surrogate
FACILITY	3-87	monitoring of process or control device parameters
		as surrogate
FACILITY	482	record keeping/maintenance procedures
FACILITY	483	record keeping/maintenance procedures
FACILITY	485	monitoring of process or control device parameters
		as surrogate
FACILITY	488	monitoring of process or control device parameters
		as surrogate
FACILITY	489	monitoring of process or control device parameters
		as surrogate
FACILITY	490	monitoring of process or control device parameters
		as surrogate
FACILITY	491	monitoring of process or control device parameters
		as surrogate
FACILITY	492	monitoring of process or control device parameters
		as surrogate
FACILITY	497	monitoring of process or control device parameters
		as surrogate
FACILITY	498	monitoring of process or control device parameters
		as surrogate
FACILITY	499	monitoring of process or control device parameters
DA GIL IMV	F00	as surrogate
FACILITY	500	monitoring of process or control device parameters
DA GII IMW	F00	as surrogate
FACILITY	502	monitoring of process or control device parameters
FACILITY	505	as surrogate
FACILITY	505	monitoring of process or control device parameters as surrogate
FACILITY	507	monitoring of process or control device parameters
FACILITI	507	as surrogate
FACILITY	508	monitoring of process or control device parameters
TACIBITI	300	as surrogate
FACILITY	81	work practice involving specific operations
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FACILITY	83	record keeping/maintenance procedures
FACILITY	93	intermittent emission testing
FACILITY	84	intermittent emission testing
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		as surrogate
FACILITY	3-26	monitoring of process or control device parameters
		as surrogate
FACILITY	87	intermittent emission testing
FACILITY	88	continuous emission monitoring (cem)
FACILITY	89	intermittent emission testing
FACILITY	90	record keeping/maintenance procedures
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FACILITY	92	record keeping/maintenance procedures
FACILITY	94	record keeping/maintenance procedures
FACILITY	95	record keeping/maintenance procedures
FACILITY	96	record keeping/maintenance procedures
FACILITY	97	record keeping/maintenance procedures
FACILITY	99	record keeping/maintenance procedures
FACILITY	3-27	record keeping/maintenance procedures
FACILITY	101	record keeping/maintenance procedures
FACILITY	102	record keeping/maintenance procedures



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FACILITY 103 record keeping/maintenance procedures FACILITY 104 record keeping/maintenance procedures

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Basis for Monitoring

6 NYCRR 212.9(b)

C-27018 Emission Point 23002

Water flow rate to the scrubber is monitored to meet required control efficiency. The lower limit of monitoring ensures compliance with all process operations. Engineering calculations is used as evidence of compliance with VOC control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

F-INISH Emission Point: 32028

Scrubber water flow during stripping is monitored to ensure sufficient control efficiency. The lower limit of monitoring ensures compliance with all process batch operations. Engineering calculations is used as evidence of compliance with contaminant control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

C-27018 Emission Point: 35006

The water flow to the scrubber is monitored to ensure the scrubber is operating at the required control efficiency.

6 NYCRR 212.9(b)

F-INISH Emission Point 32026, 32027

Condenser outlet temperature is monitored once per batch to ensure sufficient control efficiency. This process emits through two emission points 32026 and 32027. The upper limit of monitoring ensures compliance with all process batch operations. Engineering calculations is used as evidence of compliance with contaminant control efficiency when the measured temperature rises above the upper limit of monitoring.

6 NYCRR 212.9(b)

C-27018 Emission Point: 31041

Water flow to the scrubbers is monitored to ensure sufficient control efficiency. The lower limit of monitoring ensures compliance with all process batch operations. Engineering calculations is used as evidence of compliance with contaminant control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

C-27018 Emission Point 32050

Each condenser's outlet gas temperature is monitored when the ERP of non-VOCs



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(Octamethylcyclotetra Siloxane) exceeds 10 lb/hr and when "A" rated contaminant ERPs exceeds 1 lb/hr. This process emits through five emission points 32040, 32042, 32044, 32049 and 32050. Engineering calculations is used as evidence of compliance with control efficiency when the measured parameters exceeds the upper limit of monitoring.

6 NYCRR 212.9(b)

F-INISH Emission Point: 37016

For grade 88476 (main process) the condenser outlet gas temperature is maintained to ensure sufficient control efficiency. The upper limit of monitoring ensures compliance with all process batch operations. Engineering calculations is used as evidence of compliance with contaminant control efficiency when the measured temperature rises above the upper limit of monitoring.

6 NYCRR 212.9(b)

F-INISH Emission Point: 85008

Outlet temperature of condensing column 85TST is monitored to ensure sufficient control efficiency. The lower limit of monitoring ensures compliance with all process batch operations. Engineering calculations is used as evidence of compliance with contaminant control efficiency when the measured parameter exceeds the upper limit of monitoring.

6 NYCRR 212.9(b)

C-27018 Emission Point: 62005

The Venturi water flow (ES-62EVS) is monitored to ensure sufficient control efficiency. Engineering calculations is used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

C-27018 Emission Point 71001

Water scrubber flow creates the proper vacuum to operate the process and removes air contaminants. Water flow to the scrubber is recorded (on/off) to ensure sufficient control efficiency. The lower limit of monitoring ensures compliance with all process batch operations. Engineering calculations is used as evidence of compliance with contaminant control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

F-INISH Emission Points 24946, 24947

Water flow for eductor scrubber (24SRC) is recorded (on/off) to ensure sufficient control efficiency. This process is controlled by one eductor scrubber which emits through two emission points 24946 and 24947. The lower limit of monitoring ensures compliance with all process batch operations.

6 NYCRR 212.9(b)



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C-27018 Emission Point: 62011

The Venturi water flow (ES-62WVS) is monitored to ensure sufficient control efficiency. Engineering calculations is used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

C-27018 Emission Point: 62005

The tower water flow (ES-62EST) is monitored to ensure sufficient control efficiency. Engineering calculations is used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

F-INISH Emission Point: 71013

Water flow to the scrubber is recorded (on/off) to ensure sufficient control efficiency.

6 NYCRR 212.9(b)

C-27018 Emission Point 35031

Scrubber water flow rate is monitored to ensure it is greater than or equal to 3 gallons per minute. Engineering calculations is used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

C-27018 Emission Point 27018

The water flow to the scrubber is monitored to ensure the scrubber is operating at the required control efficiency. Engineering calculations is used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring.

6 NYCRR 212.9(b)

C-27018 Emission Point: 24944, 24945

High acid scrubber water flow is recorded (on/off) for each batch to ensure sufficient control efficiency.

6 NYCRR 212.9(b)

C-27018 Emission Point: 62011

The tower water flow (62WST) is monitored to ensure sufficient control efficiency. Engineering calculations is used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring.

6NYCRR 243-1.6(c)

As of the allowance transfer deadline for a control period, the owners and operators of



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each CAIR NOx Ozone Season source and each CAIR NOx Ozone Season unit at the source shall hold, in the source's compliance account, CAIR NOx Ozone Season allowances available for compliance deductions for the control period under section 243-6.5(a) in an amount not less than the tons of total nitrogen oxides emissions for the control period from all CAIR NOx Ozone Season units at the source, as determined in accordance with Subpart 243-8. The CAIR NOx ozone season is the period beginning May 1 of a calendar year, except as provided in section 243-1.6(c)(2), and ending on September 30 of the same year, inclusive.

A CAIR NOx Ozone Season unit shall be subject to the requirements under paragraph (c)(1) of this section for the control period starting on the later of May 1, 2009 or the deadline for meeting the unit's monitor certification requirements under sections 243-8.1(b)(1), (2), (3), or (7) and for each control period thereafter.

A CAIR NOx Ozone Season allowance shall not be deducted, for compliance with the requirements under paragraph (c)(1) of this section, for a control period in a calendar year before the year for which the CAIR NOx Ozone Season allowance was allocated. CAIR NOx Ozone Season allowances shall be held in, deducted from, or transferred into or among CAIR NOx Ozone Season Allowance Tracking System accounts in accordance with Subparts 243-6, 243-7, and 243-9.

A CAIR NOx Ozone Season allowance is a limited authorization to emit one ton of nitrogen oxides in accordance with the CAIR NOx Ozone Season Trading Program. No provision of the CAIR NOx Ozone Season Trading Program, the CAIR permit application, the CAIR permit, or an exemption under section 243-1.5 and no provision of law shall be construed to limit the authority of the State or the United States to terminate or limit such authorization.

A CAIR NOx Ozone Season allowance does not constitute a property right.

Upon recordation by the Administrator under Subpart 243-6, 243-7, or 243-9, every allocation, transfer, or deduction of a CAIR NOx Ozone Season allowance to or from a CAIR NOx Ozone Season source's compliance account is incorporated automatically in any CAIR permit of the source.

6NYCRR 243-1.6(d)

If a CAIR NOx Ozone Season source emits nitrogen oxides during any control period in excess of the CAIR NOx Ozone Season emissions limitation, then:

(1) the owners and operators of the source and each CAIR NOx Ozone Season unit at the source shall surrender the CAIR NOx Ozone Season allowances required for deduction



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under section 243-6.5(d)(1) and pay any fine, penalty, or assessment or comply with any other remedy imposed, for the same violations, under the Act or applicable State law; and

(2) each ton of such excess emissions and each day of such control period shall constitute a separate violation of this Subpart, the Act, and applicable State law.

6NYCRR 243-1.6(e)

Unless otherwise provided, the owners and operators of the CAIR NOx Ozone Season source and each CAIR NOx Ozone Season unit at the source shall keep on site at the source each of the following documents for a period of five years from the date the document is created. This period may be extended for cause, at any time before the end of five years, in writing by the department or the Administrator.

- (i) The certificate of representation under section 243-2.4 for the CAIR designated representative for the source and each CAIR NOx Ozone Season unit at the source and all documents that demonstrate the truth of the statements in the certificate of representation; provided that the certificate and documents shall be retained on site at the source beyond such five-year period until such documents are superseded because of the submission of a new certificate of representation under section 243-2.4 changing the CAIR designated representative.
- (ii) All emissions monitoring information, in accordance with Subpart 243-8, provided that to the extent that Subpart 243-8 provides for a three-year period for recordkeeping, the three-year period shall apply.
- (iii) Copies of all reports, compliance certifications, and other submissions and all records made or required under the CAIR NOx Ozone Season Trading Program.
- (iv) Copies of all documents used to complete a CAIR permit application and any other submission under the CAIR NOx Ozone Season Trading Program or to demonstrate compliance with the requirements of the CAIR NOx Ozone Season Trading Program.

6NYCRR 243-8.1

The owners and operators, and to the extent applicable, the CAIR designated representative, of a CAIR NOx Ozone Season unit, shall comply with the monitoring, recordkeeping, and reporting requirements as provided in this Subpart and in Subpart H of 40 CFR Part 75. For purposes of complying with such requirements, the definitions in section 243-1.2 and in 40 CFR 72.2 shall apply, and the terms "affected unit," "designated representative," and "continuous emission monitoring system" (or "CEMS") in 40 CFR Part 75 shall be deemed to refer to the terms "CAIR NOx Ozone Season unit," "CAIR



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designated representative," and "continuous emission monitoring system" (or "CEMS") respectively, as defined in section 243-1.2. The owner or operator of a unit that is not a CAIR NOx Ozone Season unit but that is monitored under 40 CFR 75.72(b)(2)(ii) shall comply with the same monitoring, recordkeeping, and reporting requirements as a CAIR NOx Ozone Season unit.

Requirements for installation, certification, and data accounting.' The owner or operator of each CAIR NOx Ozone Season unit shall:

- (1) install all monitoring systems required under this Subpart for monitoring NOx mass emissions and individual unit heat input (including all systems required to monitor NOx emission rate, NOx concentration, stack gas moisture content, stack gas flow rate, CO2 or O2 concentration, and fuel flow rate, as applicable, in accordance with 40 CFR 75.71 and 40 CFR 75.72);
- (2) successfully complete all certification tests required under section 243-8.2 and meet all other requirements of this Subpart and 40 CFR Part 75 applicable to the monitoring systems under paragraph (a)(1) of this section; and
- (3) record, report, and quality-assure the data from the monitoring systems under paragraph (a)(1) of this section.

6NYCRR 243-8.1

No owner or operator of a CAIR NOx Ozone Season unit shall use any alternative monitoring system, alternative reference method, or any other alternative to any requirement of this Subpart without having obtained prior written approval in accordance with section 243-8.6.

No owner or operator of a CAIR NOx Ozone Season unit shall operate the unit so as to discharge, or allow to be discharged, NOx emissions to the atmosphere without accounting for all such emissions in accordance with the applicable provisions of this Subpart and 40 CFR Part 75.

No owner or operator of a CAIR NOx Ozone Season unit shall disrupt the continuous emission monitoring system, any portion thereof, or any other approved emission monitoring method, and thereby avoid monitoring and recording NOx mass emissions discharged into the atmosphere or heat input, except for periods of recertification or periods when calibration, quality assurance testing, or maintenance is performed in accordance with the applicable provisions of this Subpart and 40 CFR Part 75.

No owner or operator of a CAIR NOx Ozone Season unit shall retire or permanently



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discontinue use of the continuous emission monitoring system, any component thereof, or any other approved monitoring system under this Subpart, except under any one of the following circumstances:

- (i) during the period that the unit is covered by an exemption under section 243-1.5 that is in effect;
- (ii) the owner or operator is monitoring emissions from the unit with another certified monitoring system approved, in accordance with the applicable provisions of this Subpart and 40 CFR Part 75, by the department for use at that unit that provides emission data for the same pollutant or parameter as the retired or discontinued monitoring system; or (iii) the CAIR designated representative submits notification of the date of certification testing of a replacement monitoring system for the retired or discontinued monitoring system in accordance with section 243-8.2(d)(3)(i).

6NYCRR 243-8.3

Whenever any monitoring system fails to meet the quality-assurance and quality-control requirements or data validation requirements of 40 CFR Part 75, data shall be substituted using the applicable missing data procedures in Subpart D or Subpart H of, or appendix D or appendix E to, 40 CFR Part 75.

6NYCRR 243-8.5(d)

The CAIR designated representative shall submit quarterly reports, as follows:

If the CAIR NOx Ozone Season unit is subject to an Acid Rain emissions limitation or a CAIR NOx emissions limitation or if the owner or operator of such unit chooses to report on an annual basis under this Subpart, the CAIR designated representative shall meet the requirements of Subpart H of 40 CFR Part 75 (concerning monitoring of NOx mass emissions) for such unit for the entire year and shall report the NOx mass emissions data and heat input data for such unit, in an electronic quarterly report in a format prescribed by the Administrator, for each calendar quarter beginning with:

- (i) for a unit that commences commercial operation before July 1, 2007, the calendar quarter covering May 1, 2008 through June 30, 2008;
- (ii) for a unit that commences commercial operation on or after July 1, 2007, the calendar quarter corresponding to the earlier of the date of provisional certification or the applicable deadline for initial certification under section 243-8.1(b), unless that quarter is the third or fourth quarter of 2007 or the first quarter of 2008, in which case reporting shall commence in the quarter covering May 1, 2008 through June 30, 2008.

The CAIR designated representative shall submit each quarterly report to the



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Administrator within 30 days following the end of the calendar quarter covered by the report. Quarterly reports shall be submitted in the manner specified in 40 CFR 75.73(f).

For CAIR NOx Ozone Season units that are also subject to an Acid Rain emissions limitation or the CAIR NOx Annual Trading Program, CAIR SO2 Trading Program, or the Mercury Reduction Program for Coal-Fired Electric Utility Steam Generating Units (6 NYCRR Part 246), quarterly reports shall include the applicable data and information required by Subparts F through I of 40 CFR Part 75 as applicable, in addition to the NOx mass emission data, heat input data, and other information required by this Subpart.

6NYCRR 243-8.5(e)

The CAIR designated representative shall submit to the Administrator a compliance certification (in a format prescribed by the Administrator) in support of each quarterly report based on reasonable inquiry of those persons with primary responsibility for ensuring that all of the unit's emissions are correctly and fully monitored. The certification shall state that:

- (1) the monitoring data submitted were recorded in accordance with the applicable requirements of this Subpart and 40 CFR Part 75, including the quality assurance procedures and specifications;
- (2) for a unit with add-on NOx emission controls and for all hours where NOx data are substituted in accordance with 40 CFR 75.34(a)(1), the add-on emission controls were operating within the range of parameters listed in the quality assurance/quality control program under appendix B to 40 CFR Part 75 and the substitute data values do not systematically underestimate NOx emissions; and
- (3) for a unit that is reporting on a control period basis under subparagraph (d)(2)(ii) of this section, the NOx emission rate and NOx concentration values substituted for missing data under Subpart D of 40 CFR Part 75 are calculated using only values from a control period and do not systematically underestimate NOx emissions.

40 CFR 60.48c(g)(2) Subpart Dc

Emission Unit: U-28002 Process: 410 & 411 Emission Unit: H-OFURN Process: 418 & 426

This facility currently does not have the fuel oil line connected to Boiler #18 and therefore, cannot operate Process 411. The facility also has not replaced the burners of the 21 or 35 Hot Oil Furnaces of Process 426. After these Processes becomes operable, the certification will become applicable to the respective Process 411 and 426.



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Any owner or operator subject to this part shall furnish the Administrator with the following information:

- 1) a notification of the date construction or reconstruction commenced, post marked no later than 30 days after such date;
- 2) a notification of the anticipated date of initial start up, post marked not more than 60 days not less than 30 days prior to such date;
- 3) a notification of the actual date of initial start up, post marked within 15 days after such date;
- 4) a notification of any physical or operational change to an existing facility which may increase the emission rate of any air pollutant to which a standard applies, unless the change is specifically exempted under this part. The notice shall be post marked 60 days or as soon as practicable before the change is commenced and shall include information describing the precise nature of the change, present and proposed emission control systems, productive capability of the facility before and after the change, and the expected completion date of the change. The Administrator may request additional information regarding the change;
- 5) a notification of any physical or operational change to an existing facility which may increase the emission rate of any air pollutant to which a standard applies, unless the change is specifically exempted under 40 CFR Part 60. The notice shall be post marked 60 days or as soon as practicable before the change is commenced and shall include information describing the precise nature of the change, present and proposed emission control systems, productivity capability of the facility before and after the change, and the expected completion date of the change. The Administrator and/or this Department may request additional information regarding the change.

40 CFR 63.139(c)

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Process 422 Emission Source WTPAS

Process 424 Emission Source WTPAS

Process 424 Emission Source WTPAS

Process 425 Emission Source WTPAS

The control device shall be designed and operated in accordance with paragraph (c)(1), (c)(2), (c)(3), (c)(4), or (c)(5) of this section.

(5) Any other control device used shall, alone or in combination with other control devices, reduce the total organic compound emissions, less methane and ethane, or total organic hazardous air pollutants emissions vented to the control device by 95 percent by weight or greater or achieve an outlet total organic compound concentration, less methane and ethane, or total organic hazardous air pollutants concentration of 20 parts per million by volume, whichever is less stringent. The 20 parts per million by volume performance standard is not applicable to compliance with the provisions of §63.134 or §63.135 of this



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subpart.

Emissions from these sources (PKSDT, 30WWT, and 20KEQ) will be vented to the RKI (RKIAB) or Fixed Box #2 Incinerator (FBIAB).

40 CFR 63.140

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Process 422 Emission Source WTPAS Process 424 Emission Source WTPAS Process 424 Emission Source WTPAS Process 425 Emission Source WTPAS

- (a) Delay of repair of equipment for which a control equipment failure or a gap, crack, tear, or hole has been identified, is allowed if the repair is technically infeasible without a shutdown, as defined in §63.101 of subpart F of this part, or if the owner or operator determines that emissions of purged material from immediate repair would be greater than the emissions likely to result from delay of repair. Repair of this equipment shall occur by the end of the next shutdown.
- (b) Delay of repair of equipment for which a control equipment failure or a gap, crack, tear, or hole has been identified, is allowed if the equipment is emptied or is no longer used to treat or manage Group 1 wastewater streams or residuals removed from Group 1 wastewater streams.
- (c) Delay of repair of equipment for which a control equipment failure or a gap, crack, tear, or hole has been identified is also allowed if additional time is necessary due to the unavailability of parts beyond the control of the owner or operator. Repair shall be completed as soon as practical. The owner or operator who uses this provision shall comply with the requirements of §63.147(b)(7) to document the reasons that the delay of repair was necessary.

40 CFR 63.143(e)

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(e) Except as provided in paragraphs (e)(4) and (e)(5) of this section, for each control device used to comply with the requirements of §§63.133 through 63.139 of this subpart, the owner or operator shall comply with the requirements in §63.139(d) of this subpart, and with the requirements specified in paragraph (e)(1), (e)(2), or (e)(3) of this section.

40 CFR 63.143(g)

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Process 424 Emission Source WTPAS Process 424 Emission Source WTPAS Process 425 Emission Source WTPAS

Monitoring equipment shall be installed, calibrated, and maintained according to the manufacturer's specifications or other written procedures that provide adequate assurance that the equipment would reasonably be expected to monitor accurately.

40CFR63.145(h)

Emission Unit: C-27018 Emission Unit: C-27035 Emission Unit: F-INISH

When Group 1 wastewaters are treated using the biosystems, the Volatile Suspended Solids (VSS) will be sampled quarterly to demonstrate enhanced biological treatment. If the VSS concentration falls below 1000 mg/L, WATER9 modeling will be used to demonstrate 99% removal by biological treatment.

40 CFR 63.998(a)(2)

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F-INISH

- (i) Upon request, the owner or operator shall make available to the Administrator such records as may be necessary to determine the conditions of performance tests performed pursuant to §§63.988(b), 63.990(b), 63.994(b), or 63.995(b).
- (ii) Nonflare control device and halogen reduction device performance test records.
- (A) General requirements. Each owner or operator subject to the provisions of this subpart shall keep up-to-date, readily accessible continuous records of the data specified in paragraphs (a)(2)(ii)(B) through (C) of this section, as applicable, measured during each performance test performed pursuant to \$63.988(b), \$63.990(b), \$63.994(b), or \$63.995(b), and also include that data in the Notification of Compliance Status required under \$63.999(b). The same data specified in this section shall be submitted in the reports of all subsequently required performance tests where either the emission control efficiency of a combustion device, or the outlet concentration of TOC or regulated material is determined.

This permit condition becomes effective on the compliance date of May 10, 2008.

40 CFR 63.998(a)(2)

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(B) Nonflare combustion device. Where an owner or operator subject to the provisions of this paragraph seeks to demonstrate compliance with a percent reduction requirement or a



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parts per million by volume requirement using a nonflare combustion device the information specified in (a)(2)(ii)(B)(1) through (6) of this section shall be recorded.

(D) Halogen reduction devices. When using a scrubber following a combustion device to control a halogenated vent stream, record the information specified in paragraphs (a)(2)(ii)(D)(1) through (3) of this section.

40 CFR 63.998(a)(2)

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(C) Other nonflare control devices. Where an owner or operator seeks to use an absorber, condenser, or carbon adsorber as a control device, the information specified in paragraphs (a)(2)(ii)(C)(1) through (5) of this section shall be recorded, as applicable.

40 CFR 63.1203(a)(5)(i)

This condition was revised to expire 10/14/08 when the identical condition under 40 CFR 63.1219(a) becomes effective.

When Group 1 wastewaters are treated using the biosystems, the Volatile Suspended Solids (VSS) will be sampled quarterly to demonstrate enhanced biological treatment. If the VSS concnetration falls below 1000 mg/L, WATER9 modeling will be used to demonstrate 99% removal by biological treatment.

40 CFR 63.1209(j)(2)

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Emission Points: 97001, 97002 & 97003

As an indicator of gas residence time in the control device, you must establish and comply with a limit on the maximum flue gas flowrate, the maximum production rate, or another parameter that you document in the site-specific test plan as an appropriate surrogate for gas residence time, as the average of the maximum hourly rolling averages for each run and you must comply with this limit on a hourly rolling average basis.

If the monitored parameter exceeds the limitation, the automatic waste feed cutoff must immediately and automatically cut off of the hazardous waste feed, except as provided by Section 63.1206(c)(3)(viii). In accordance with 63.1206(c)(2)(v)(2), an exceedance of this emission standard is not a violation of 40 CFR Part 63, Subpart EEE if you take the corrective measures prescribed in the startup, shutdown, and malfunction plan.

This condition also satisfies the requirements of:



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40 CFR 63.1209(k)(3), dioxins and furans – maximum flue gas flowrate or production rate

40 CFR 63.1209(m)(2), particulate matter – maximum flue gas flow rate or production rate

40 CFR 63.1209(n)(5), semivolatile metals and low volatility metals - maximum flue gas flow rate or production rate

40 CFR 63.1209(o)(3)(v), hydrogen chloride and chlorine gas – wet scrubber

40 CFR 63.1209(j)(3)

C-27018 Process: 422, 423

You must establish limits on the maximum pumpable and total (i.e., pumpable and nonpumpable) hazardous waste feedrate for each location where hazardous waste is fed, you must establish the limits as the average of the maximum hourly rolling averages for each run, and you must comply with the feedrate limit(s) on a hourly rolling average basis. If the monitored parameter exceeds the limitation, the automatic waste feed cutoff must immediately and automatically cut off of the hazardous waste feed, except as provided by Section 63.1206(c)(3)(viii). In accordance with 63.1206(c)(2)(v)(2), an exceedance of this emission standard is not a violation of 40 CFR Part 63, Subpart EEE if you take the corrective measures prescribed in the startup, shutdown, and malfunction plan. The total hazardous waste feed rate is monitored continuously and is limited to a maximum of 751 pounds per hour on an hourly rolling average basis. This condition also satisfies the requirements of 40 CFR 63.1209(k)(4), dioxins and furans – maximum hazardous waste federate.

40 CFR 63.1209(j)(4)

C-27018 Process: 422, 423

You must specify operating parameters and limits to ensure that good operation of each hazardous waste firing system is maintained.

If the monitored parameter exceeds the limitation, the automatic waste feed cutoff must immediately and automatically cut off of the hazardous waste feed, except as provided by Section 63.1206(c)(3)(viii). In accordance with 63.1206(c)(2)(v)(2), an exceedance of this emission standard is not a violation of 40 CFR Part 63, Subpart EEE if you take the corrective measures prescribed in the startup, shutdown, and malfunction plan.

Air atomization pressure is monitored continuously and is maintained at a minimum of 78 on an hourly rolling average basis.

40 CFR 63.1209(i)(4)

C-27018 Process: 424, 425



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You must specify operating parameters and limits to ensure that good operation of each hazardous waste firing system is maintained. If the monitored parameter exceeds the limitation, the automatic waste feed cutoff must immediately and automatically cut off of the hazardous waste feed, except as provided by Section 63.1206(c)(3)(viii). In accordance with 63.1206(c)(2)(v)(2), an exceedance of this emission standard is not a violation of 40 CFR Part 63, Subpart EEE if you take the corrective measures prescribed in the startup, shutdown, and malfunction plan. Steam atomization pressure is monitored continuously and is maintained at a minimum of 80.6 psig on an hourly rolling average basis.

40 CFR 63.1209(j)(4)

C-27018 Process: 422, 423

You must specify operating parameters and limits to ensure that good operation of each hazardous waste firing system is maintained. If the monitored parameter exceeds the limitation, the automatic waste feed cutoff must immediately and automatically cut off of the hazardous waste feed, except as provided by Section 63.1206(c)(3)(viii). In accordance with 63.1206(c)(2)(v)(2), an exceedance of this emission standard is not a violation of 40 CFR Part 63, Subpart EEE if you take the corrective measures prescribed in the startup, shutdown, and malfunction plan. Steam atomization pressure is monitored continuously and is maintained at a minimum of 126 psig on an hourly rolling average basis.

40 CFR 63.1209(m)(1)(i)(B)(1)

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Process: 422 Emission Source: IWS1A
Process: 422 Emission Source: IWS1B
Process: 422 Emission Source: IWS1C
Process: 422 Emission Source: IWS2A
Process: 422 Emission Source: IWS2B
Process: 422 Emission Source: IWS2B
Process: 423 Emission Source: IWS1A
Process: 423 Emission Source: IWS1B
Process: 423 Emission Source: IWS1C
Process: 423 Emission Source: IWS2A
Process: 423 Emission Source: IWS2A
Process: 423 Emission Source: IWS2A
Process: 423 Emission Source: IWS2B
Process: 423 Emission Source: IWS2C

For sources equipped with wet scrubbers, including ionizing wet scrubbers, high energy wet scrubbers such as venturi, hydrosonic, collision, or free jet wet scrubbers, and low energy wet scrubbers, you must establish limits to ensure that the solids content of the scrubber liquid does not exceed levels (established) during the performance test, by either



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(i) Establishing a limit on solids content of the scrubber liquid using a CMS or by manual sampling and analysis; or (ii) Establishing a minimum blowdown rate using a CMS and either a minimum scrubber tank volume or liquid level using a CMS. If you elect to monitor solids content manually, you must sample and analyze the scrubber liquid hourly unless you support an alternative monitoring frequency in the performance test plan that you submit for review and approval. If the monitored parameter exceeds the limitation, the automatic waste feed cutoff must immediately and automatically cut off of the hazardous waste feed, except as provided by Section 63.1206(c)(3)(viii). In accordance with 63.1206(c)(2)(v)(2), an exceedance of this emission standard is not a violation of 40 CFR Part 63, Subpart EEE if you take the corrective measures prescribed in the startup, shutdown, and malfunction plan. The facility IWS system has a constant overflow sump instead of a recirculating tank system. Compliance with the requirement is achieved with a minimum IWS voltage of 17 kV for each IWS unit.

40 CFR 63.1209(p)

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Process: 422 ES/C: 96RKI Process: 423 ES/C: 96RKI

This condition reduces the emissions of hazardous air pollutants by requiring the facility to keep the pressure inside of the combustion chamber of the hazardous waste combustor under that of the atmosphere outside of the combustor. This reduces the chance of leaks from the combustor escaping into the atmosphere.

40 CFR 63.2450(f)

C-27018 Emission Point 62007

If you use a halogen reduction device to reduce hydrogen halide and halogen HAP emissions from halogenated vent streams, you must meet the requirements of §63.994 and the requirements referenced therein. If you use a halogen reduction device before a combustion device, you must determine the halogen atom emission rate prior to the combustion device according to the procedures in §63.115(d)(2)(v).

40CFR 63.2455(a), Subpart FFFF

Emission Unit: F-INISH Emission Point: 76006

Water flow to the third stage of the scrubber will be monitored to ensure sufficient control efficiency. The lower limit of monitoring ensures compliance with all process batch operations under 6 NYCRR 212.9(b). Engineering calculations will be used as evidence of compliance under 6 NYCRR 212.9(b) with contaminant control efficiency when the measured flow rate falls below the lower limit of monitoring. Compliance with this monitoring requirement assures compliance with Subpart FFFF 63.2465(a) and 212.9(b) per the Pre-Compliance Report.



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40CFR 63.2455(a), Subpart FFFF

Emission Unit: F-INISH Emission Point: 76006

Water flow to the second stage of the scrubber will be monitored to ensure sufficient control efficiency. The lower limit of monitoring ensures compliance with all process batch operations under 6 NYCRR 212.9(b). Engineering calculations will be used as evidence of compliance under 6 NYCRR 212.9(b) with contaminant control efficiency when the measured flow rate falls below the lower limit of monitoring. Compliance with this monitoring requirement assures compliance with Subpart FFFF 63.2465(a) and 212.9(b) per the Pre-Compliance Report.

40CFR 63.2455(a), Subpart FFFF

Emission Unit: F-INISH Emission Point: 76006

Water flow to the first stage of the scrubber will be monitored to ensure sufficient control efficiency. The lower limit of monitoring ensures compliance with all process batch operations under 6 NYCRR 212.9(b). Engineering calculations will be used as evidence of compliance under 6 NYCRR 212.9(b) with contaminant control efficiency when the measured flow rate falls below the lower limit of monitoring. Compliance with this monitoring requirement assures compliance with Subpart FFFF 63.2465(a) and 212.9(b) per the Pre-Compliance Report.

40CFR 63.2455(a), Subpart FFFF

Emission Unit: C-27018 Emission Point: 62007

The scrubber water flow (ES-MCSVS) is monitored to ensure sufficient control efficiency. Engineering calculations will be used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring. Compliance with this monitoring requirement assures compliance with Subpart FFFF 63.2465(a) and 212.9(b) per the Pre-Compliance Report.

40CFR 63.2455(a), Subpart FFFF

F-INISH Emission Point 76006

Spray tower flow rate will be monitored to ensure sufficient control efficiency. The lower limit of monitoring ensures compliance with all process batch operations under 6 NYCRR 212.9(b). Engineering calculations will be used as evidence of compliance under 6 NYCRR 212.9(b) with contaminant control efficiency when the measured flow rate falls below the lower limit of monitoring. Compliance with this monitoring requirement assures compliance with Subpart FFFF 63.2465(a) and 212.9(b) per the Pre-Compliance Report.



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40CFR 63.2465(a), Subpart FFFF

Emission Unit: C-27018 Emission Point: 76001

A flow meter is used to monitor the water flow rate to the scrubber to ensure sufficient control efficiency. Engineering calculations will be used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring. Compliance with this monitoring requirement assures compliance with 212.9(b) per the Pre-Compliance Report.

40CFR 63.2465(a), Subpart FFFF

Emission Unit: C-27018 Emission Point: 35017

The water flow to the scrubber is monitored to ensure the scrubber is operating at the required control efficiency. Engineering calculations will be used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring. Compliance with this monitoring requirement assures compliance with 212.9(b) per the Pre-Compliance Report.

40CFR 63.2465(a), Subpart FFFF

Emission Unit: C-27018 Emission Point: 27024

The scrubber temperature will be monitored to ensure the scrubber is operating at the required control efficiency. Engineering calculations will be used as evidence of compliance with control efficiency when the measured parameter exceeds the upper limit of monitoring. Compliance with this monitoring requirement assures compliance with 212.9(b) per the Pre-Compliance Report.

40CFR 63.2465(a), Subpart FFFF

Emission Unit: C-27035 Emission Point: 27035

The packed tower water scrubber flow is maintained at a minimum of 5 gpm to ensure 99% control efficiency for Part 212. Engineering calculations will be used as evidence of compliance with control efficiency when the measured flow rate falls below the lower limit of monitoring. Compliance with this monitoring requirement assures compliance with 212.9(b) per the Pre-Compliance Report.

40CFR 63.162(c), Subpart H Emission Unit: C-27018

Process: 400 Emission Source: FUGTV

Each piece of equipment to which Subpart H applies shall be identified such that it can be

distinguished readily from equipment that is not subject to Subpart H. This does not



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require physical tagging, but may be identified on a plant site plan, log entries, or by designation of process unit boundaries by some form of weatherproof identification.

40CFR 63.104, Subpart F Emission Unit: C-27018

Process: 406 Emission Source: HXCWW

Delay of repair is allowed for heat exchanger system leaks in the following situations:

- 1) If the equipment that is isolated from the process, or
- 2) If the repair is technically infeasible without a shutdown, and one of the following is true:
- a) A shutdown is expected within two months after the delay of repair is determined to be necessary. Repair may be delayed until that shutdown.
- b) A shutdown is not expected within the next two months and a shutdown to repair the leaking equipment would result in greater emissions than delaying repair. In this case the owner/operator shall document the items listed in 63.104(e)(2)(i)(A) and (B) and delay the repair until the next shutdown.
- c) A shutdown is not expected within the next two months and the owner/operator does not determine that the shutdown would result in greater emissions than a delay of repair. The owner/operator may delay the repair for 120 days. The owner/owner shall demonstrate that the necessary parts or personnel were not available

The owner/operator shall submit the following in the next semiannual report:

- 1) the presence of a leak and the date the leak was detected
- 2) whether the leak has been repaired
- 3) the reason(s) for the delay of repair
- 4) the expected date of repair if not repaired
- 5) the date of successful repair of the leak

40CFR 63.104, Subpart F Emission Unit: C-27018

Process: 406 Emission Source: HXCWW

If a leak is detected, it shall be repaired as soon as practical but not later than 45 calendar days after the owner/operator is notified of the results indicating a leak. The owner/operator shall confirm the repair within 7 days of the repair or startup, whichever is later.

The owner/operator shall retain the following records:

- records of any leaks detected
- monitoring data indicating the presence of a leak
- date(s) of the leak's detection
- date(s) of efforts to repair leak(s)



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- method and date of confirmation of leak(s)